

The SEMATECH high-NA actinic reticle review project, an EUV mask-imaging microscope

Kenneth A. Goldberg

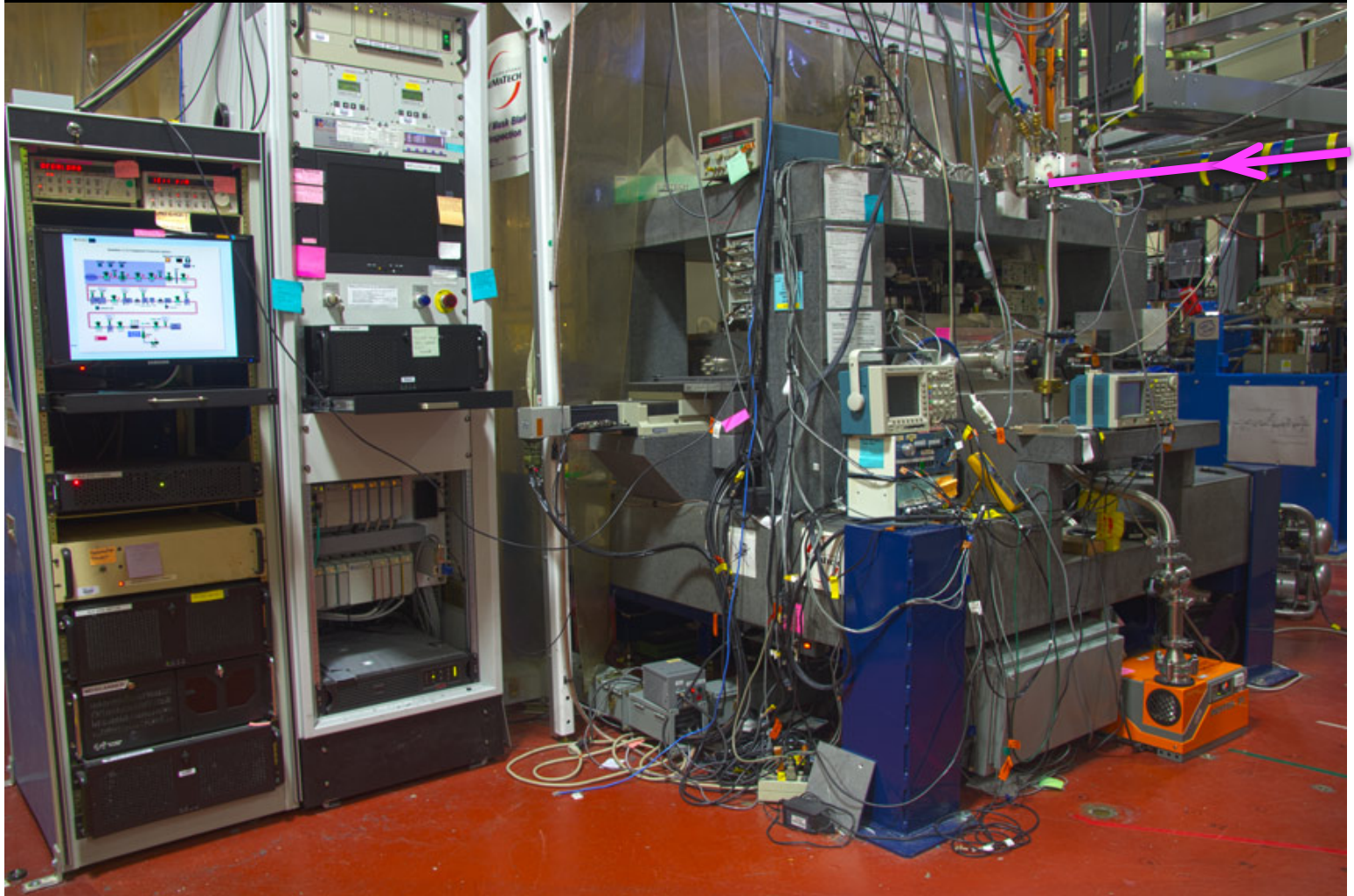
Lawrence Berkeley National Laboratory

I. Mochi, M. P. Benk, **C. C. Lin**, A. Allezy, M. Dickinson, C. Cork, J. Macdougall, E. H. Anderson, W. Chao, F. Salmassi, R. Delano, D. Zehm, A. Pekedis, J. DePonte, T. Katayanagi, W. Cork, E. Martin, P. P. Naulleau, S. B. Rekawa



SHARP
SEMATECH HIGH-NA ACTINIC
RETICLE REVIEW PROJECT





AIT: 2004–2012 *Retired*

Source: Synchrotron

Optics: Zoneplate-lenses

4×NA: 0.25–0.625

σ : Programmable

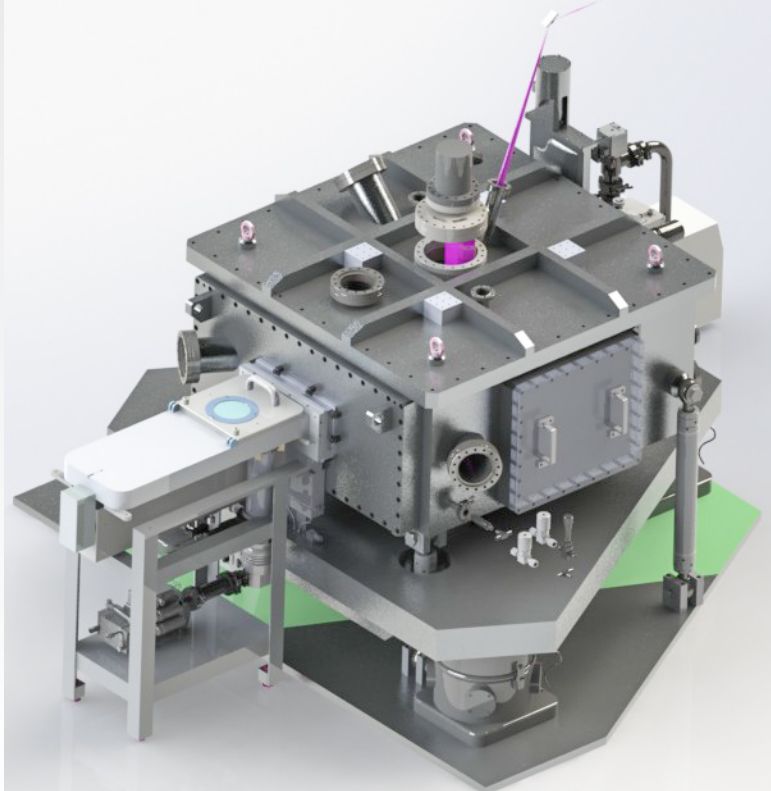
Nav: Full-mask xy

Speed: 5–10 series/hr

Vibration Isolation

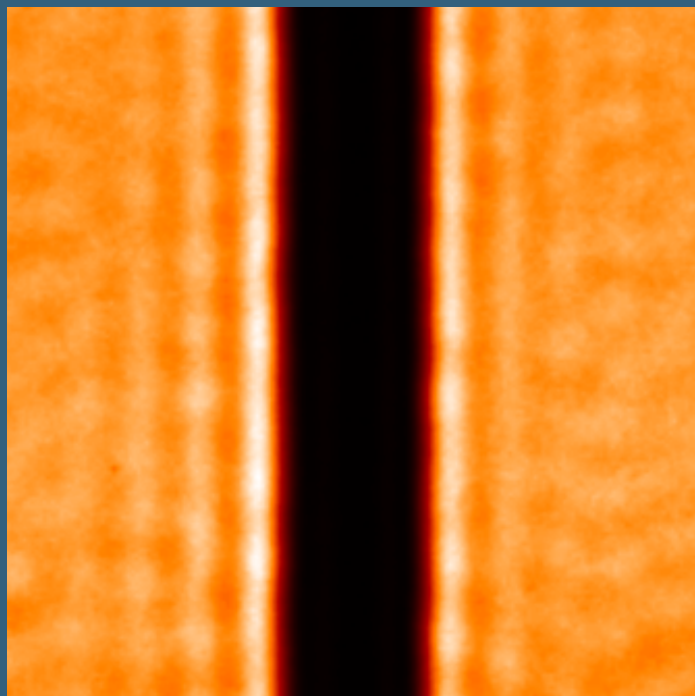
SHARP

SEMATECH HIGH-NA ACTINIC
RETICLE REVIEW PROJECT

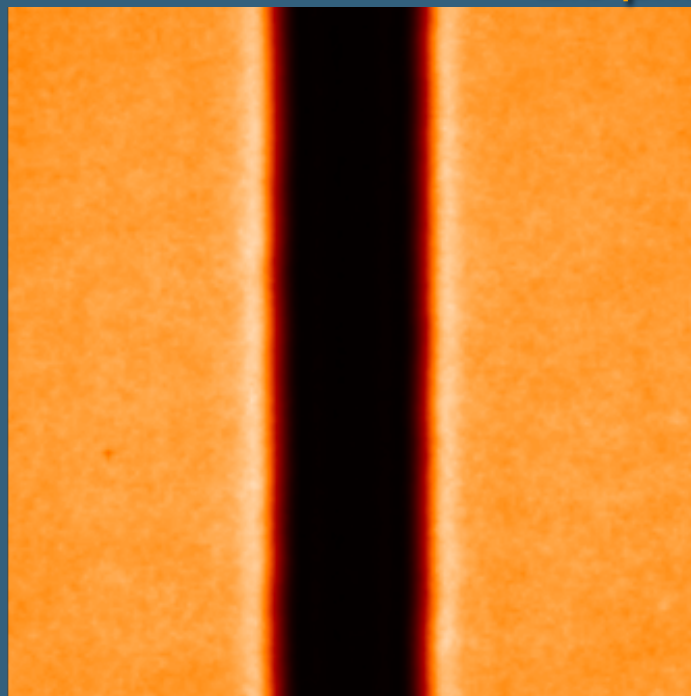


**Coherence control
is important**

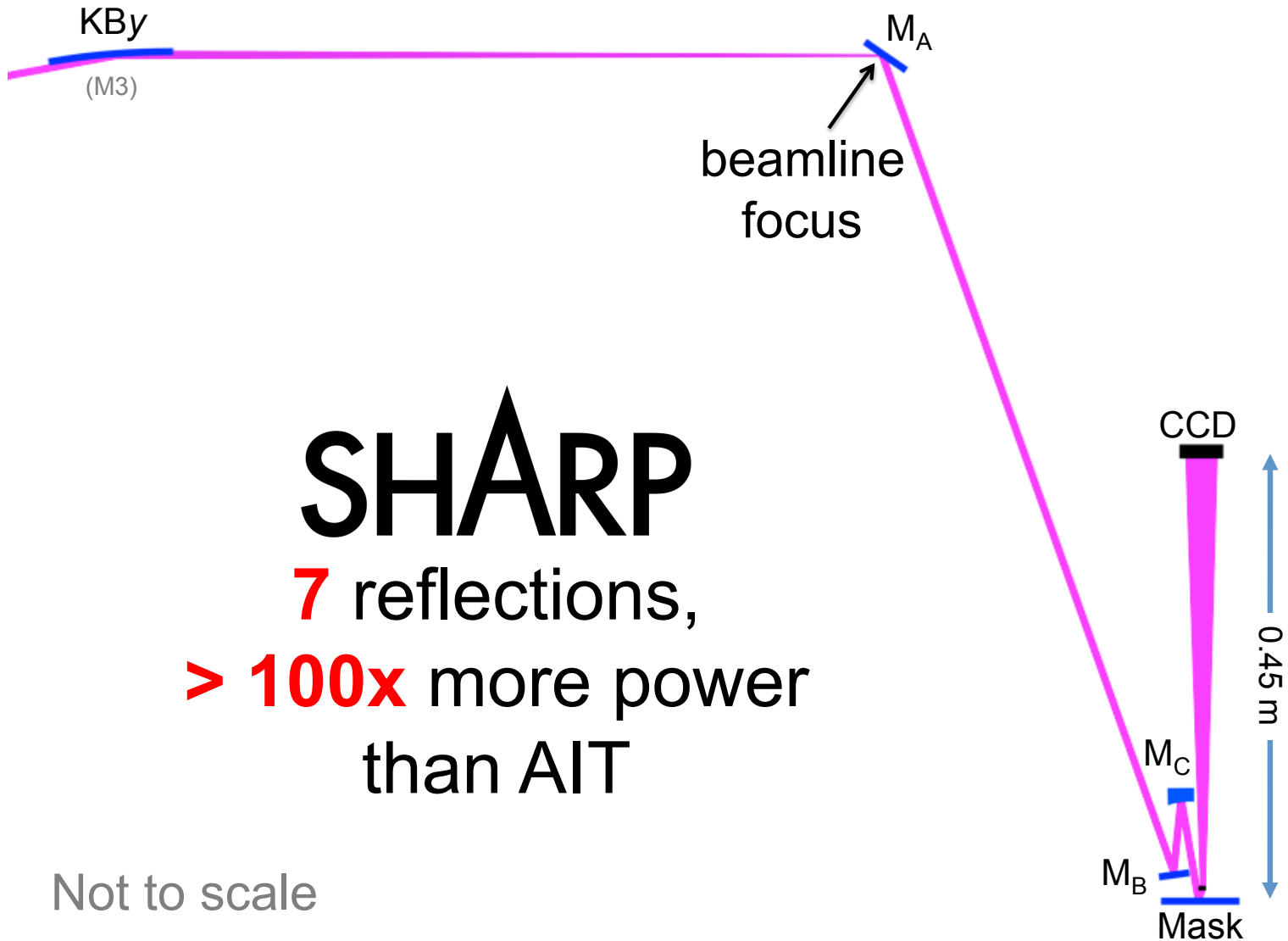
2.5 μm

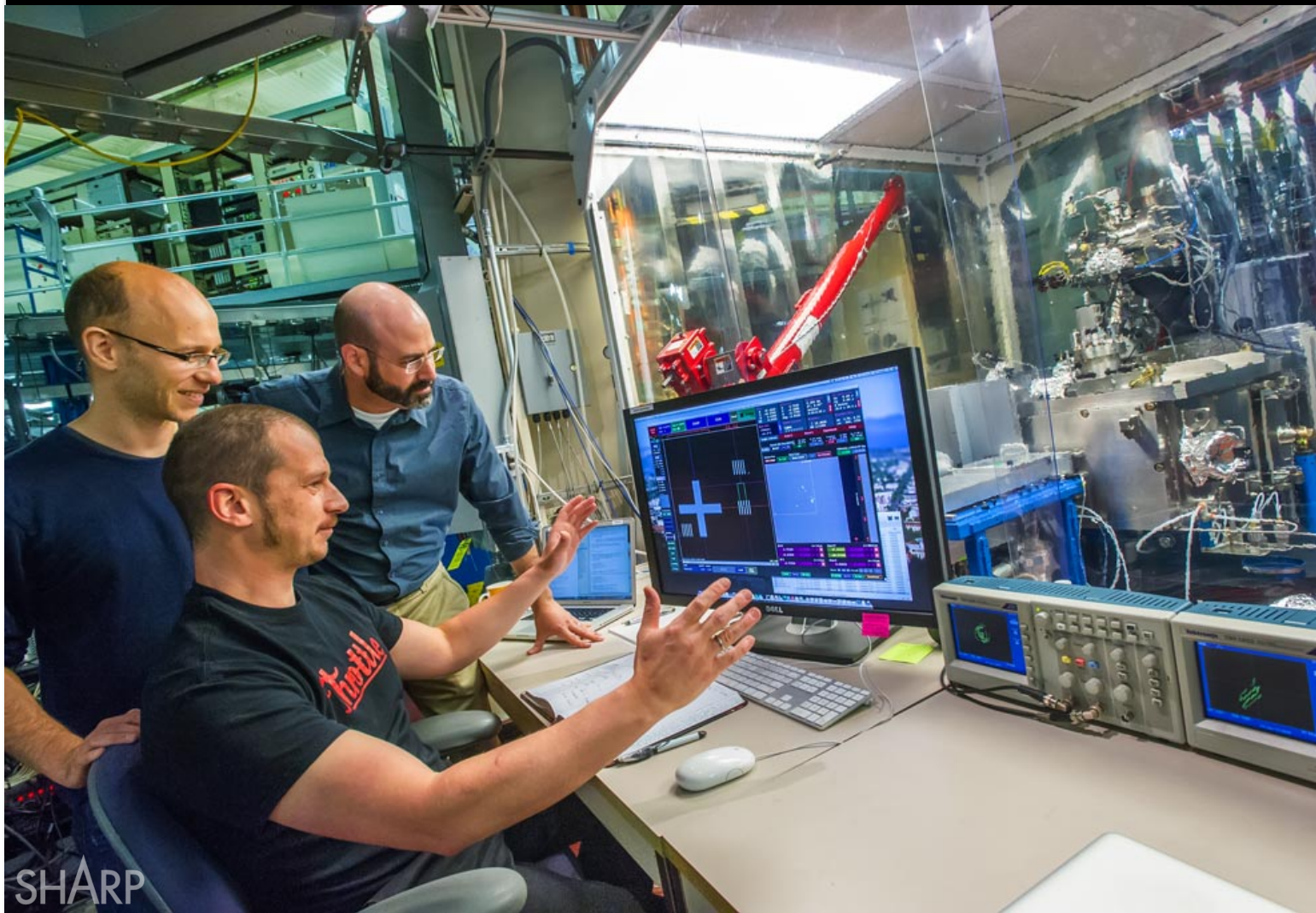


coherent
 $\sigma \approx 0$



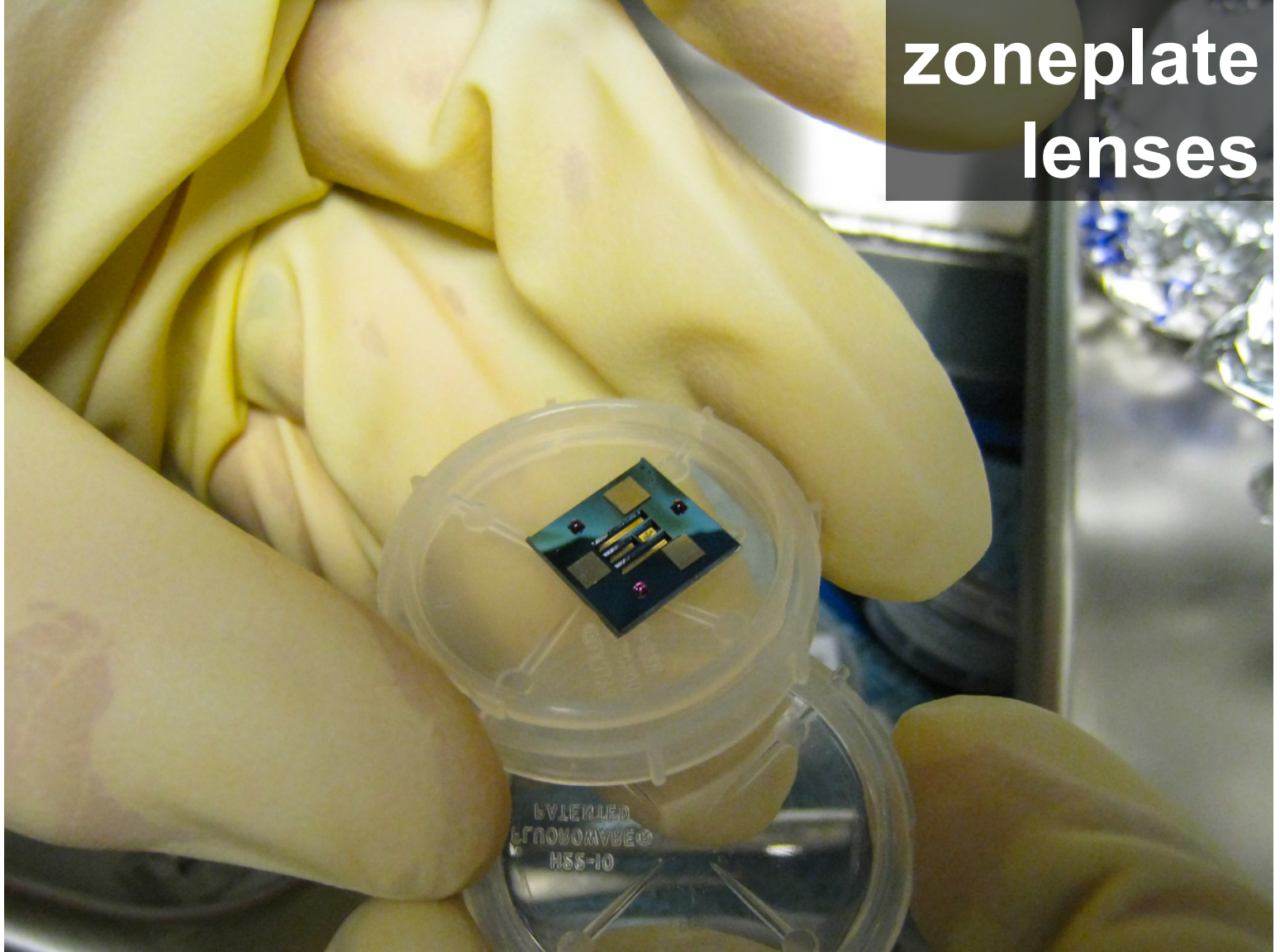
partially coherent
 $\sigma = 0.5$

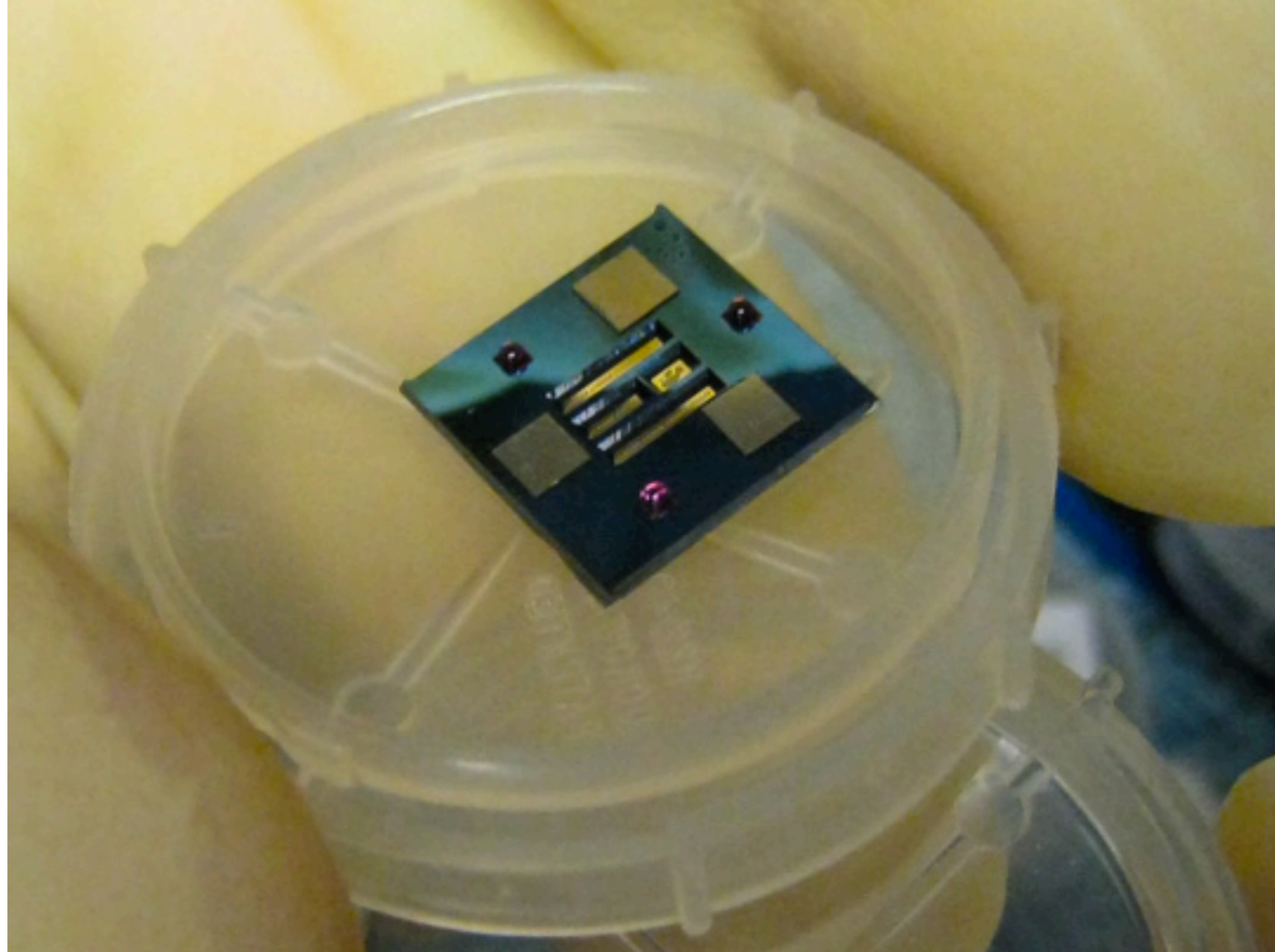




SHARP

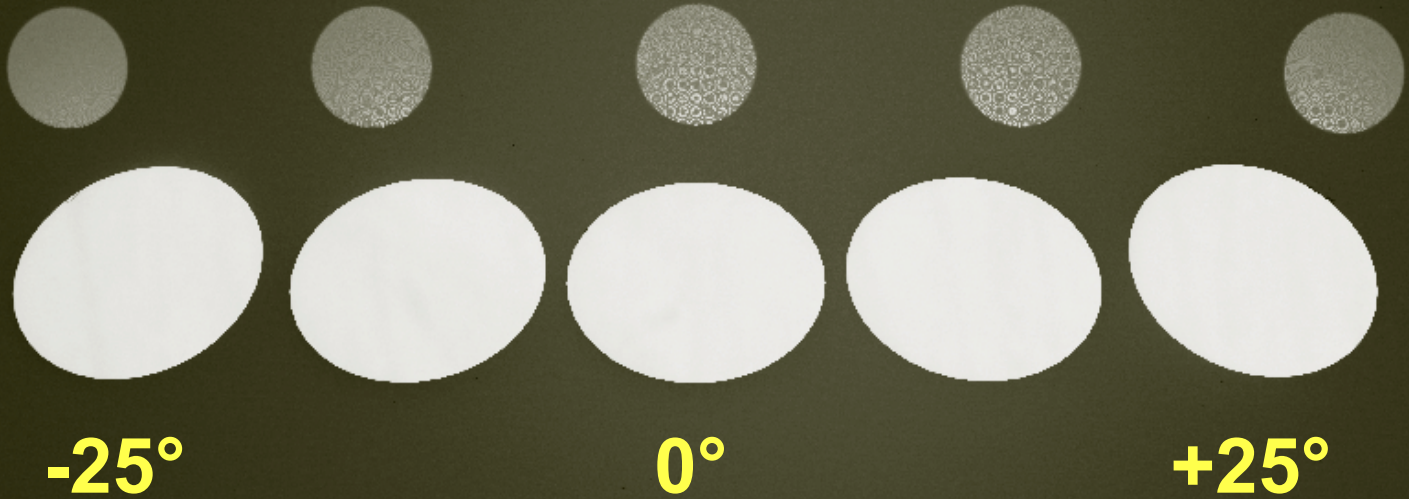
zoneplate lenses







0.25 4xNA zoneplates



Mag = 179 X

100μm



EHT = 5.00 kV

WD = 3 mm

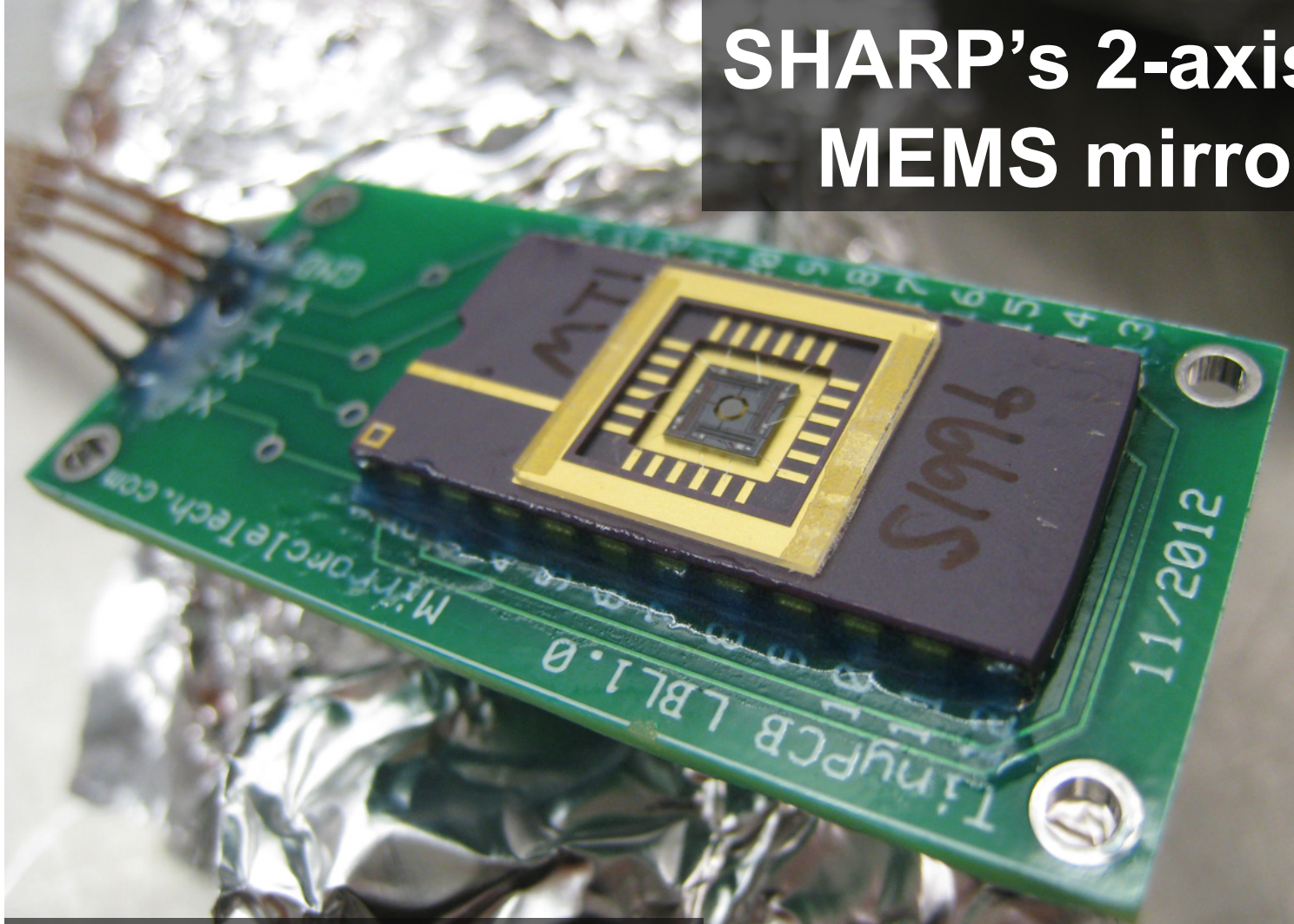
Signal A = InLens

Photo No. = 8758

Date :

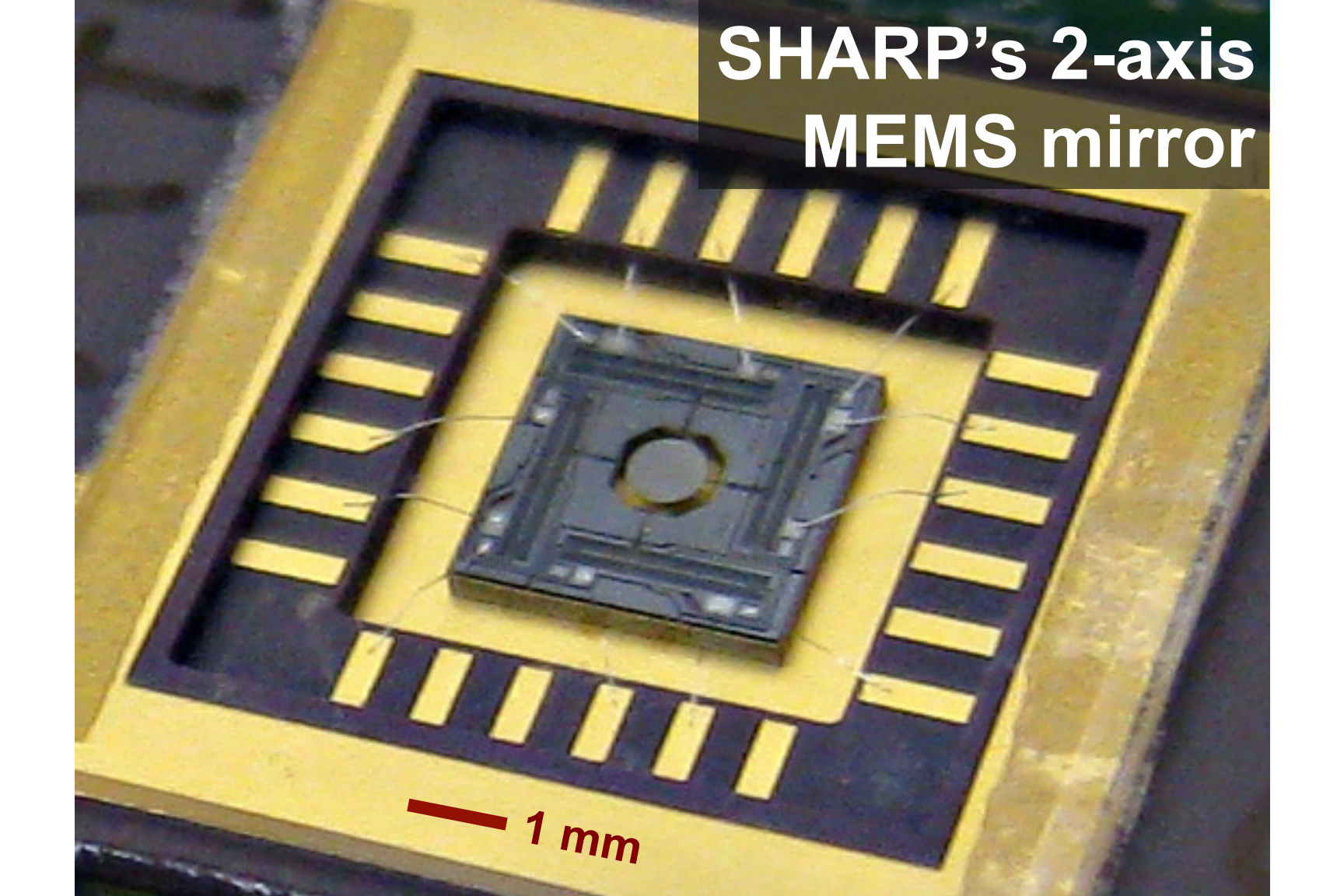
Time :

SHARP's 2-axis MEMS mirror



Mirrorcle Technologies

SHARP's 2-axis MEMS mirror



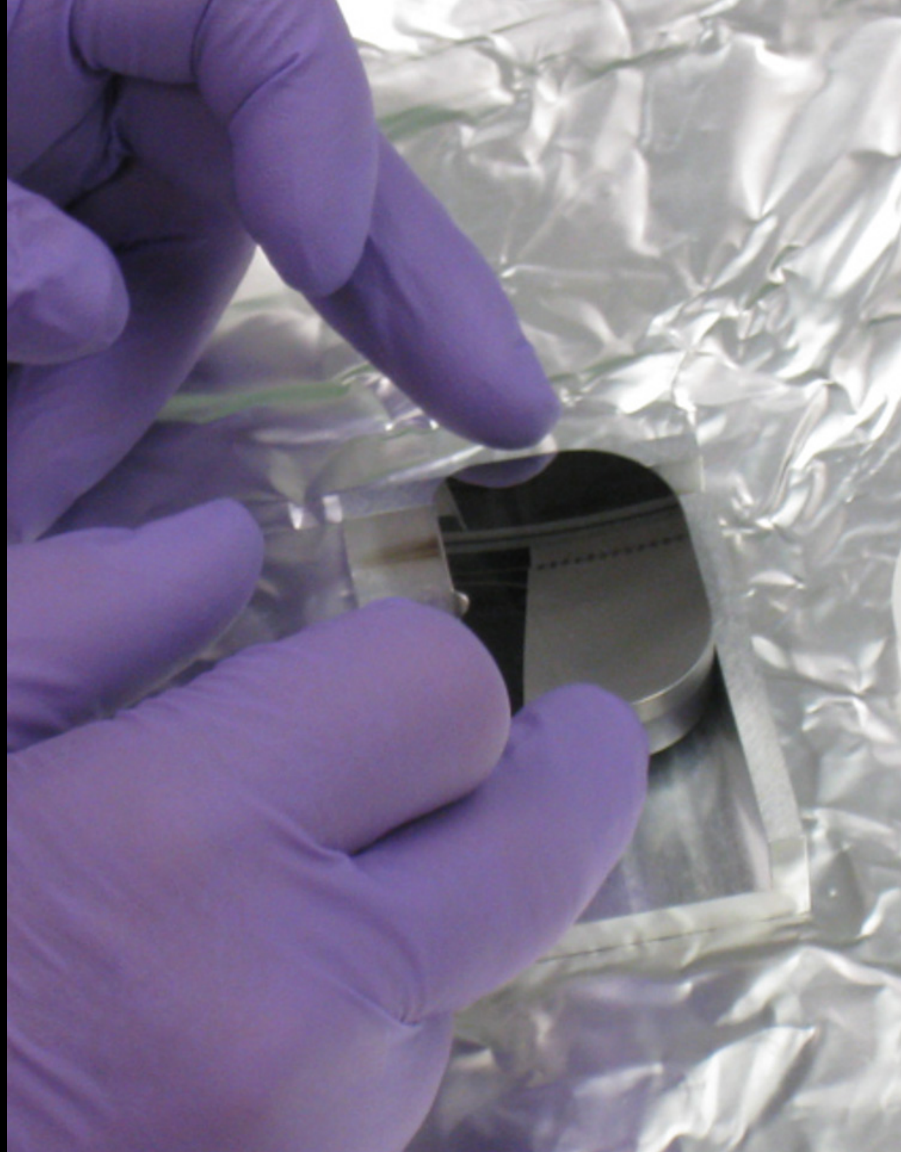
A photograph of a SHARP 2-axis MEMS mirror. The device is a small, square, dark-colored component with a central circular mirror. It is mounted on a larger, square, yellowish-gold substrate. The substrate has a series of parallel, rectangular slots or fingers extending from the edges towards the center. The mirror is connected to the substrate by several thin, white wires. A scale bar in the bottom right corner indicates a length of 1 mm.

— 1 mm

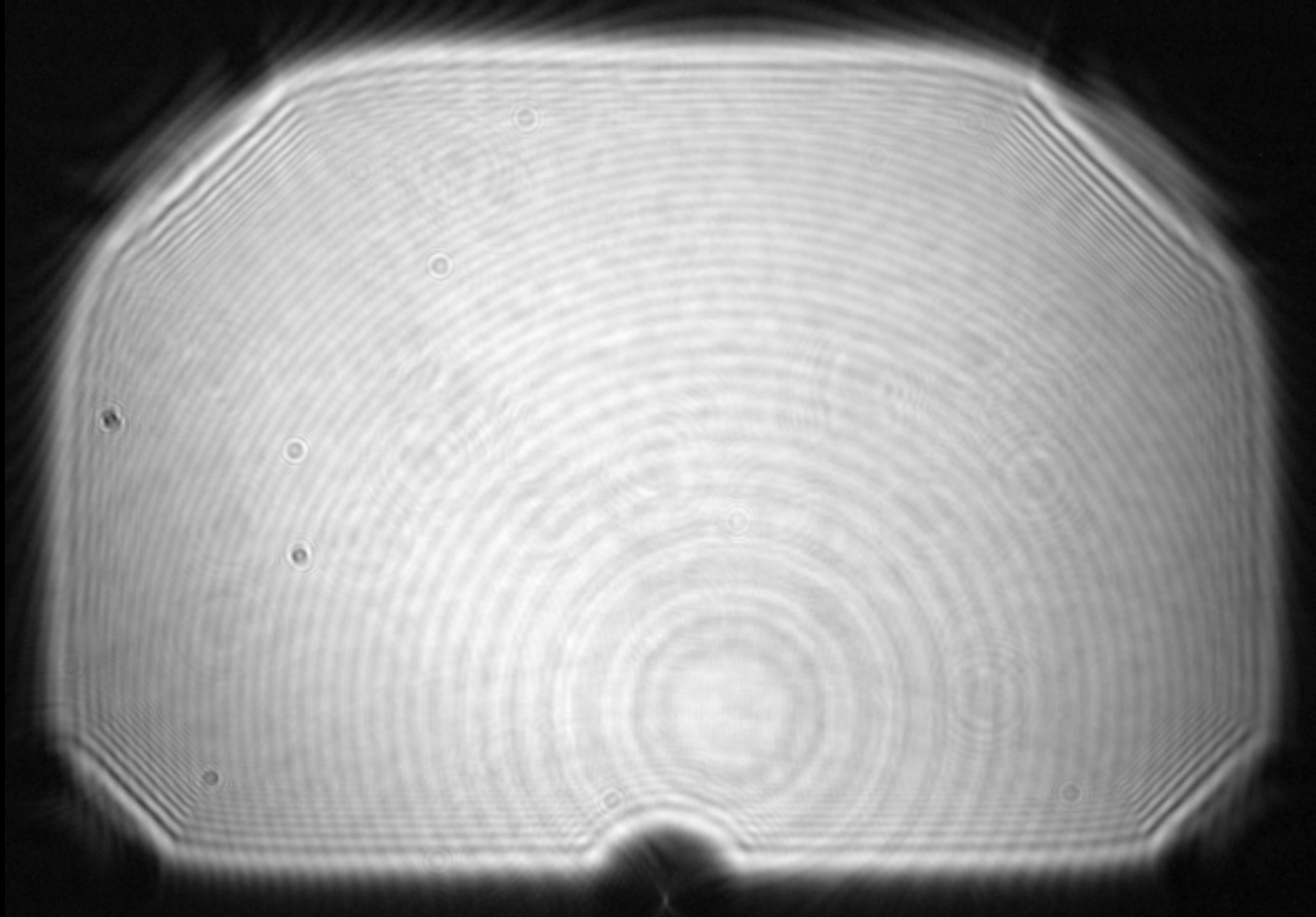


**SHARP
Condenser**

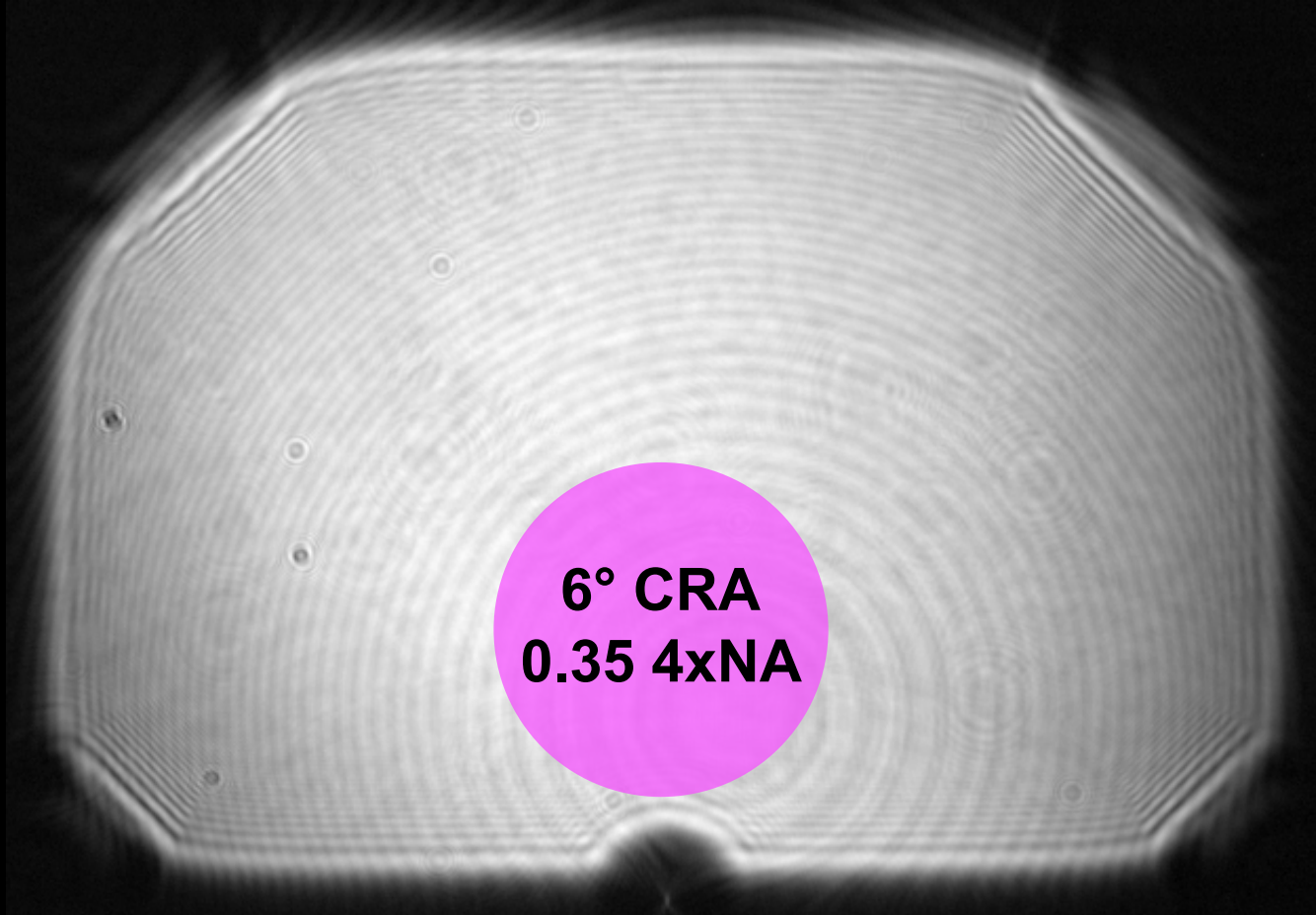
L-3 Tinsley



SHARP condenser

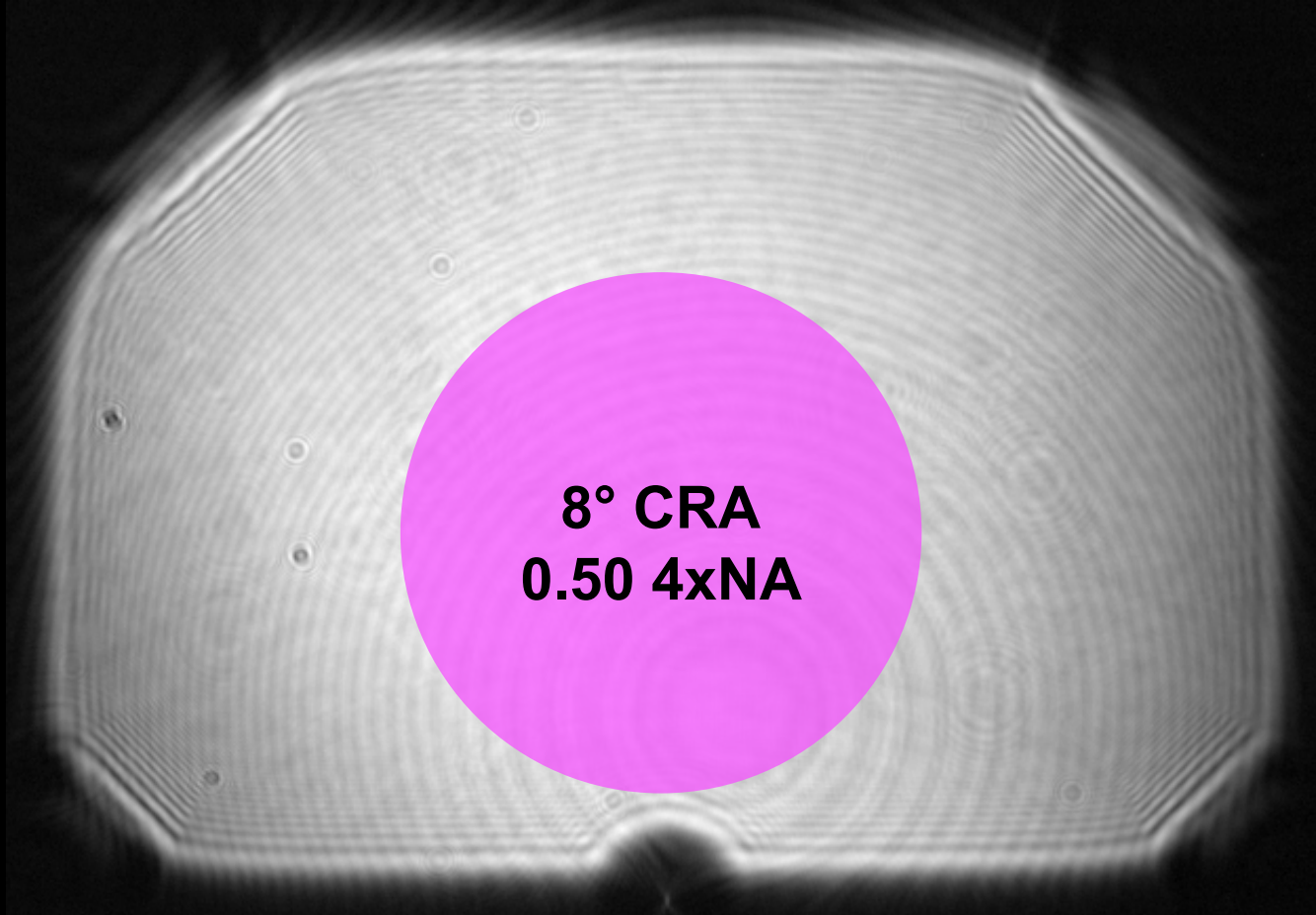


SHARP condenser

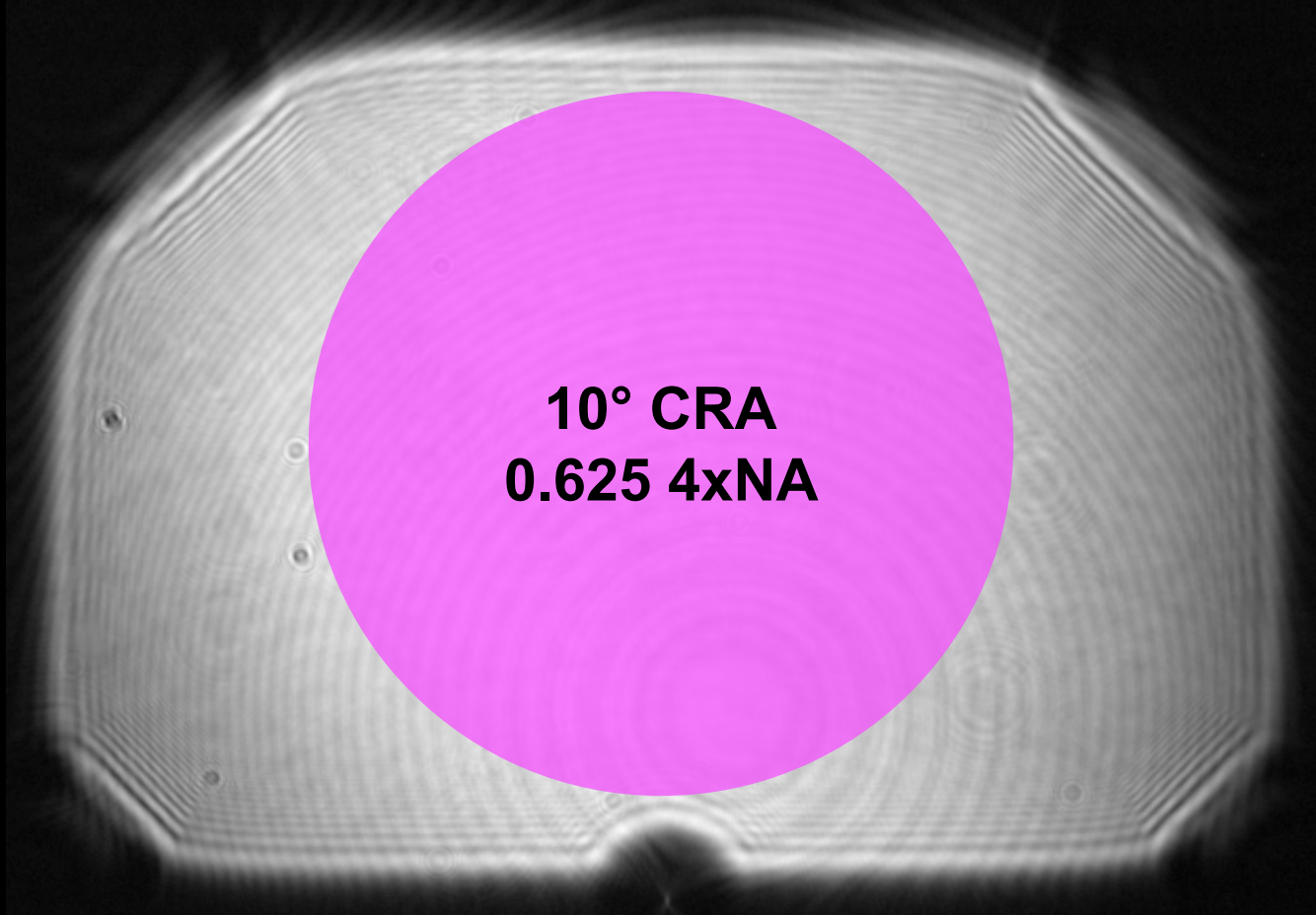


6° CRA
0.35 4xNA

SHARP condenser



SHARP condenser

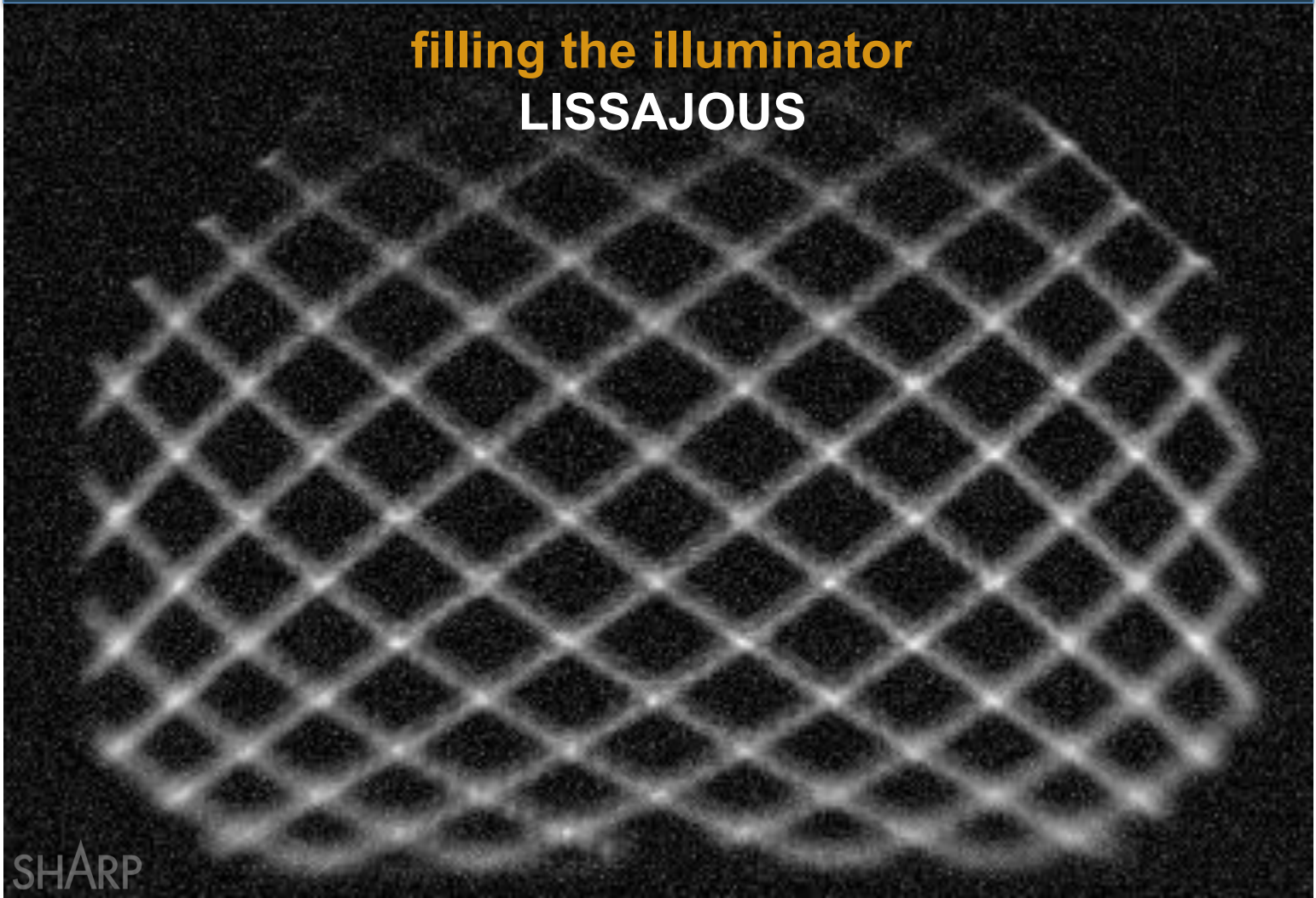


10° CRA
0.625 4xNA

Coherence Control: Pupil Fill Patterns

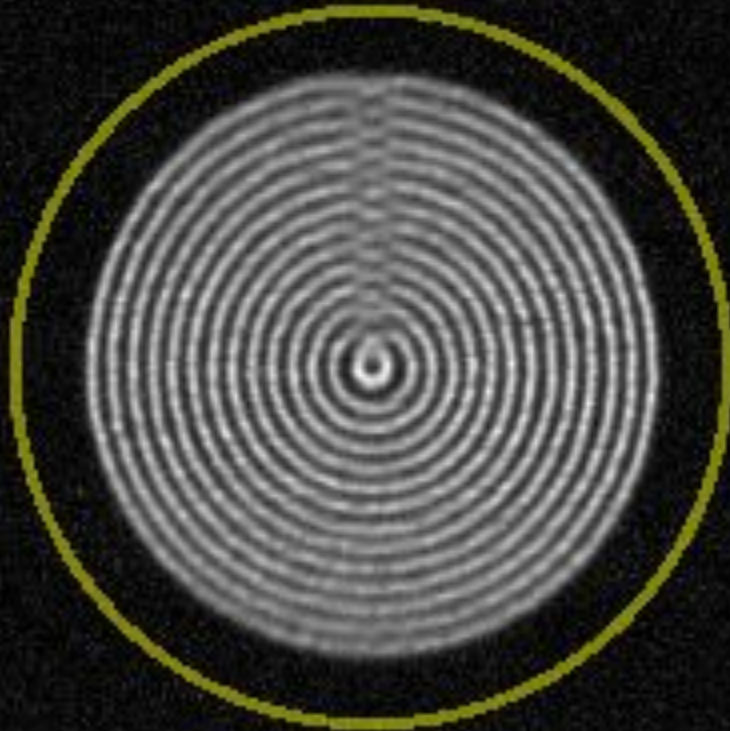
filling the illuminator

LISSAJOUS



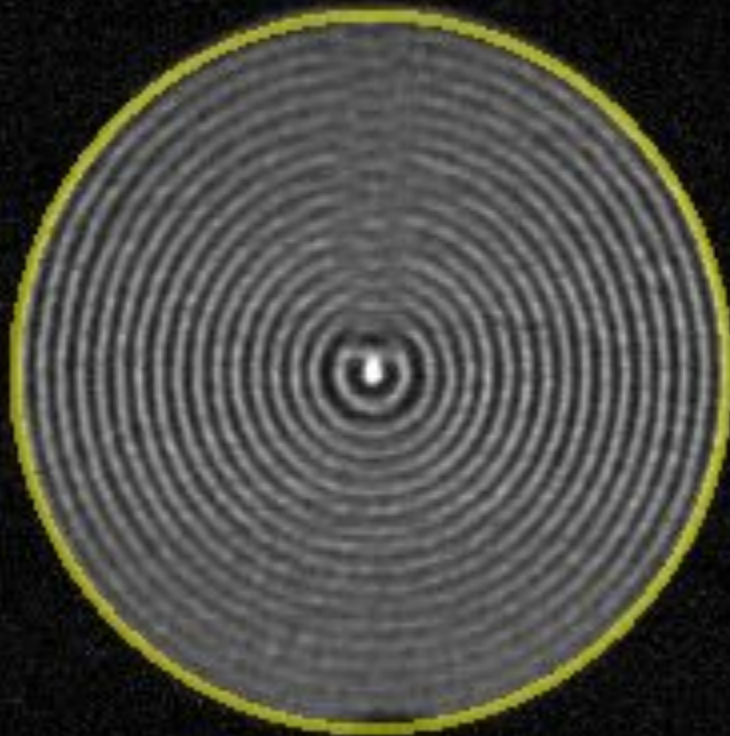
Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA
DISK



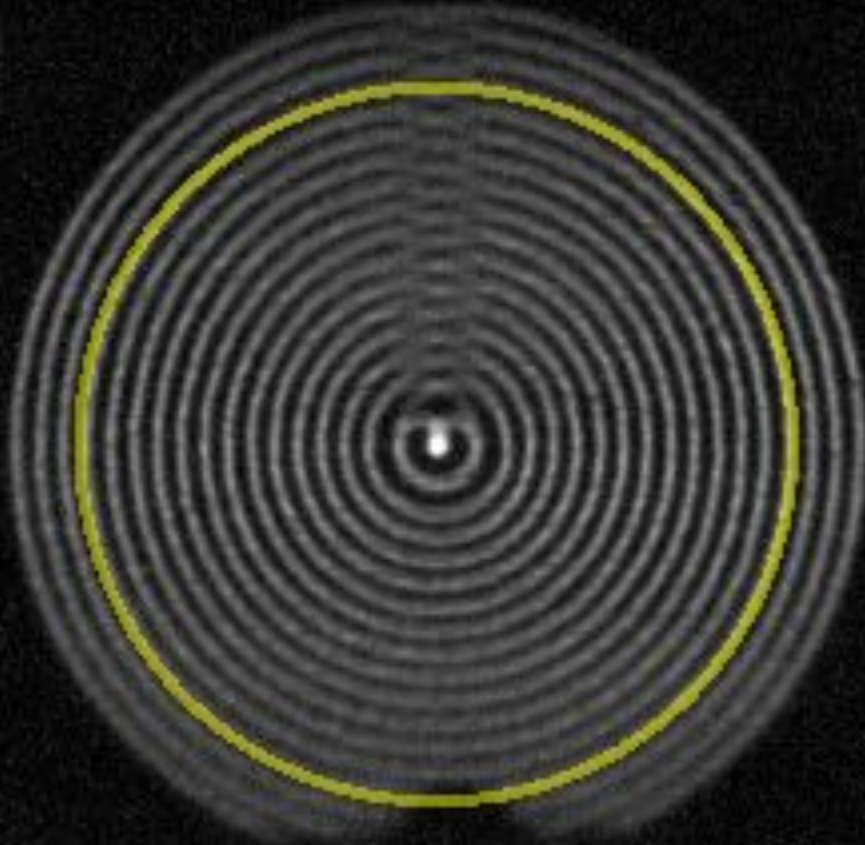
Coherence Control: Pupil Fill Patterns

0.5-NA 1.0- σ 8° CRA
DISK



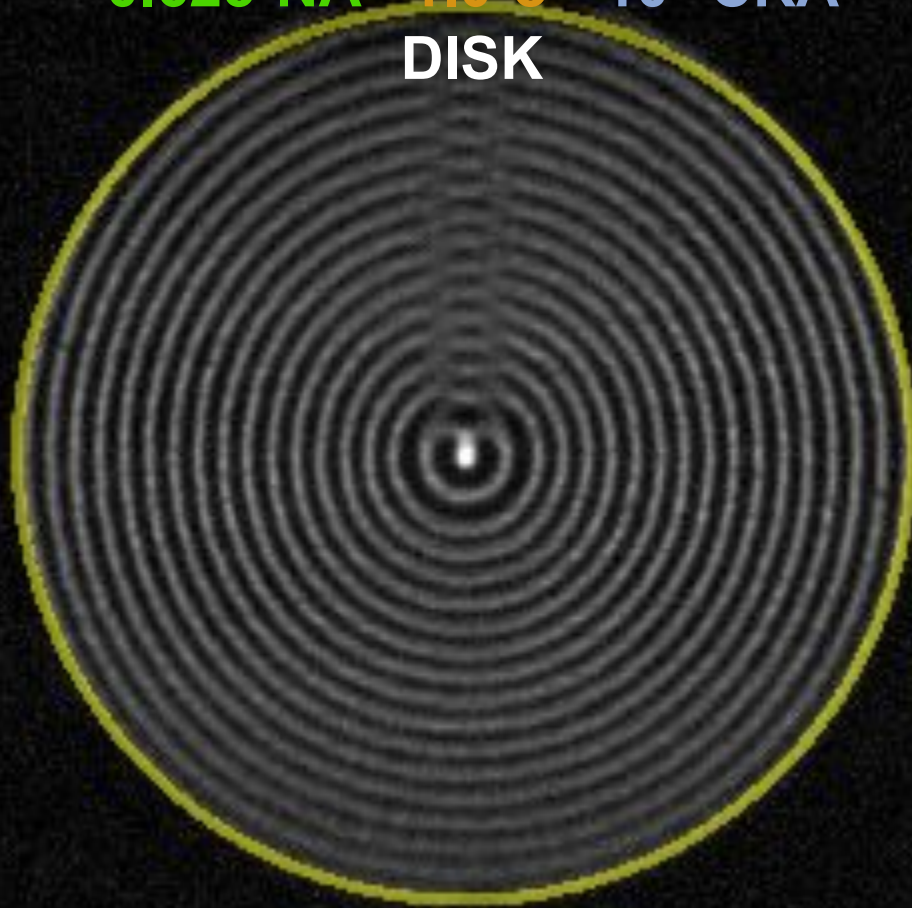
Coherence Control: Pupil Fill Patterns

0.5-NA 1.2- σ 8° CRA
DISK



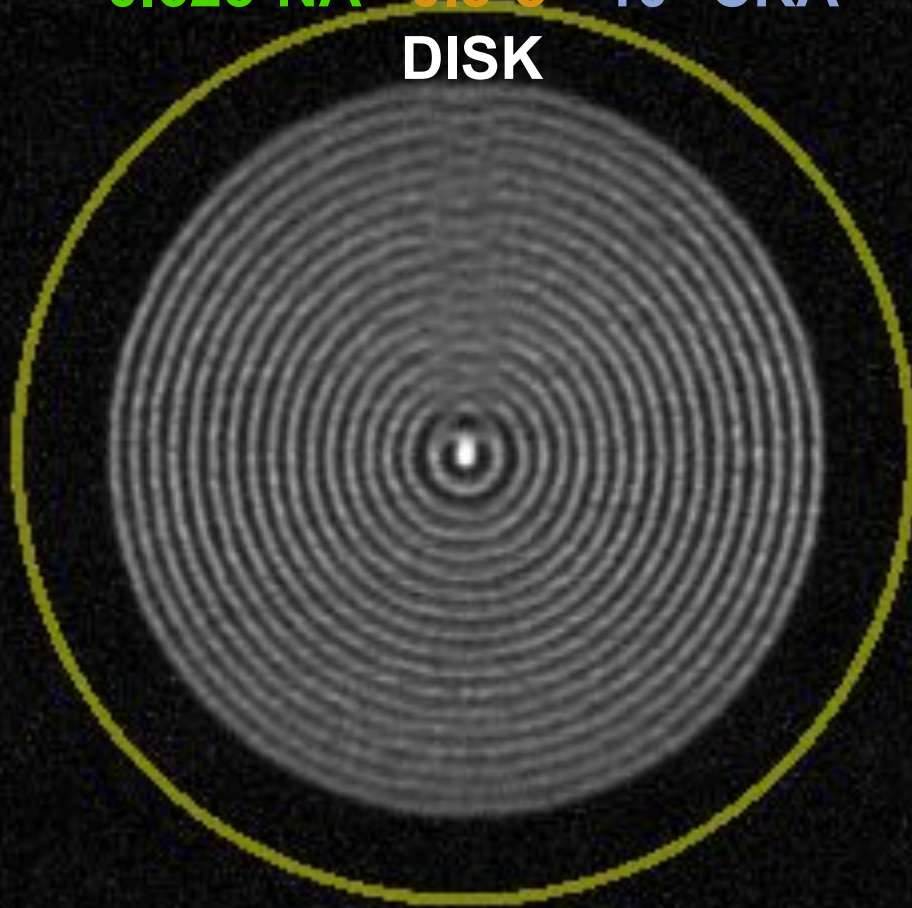
Coherence Control: Pupil Fill Patterns

0.625-NA 1.0- σ 10° CRA
DISK



Coherence Control: Pupil Fill Patterns

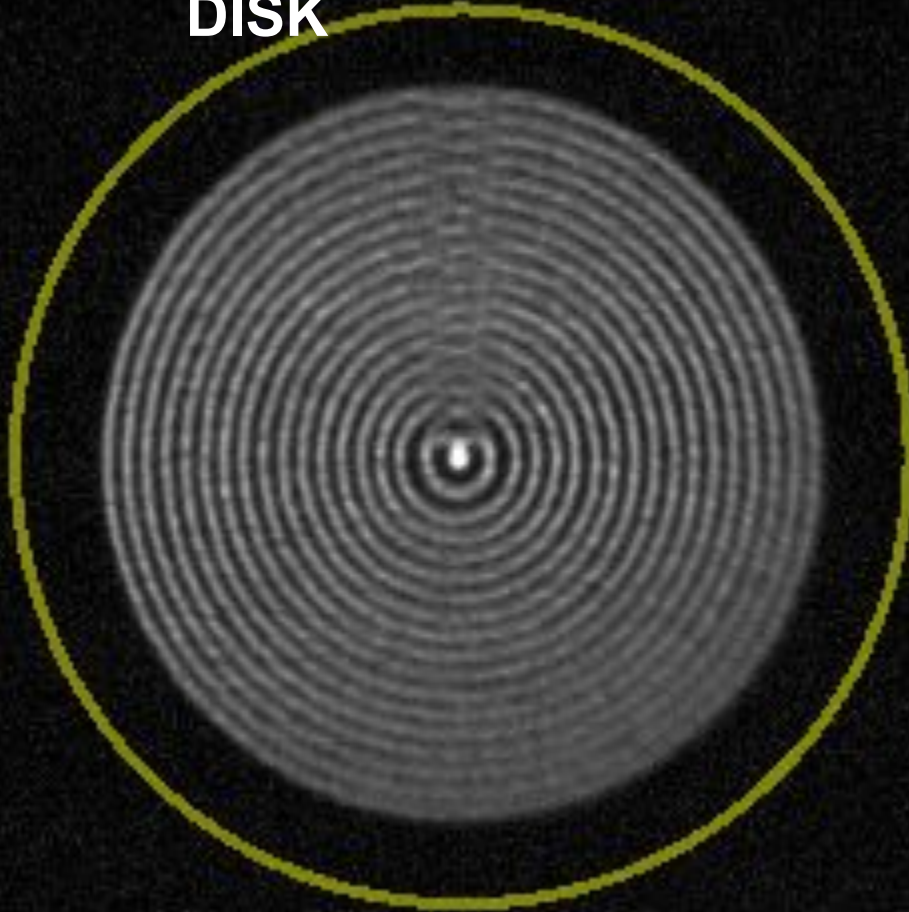
0.625-NA 0.8- σ 10° CRA
DISK



Coherence Control: Pupil Fill Patterns

0.625-NA 0.8- σ 10° CRA +25°

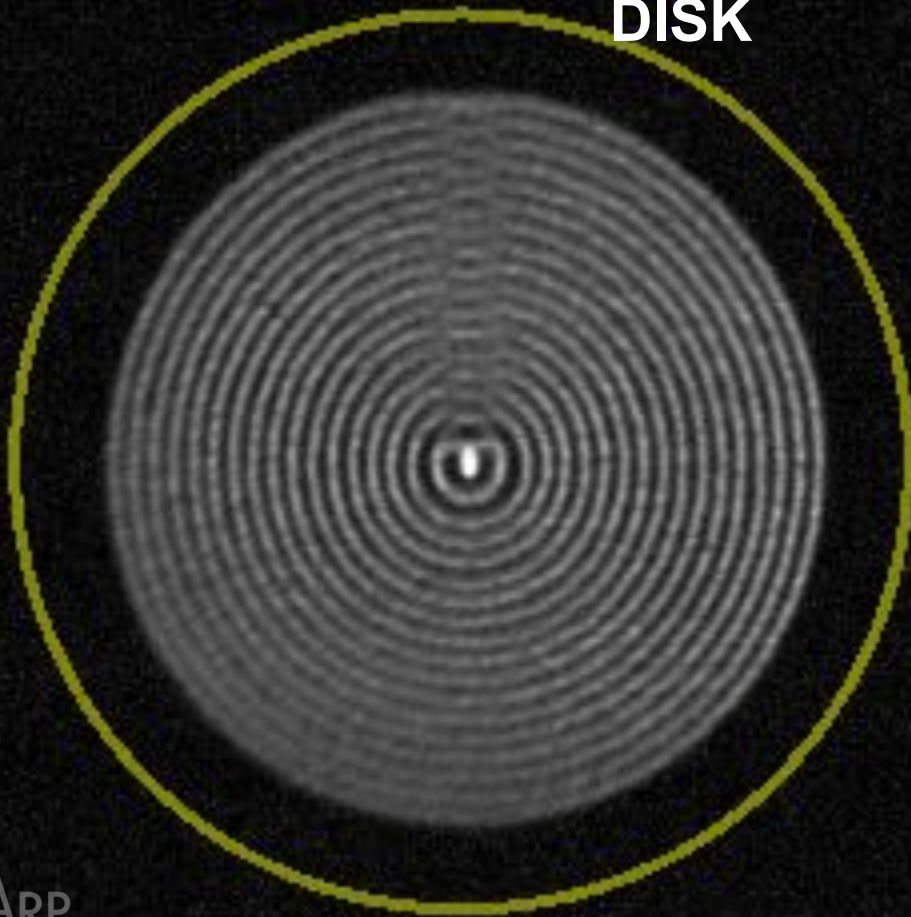
DISK



Coherence Control: Pupil Fill Patterns

0.625-NA 0.8- σ 10° CRA -25°

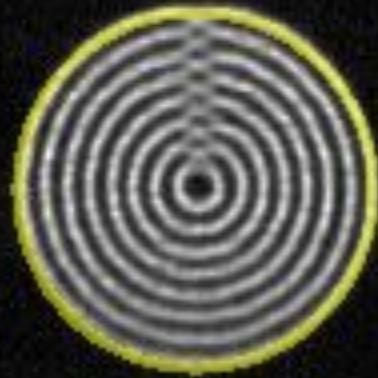
DISK



SHARP

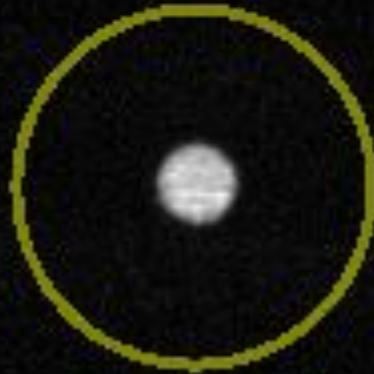
Coherence Control: Pupil Fill Patterns

0.25-NA 1.0- σ 6° CRA
DISK



Coherence Control: Pupil Fill Patterns

0.25-NA 0.2- σ 6° CRA
DISK



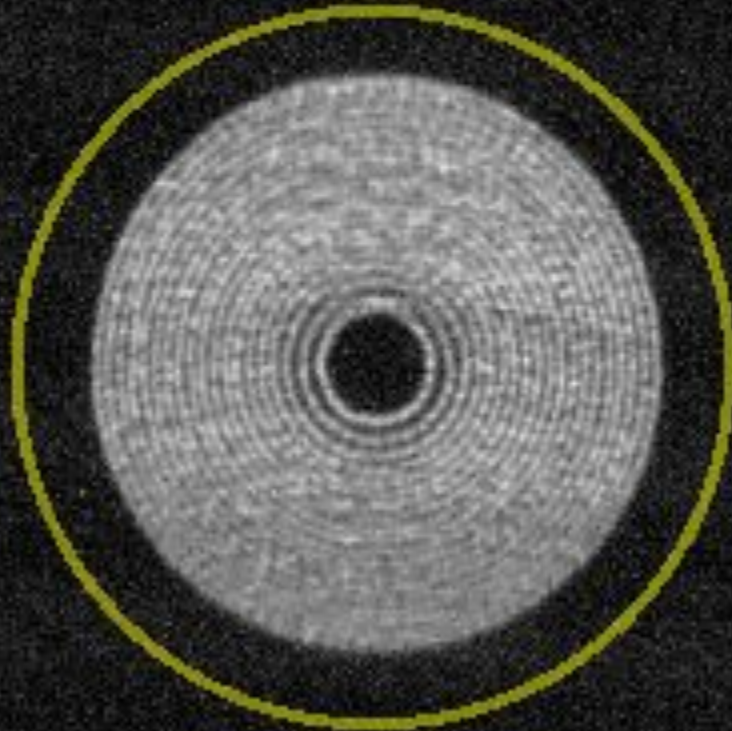
Coherence Control: Pupil Fill Patterns

0.25-NA 0.05- σ 6° CRA
DISK



Coherence Control: Pupil Fill Patterns

0.5-NA 0.2–0.8- σ 8° CRA
ANNULAR



Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA

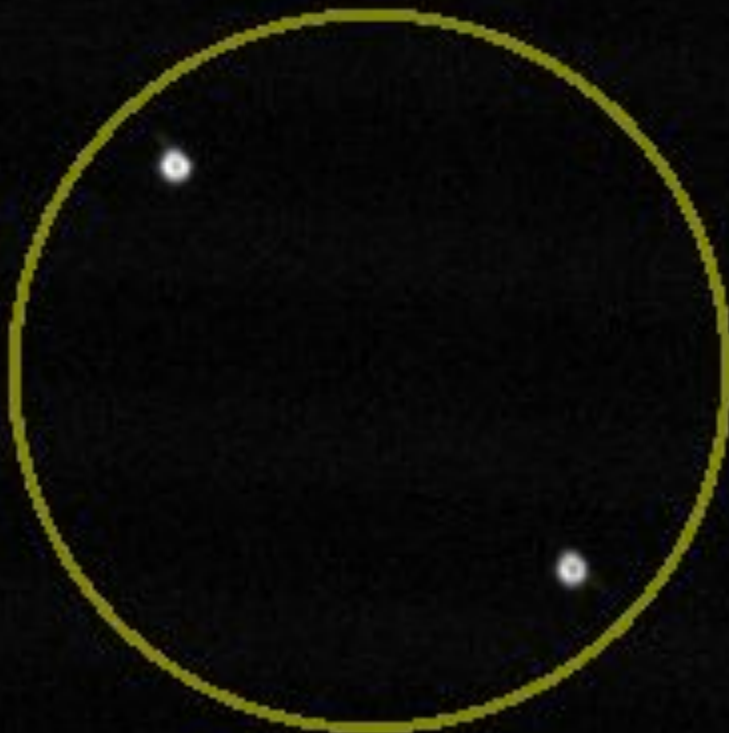
DIPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA

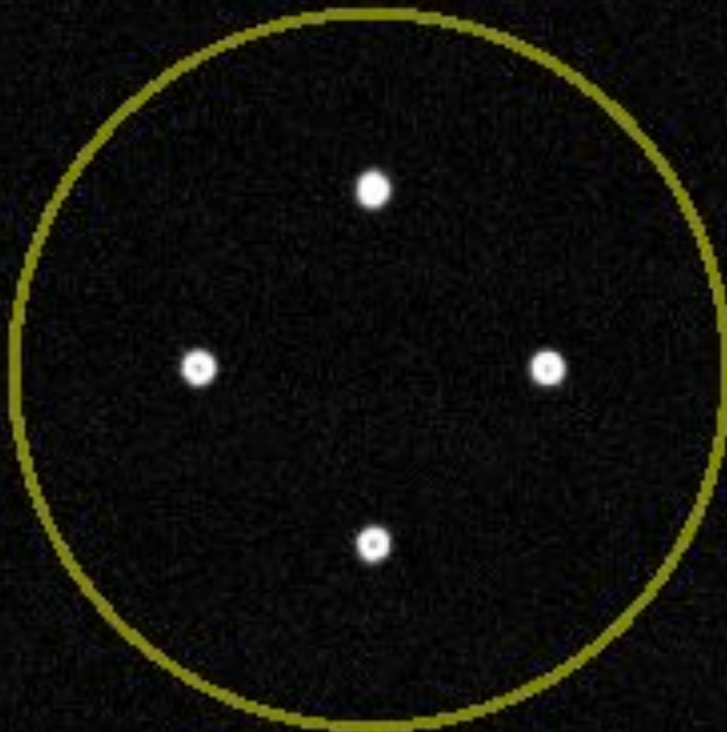
45° DIPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.5- σ 8° CRA

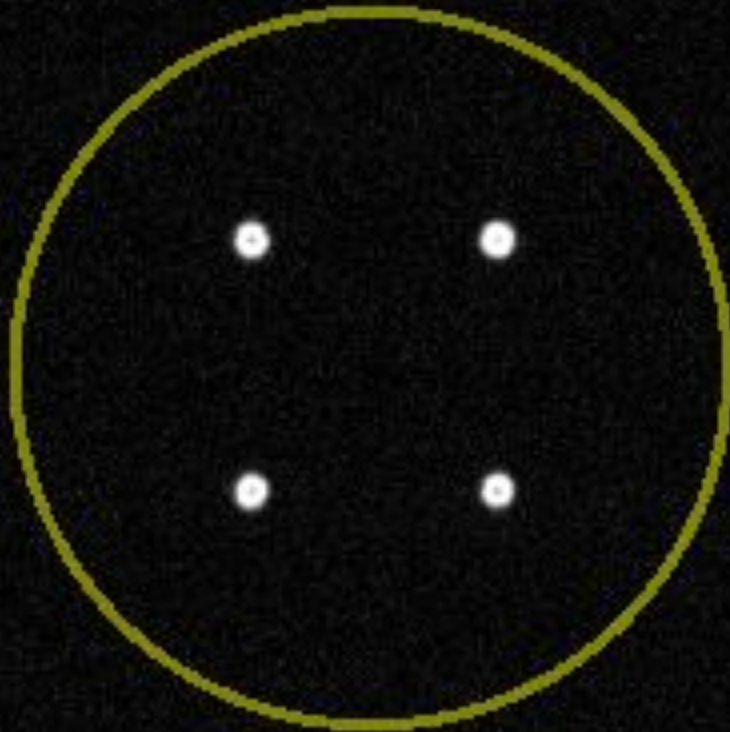
QUADRUPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.5- σ 8° CRA

45° QUADRUPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA
CROSSPOLE (22.5° arc)



Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA

CROSSPOLE (45° arc)



Coherence Control: Pupil Fill Patterns

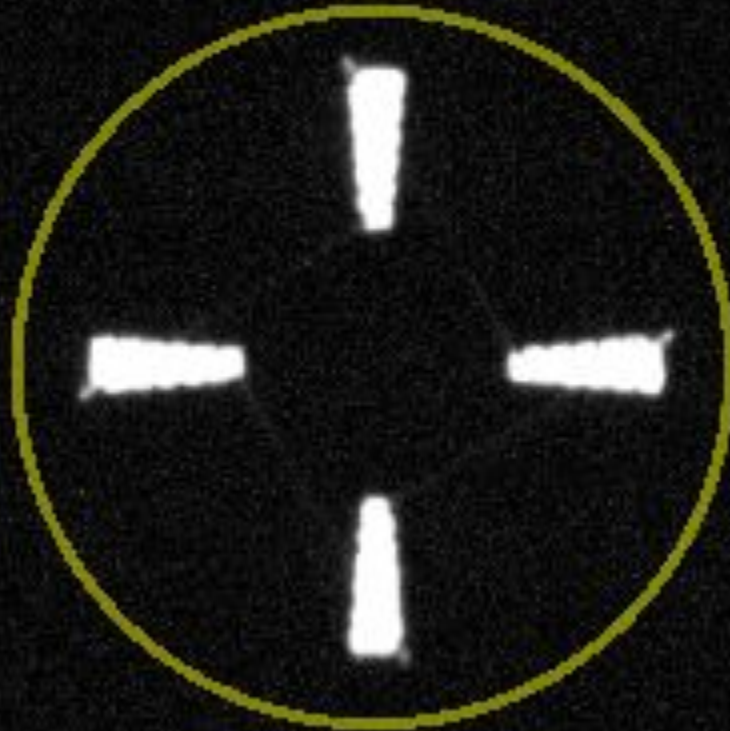
0.5-NA 0.4–0.8- σ 8° CRA
CROSSPOLE (45° arc)



Coherence Control: Pupil Fill Patterns

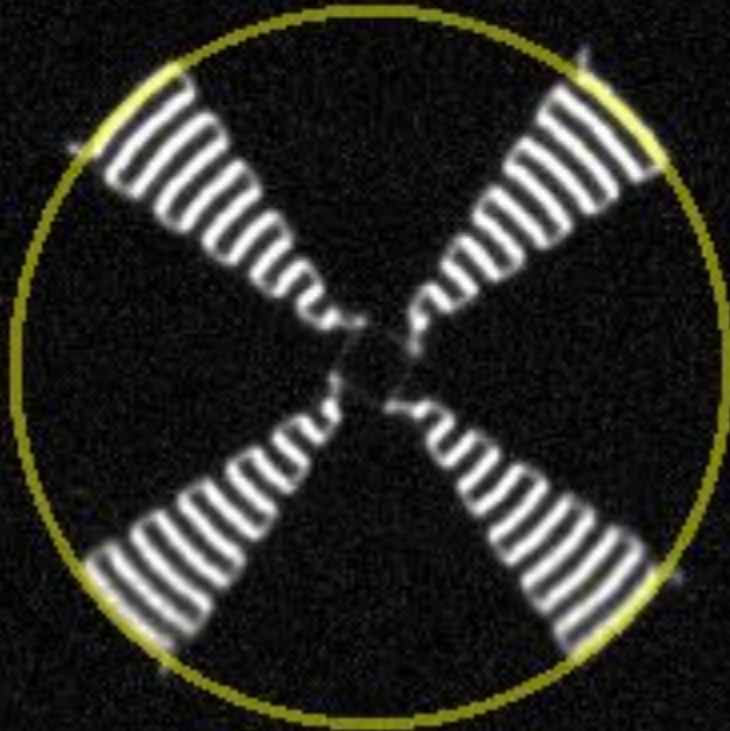
0.5-NA 0.4–0.8- σ 8° CRA

CROSSPOLE (10° arc)



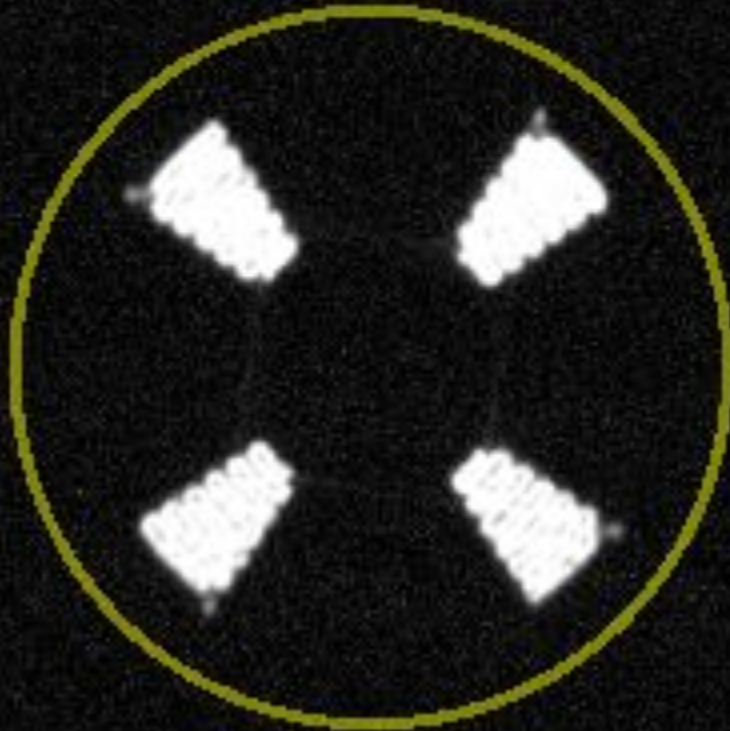
Coherence Control: Pupil Fill Patterns

0.5-NA 0.1–1.0- σ 8° CRA
45° CROSSPOLE (22.5° arc)



Coherence Control: Pupil Fill Patterns

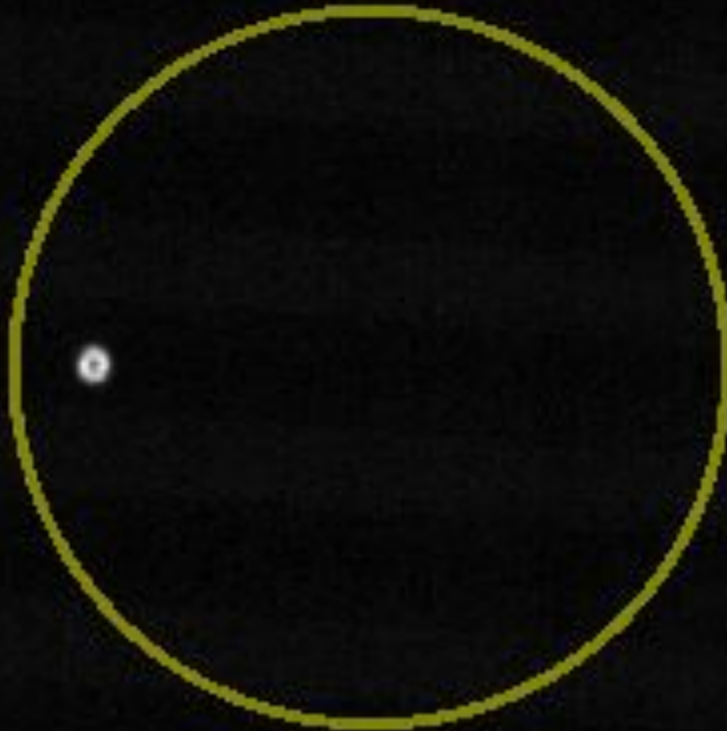
0.5-NA 0.4–0.8- σ 8° CRA
45° CROSSPOLE (22.5° arc)



Coherence Control: Pupil Fill Patterns

0.5-NA 0.8- σ 8° CRA

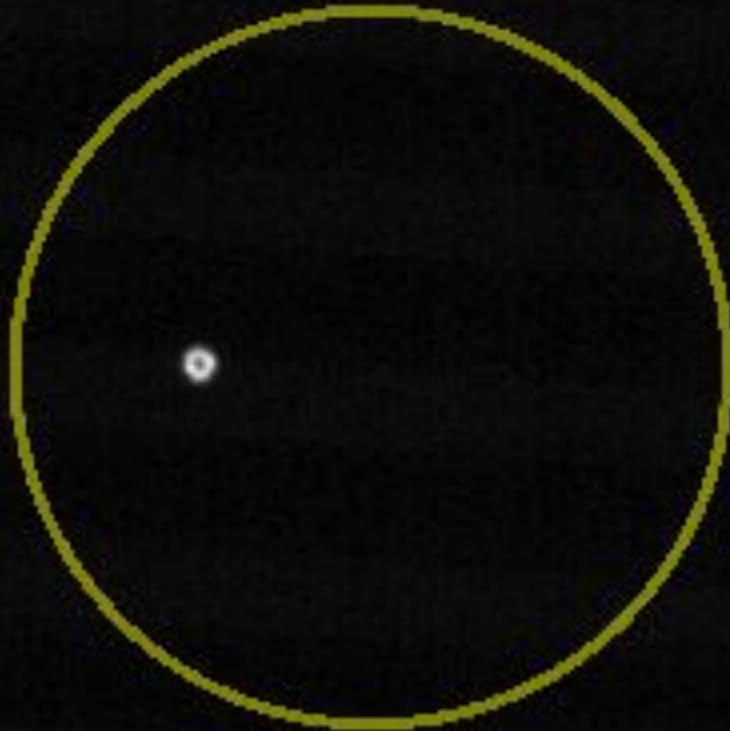
X MONOPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.5- σ 8° CRA

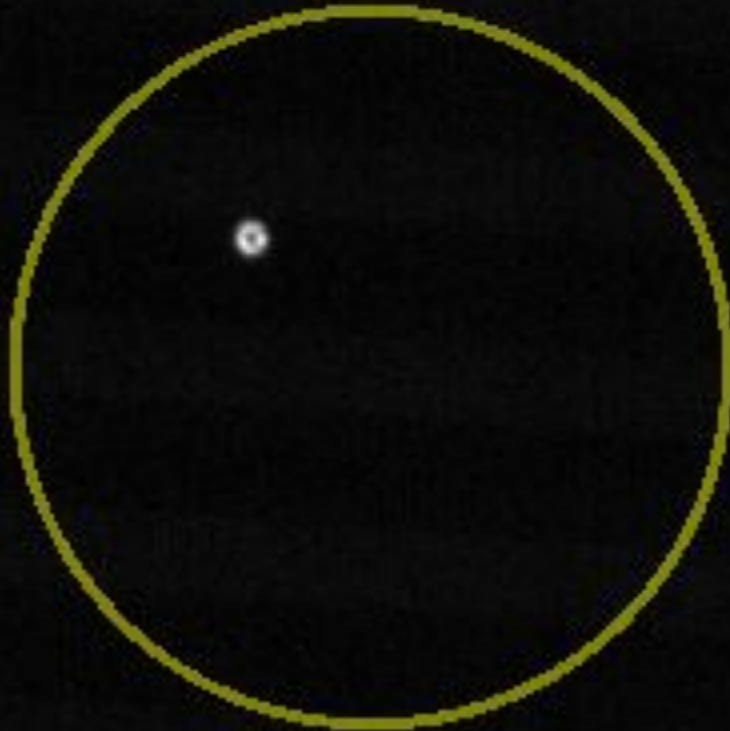
X MONOPOLE



Coherence Control: Pupil Fill Patterns

0.5-NA 0.5- σ 8° CRA

45° MONOPOLE



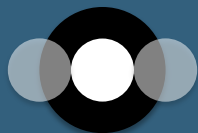
**High NA
for high spatial resolution**

4xNA

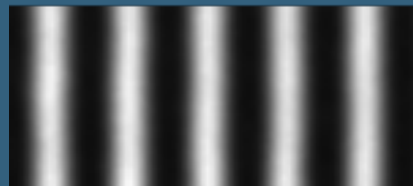
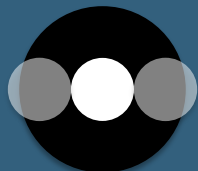
Pupil

110-nm CD

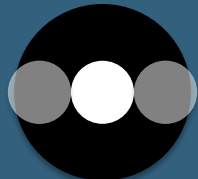
0.25



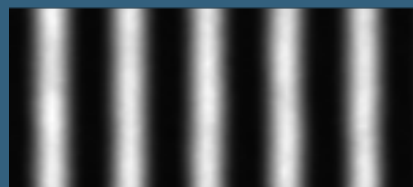
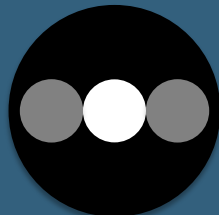
0.33



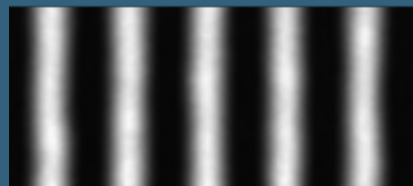
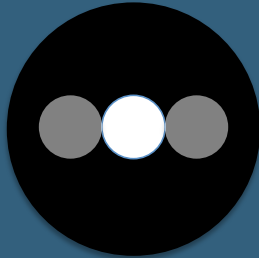
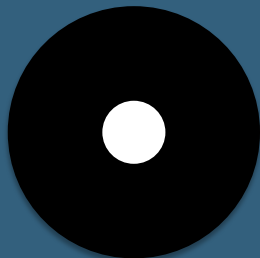
0.35



0.42



0.50



4xNA

110-nm CD

0.25

0.50 σ

0.33

0.38 σ

0.35

0.36 σ

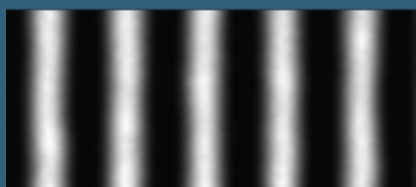
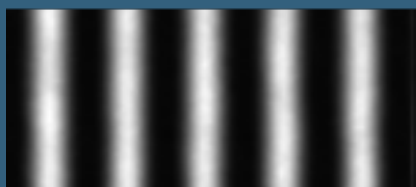
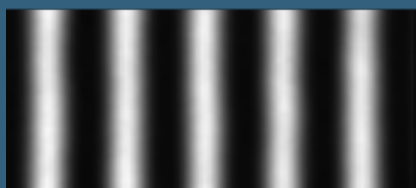
0.42

0.30 σ

0.50

0.25 σ

SHARP



$I(x)$

1.0

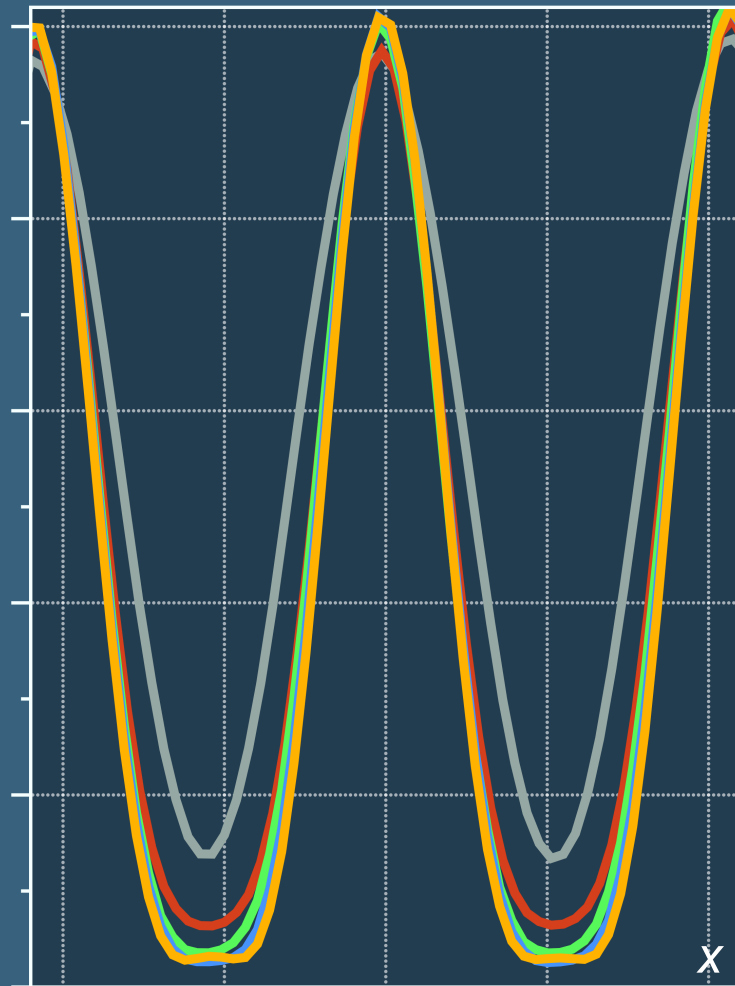
0.8

0.6

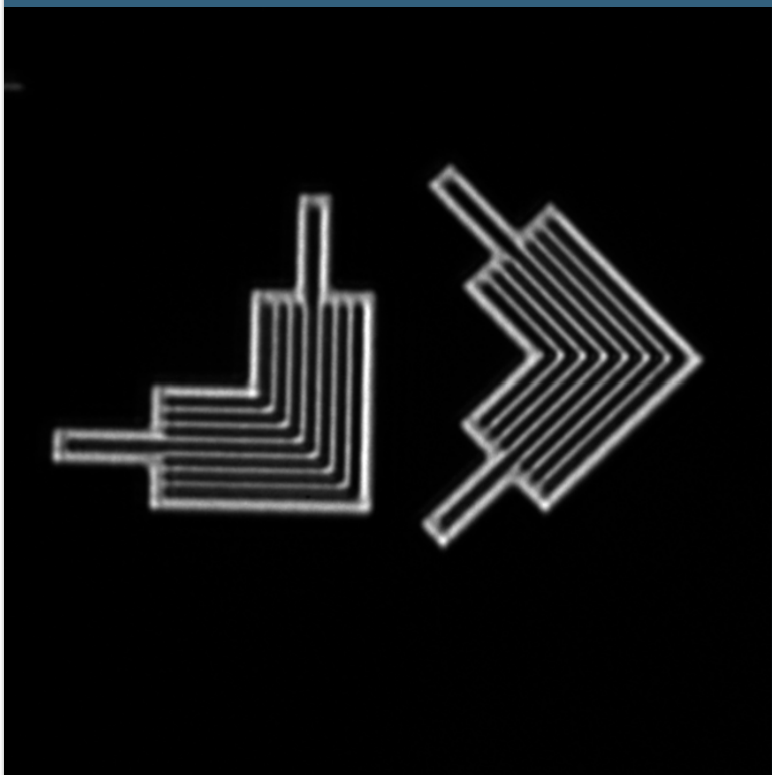
0.4

0.2

0



Pupil-fill affects imaging

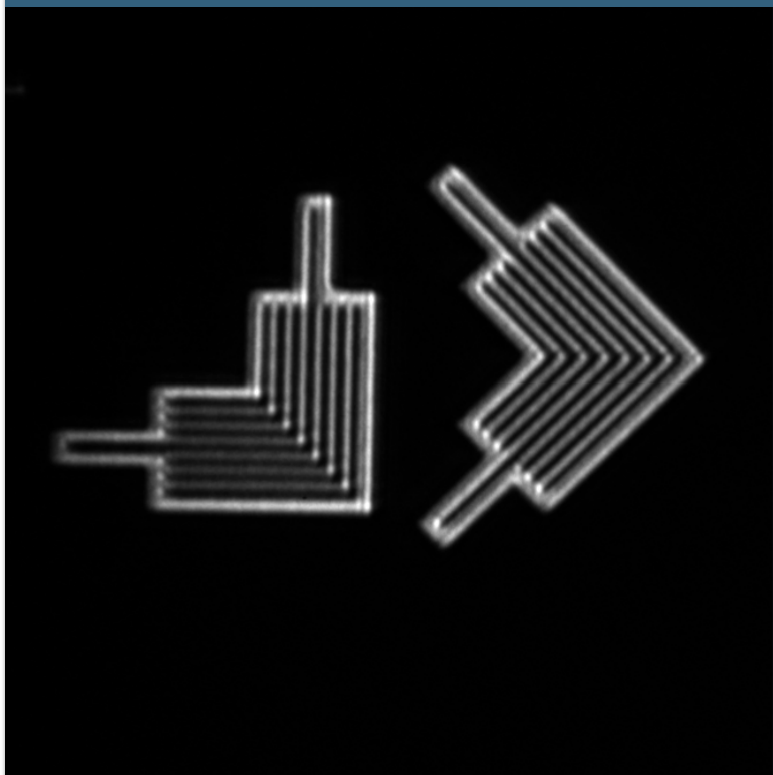


Elbows, 100-nm CD

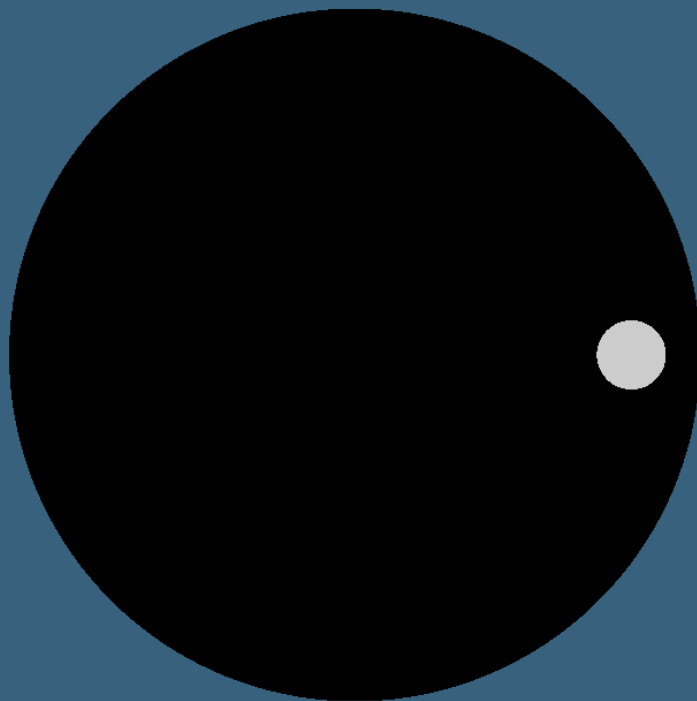


0.33 4xNA pupil

Pupil-fill affects imaging

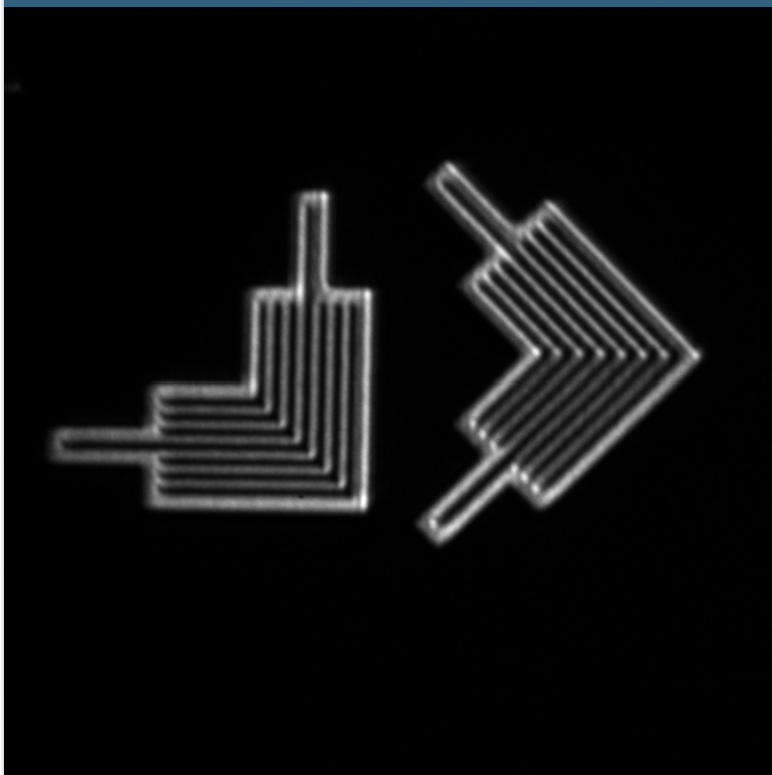


Elbows, 100-nm CD

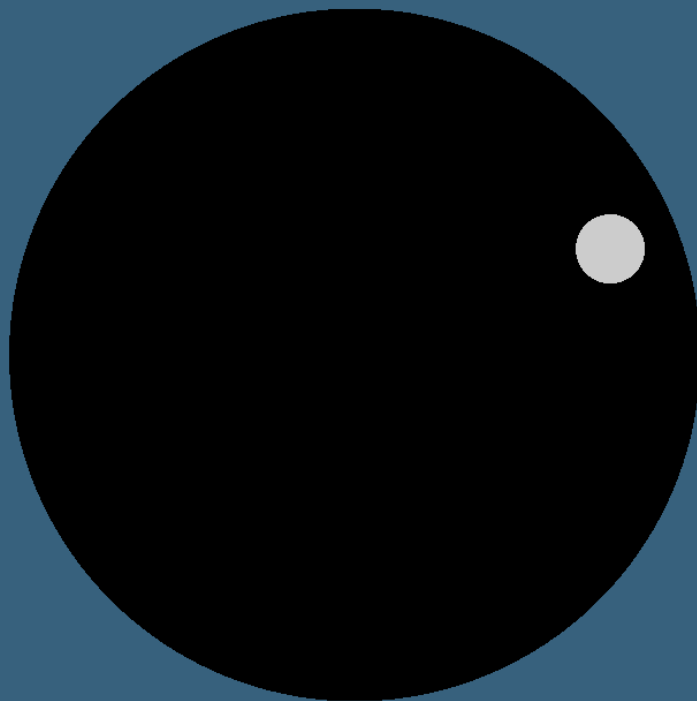


0.33 4xNA pupil

Pupil-fill affects imaging

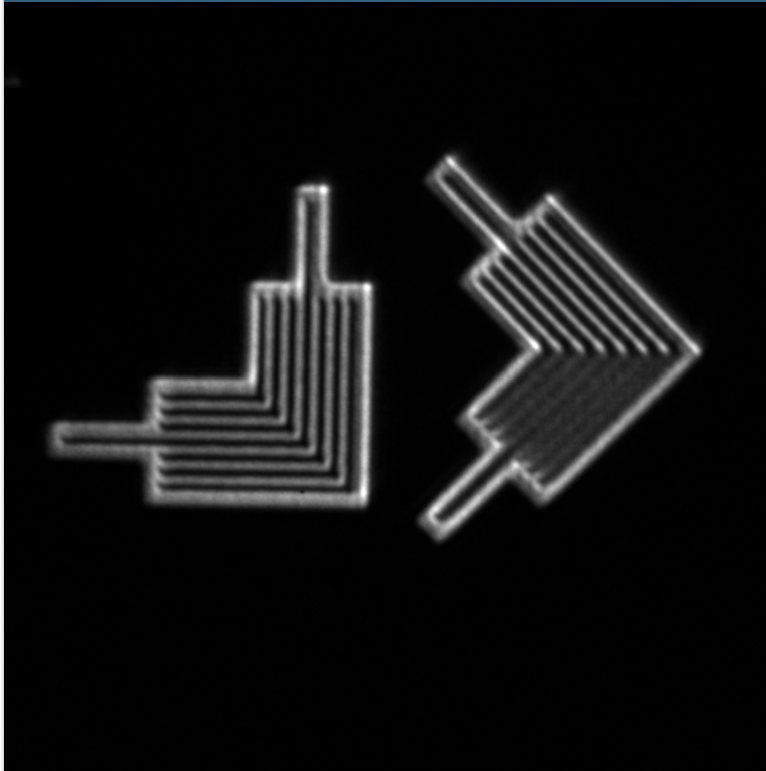


Elbows, 100-nm CD

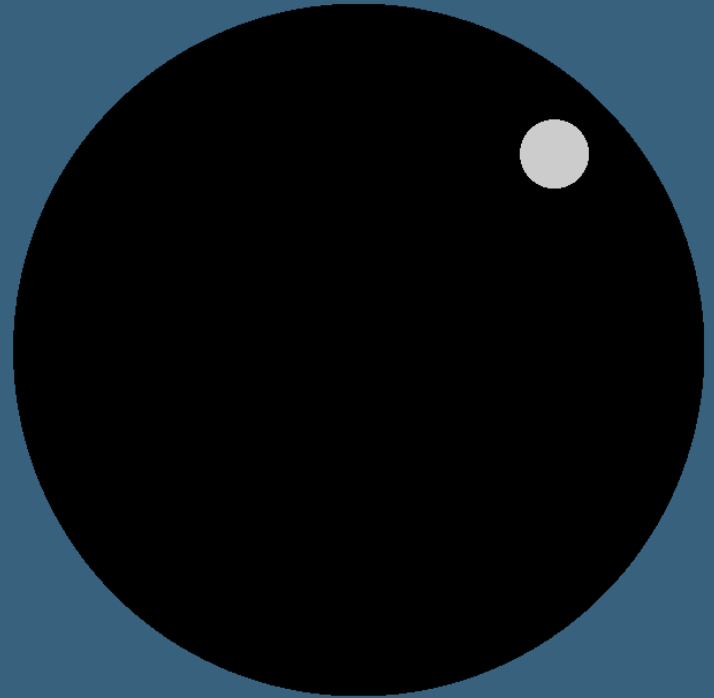


0.33 4xNA pupil

Pupil-fill affects imaging

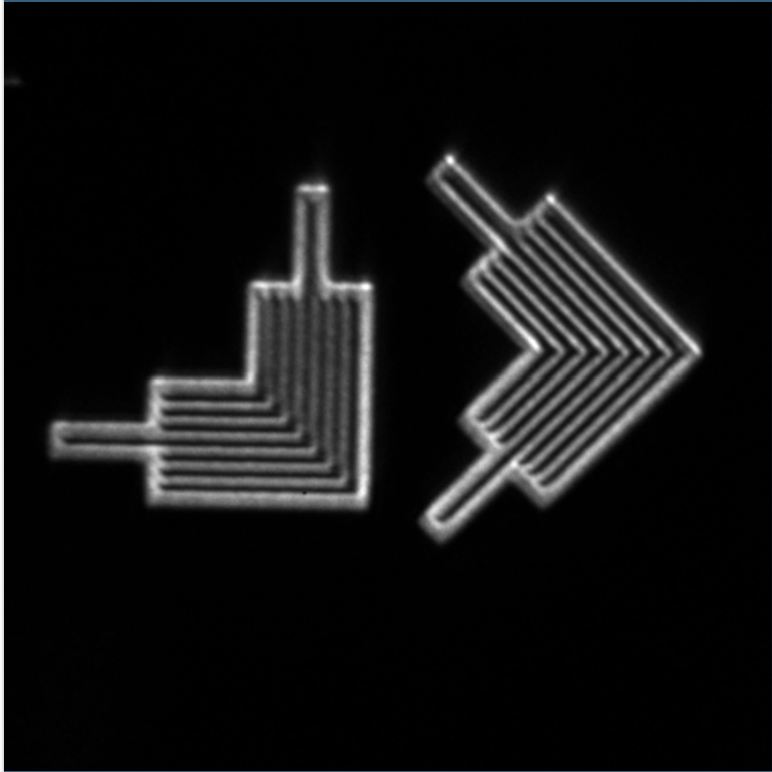


Elbows, 100-nm CD

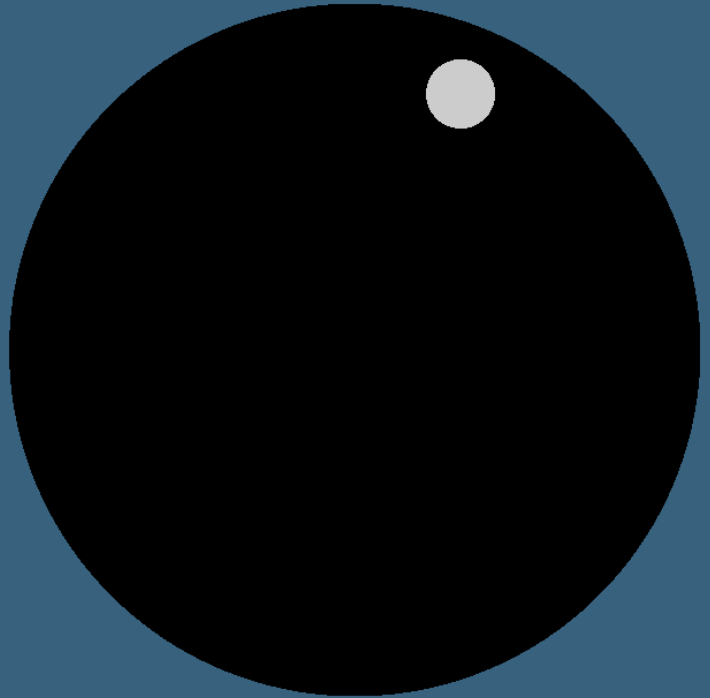


0.33 4xNA pupil

Pupil-fill affects imaging

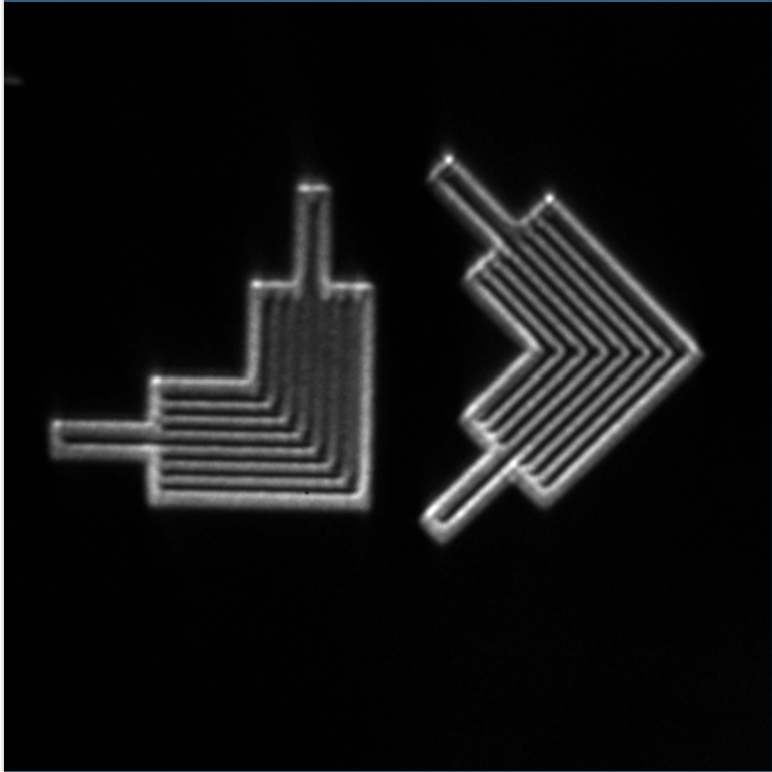


Elbows, 100-nm CD

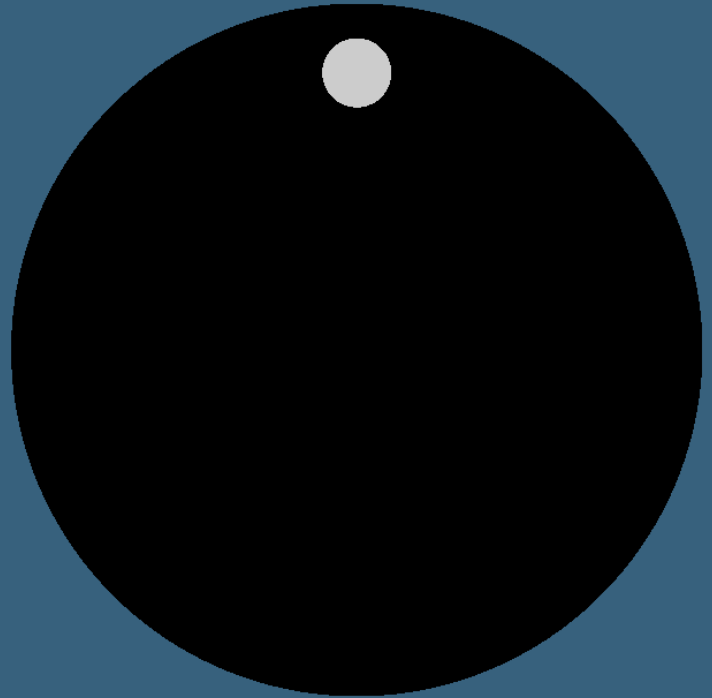


0.33 4xNA pupil

Pupil-fill affects imaging

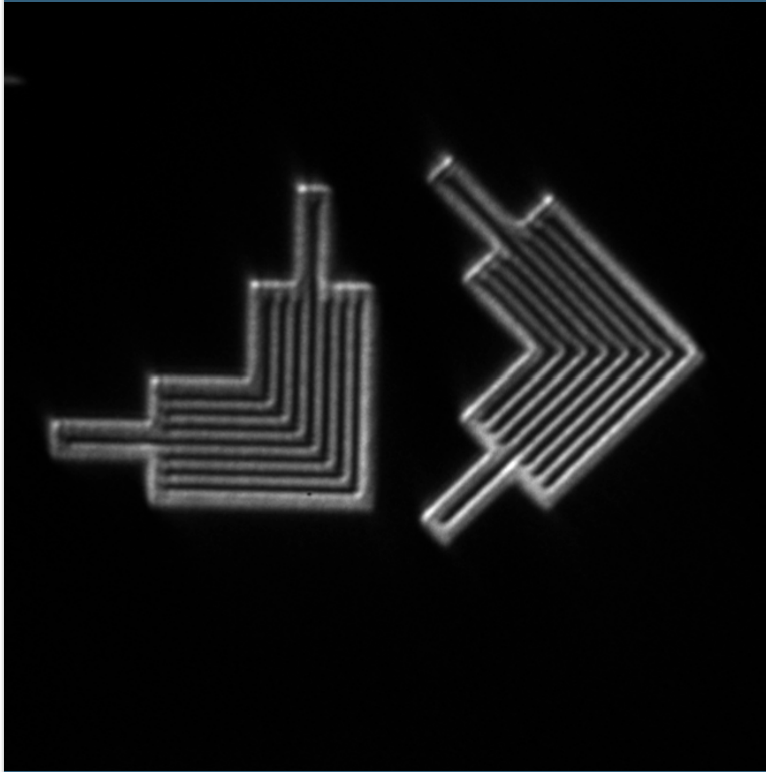


Elbows, 100-nm CD

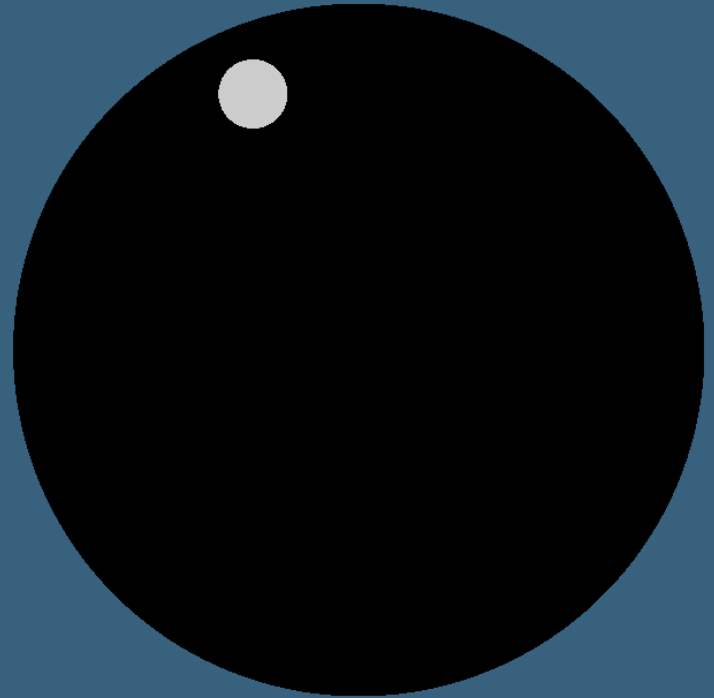


0.33 4xNA pupil

Pupil-fill affects imaging

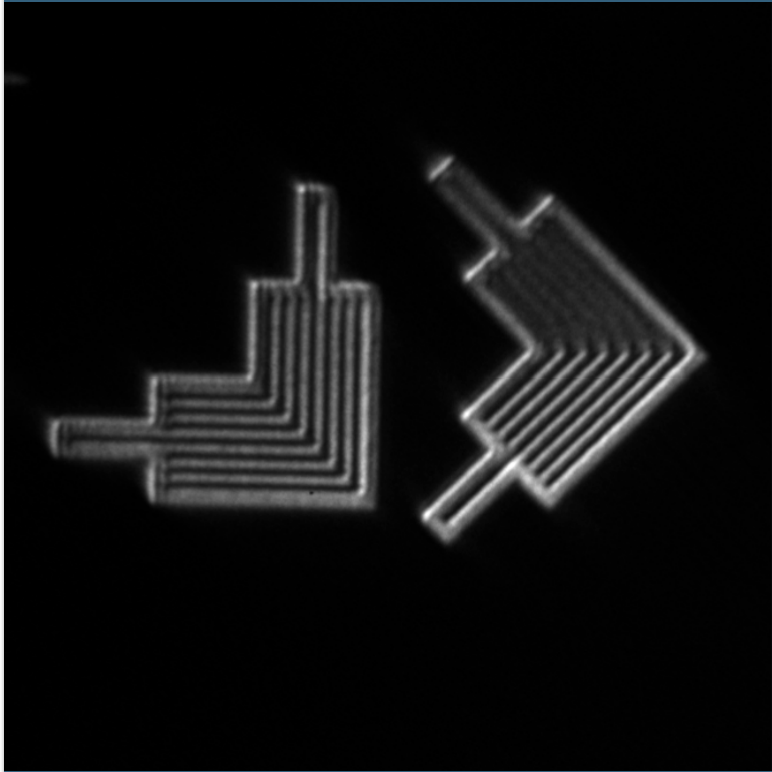


Elbows, 100-nm CD



0.33 4xNA pupil

Pupil-fill affects imaging

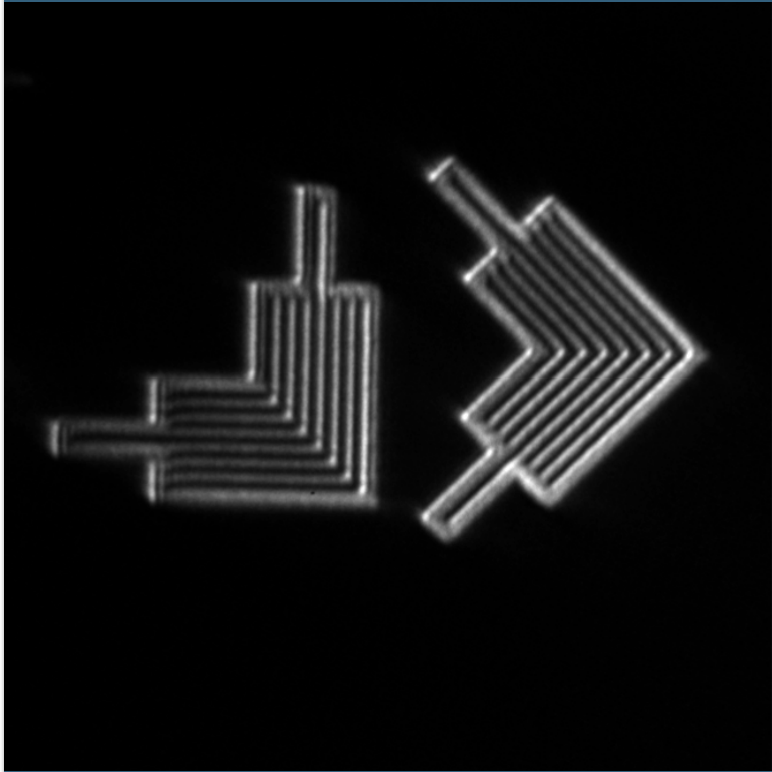


Elbows, 100-nm CD

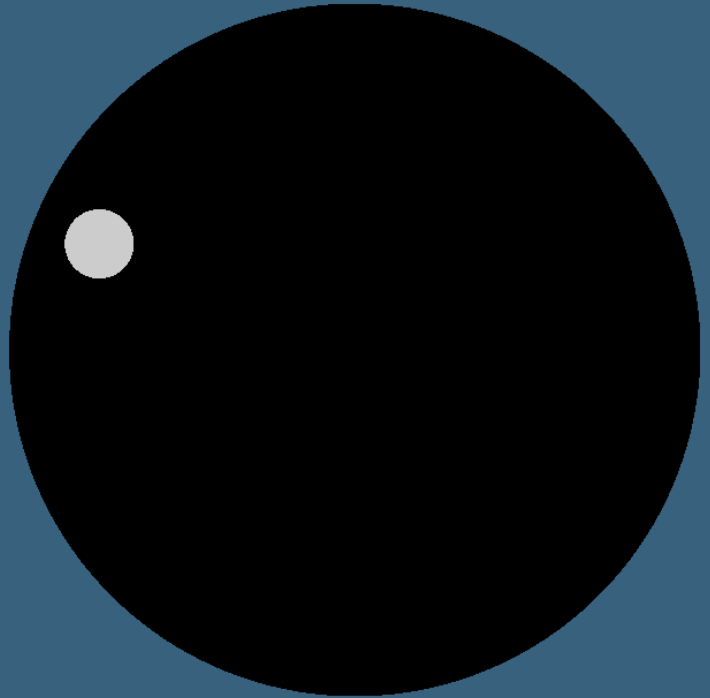


0.33 4xNA pupil

Pupil-fill affects imaging

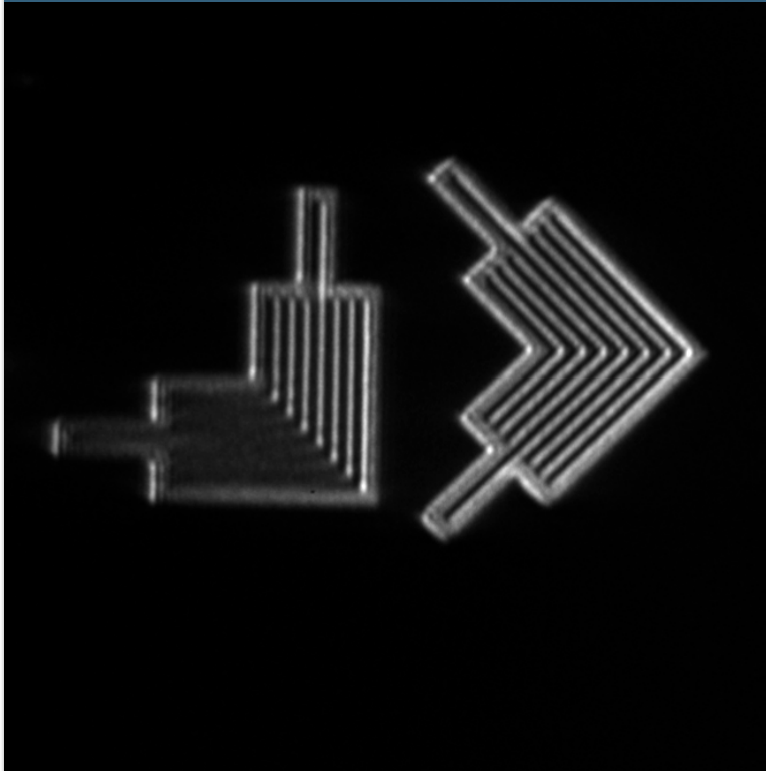


Elbows, 100-nm CD

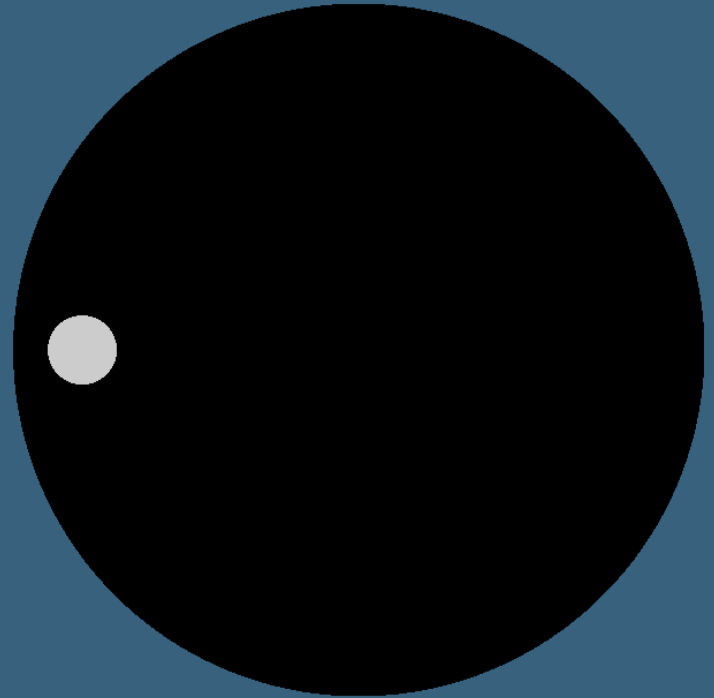


0.33 4xNA pupil

Pupil-fill affects imaging

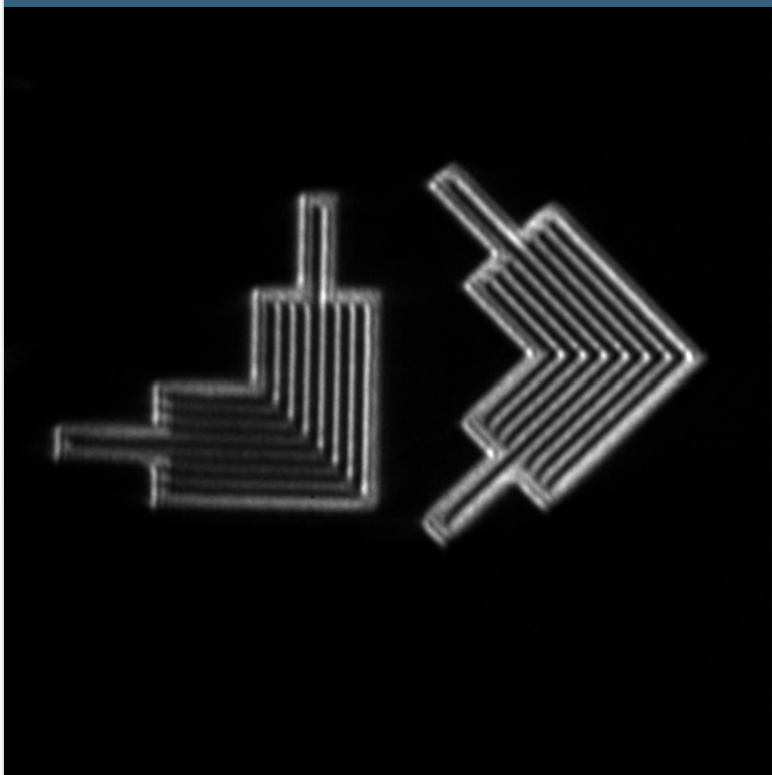


Elbows, 100-nm CD

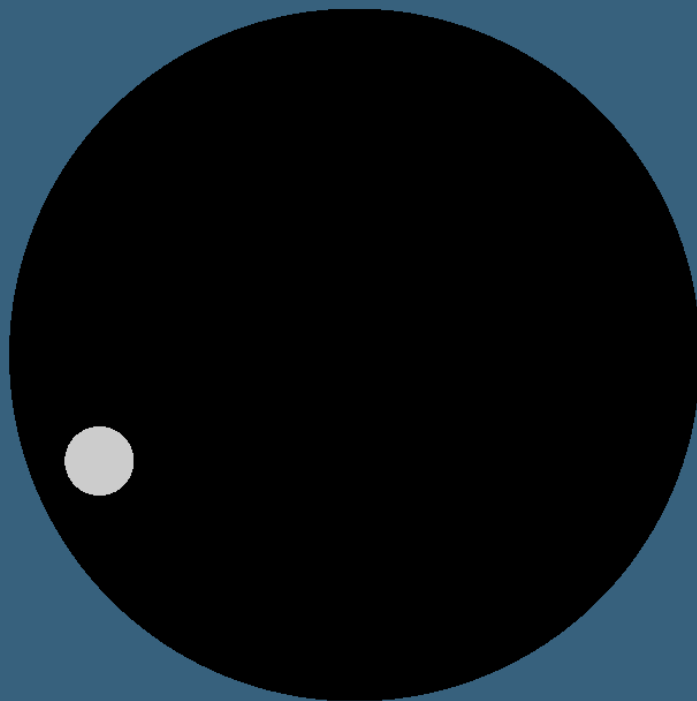


0.33 4xNA pupil

Pupil-fill affects imaging

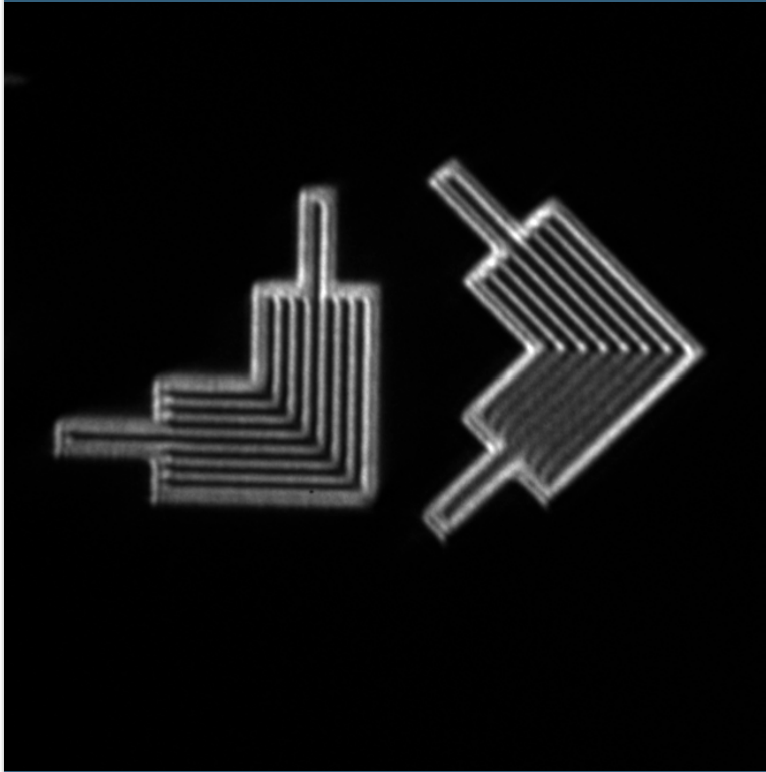


Elbows, 100-nm CD



0.33 4xNA pupil

Pupil-fill affects imaging

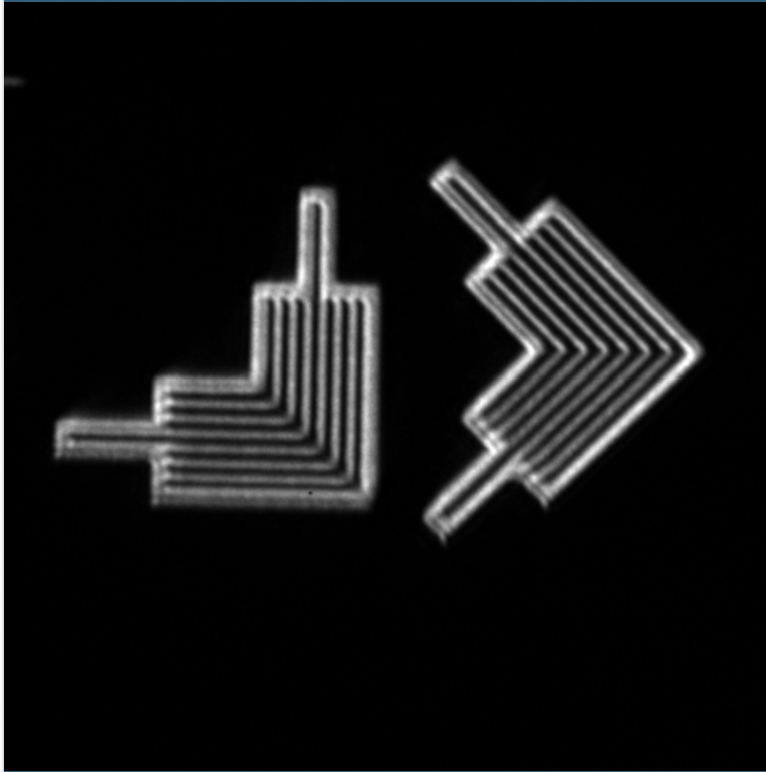


Elbows, 100-nm CD

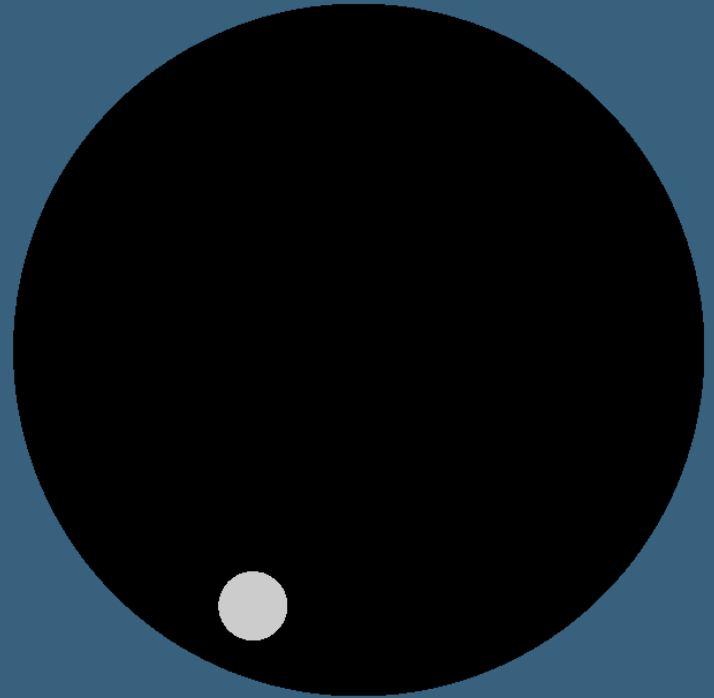


0.33 4xNA pupil

Pupil-fill affects imaging

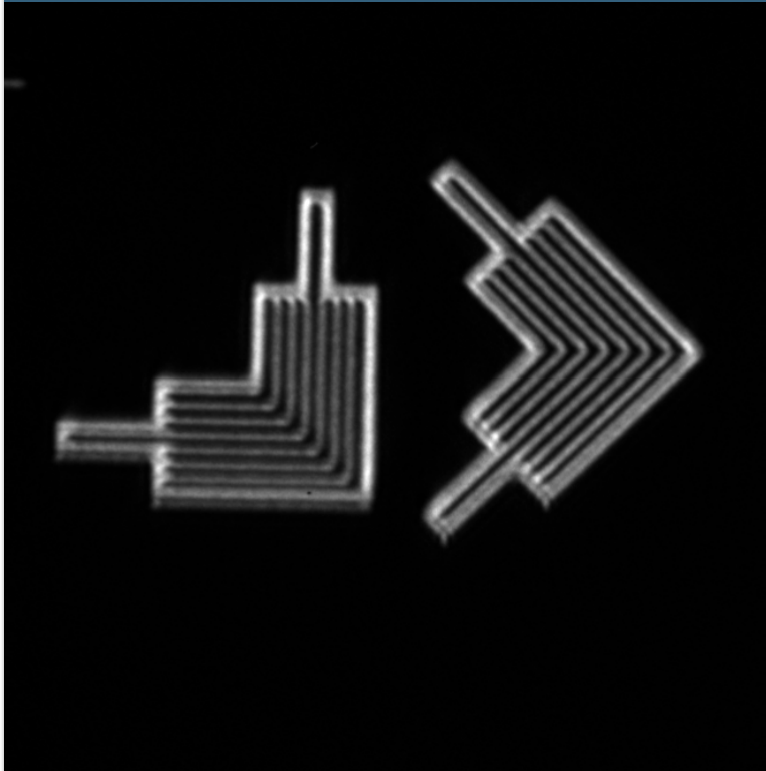


Elbows, 100-nm CD

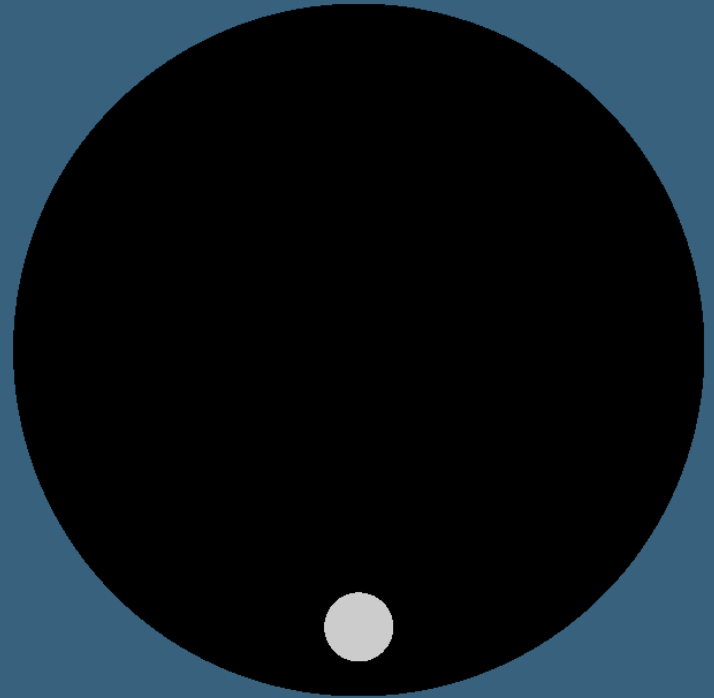


0.33 4xNA pupil

Pupil-fill affects imaging

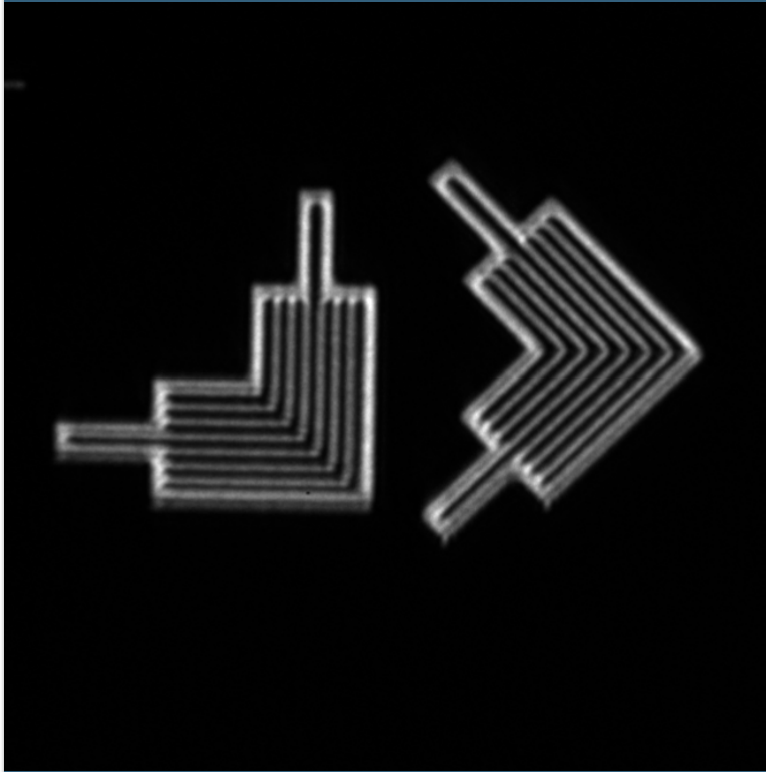


Elbows, 100-nm CD



0.33 4xNA pupil

Pupil-fill affects imaging

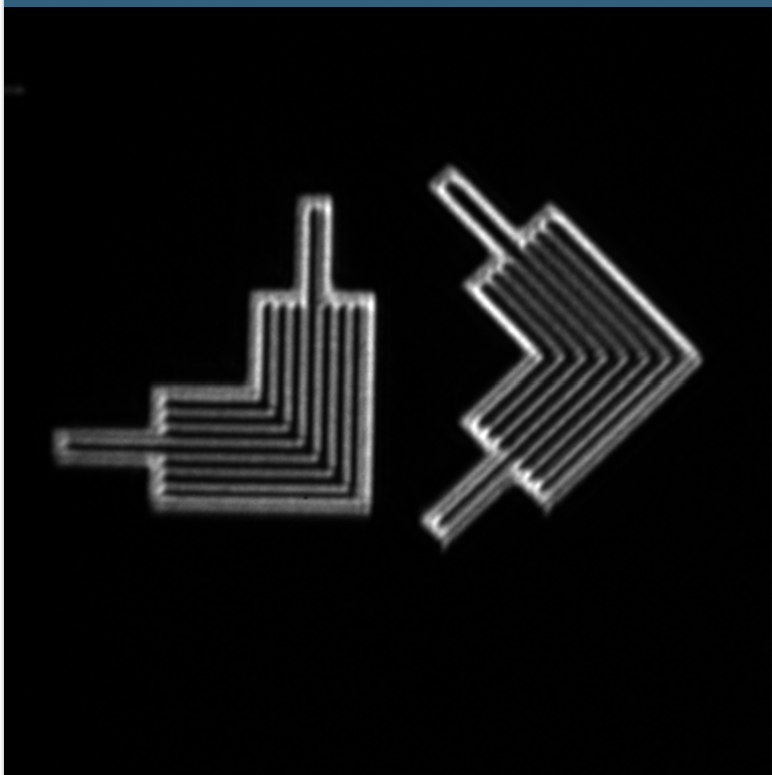


Elbows, 100-nm CD

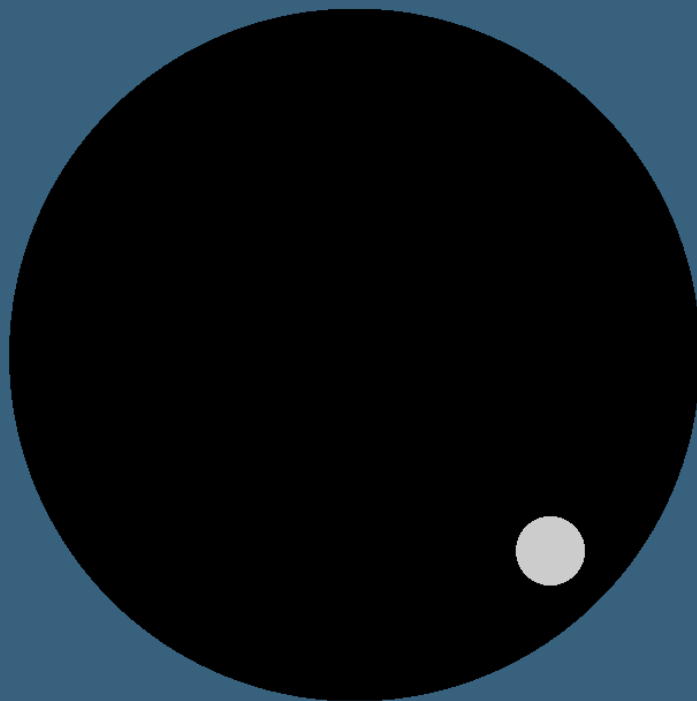


0.33 4xNA pupil

Pupil-fill affects imaging

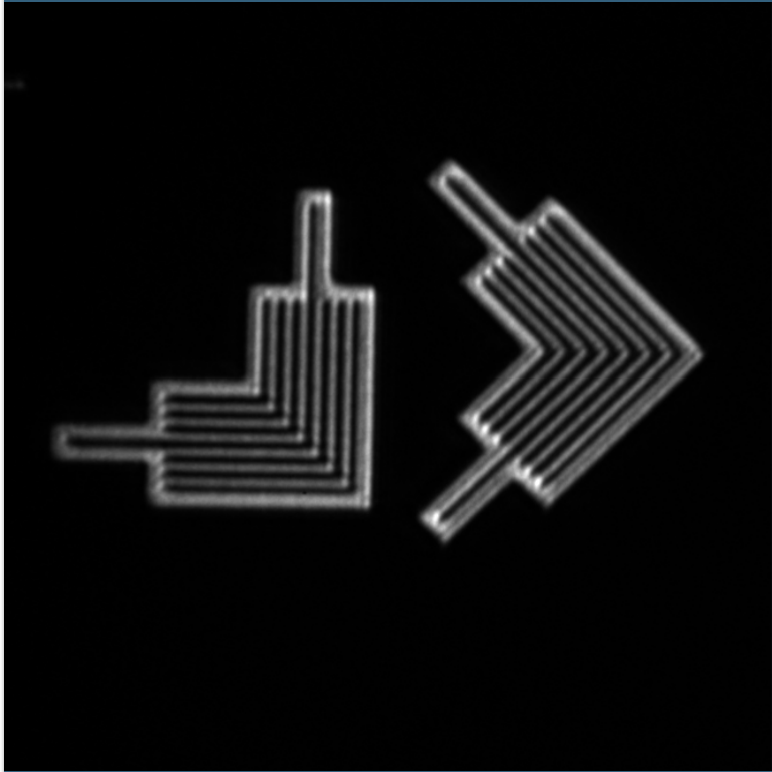


Elbows, 100-nm CD

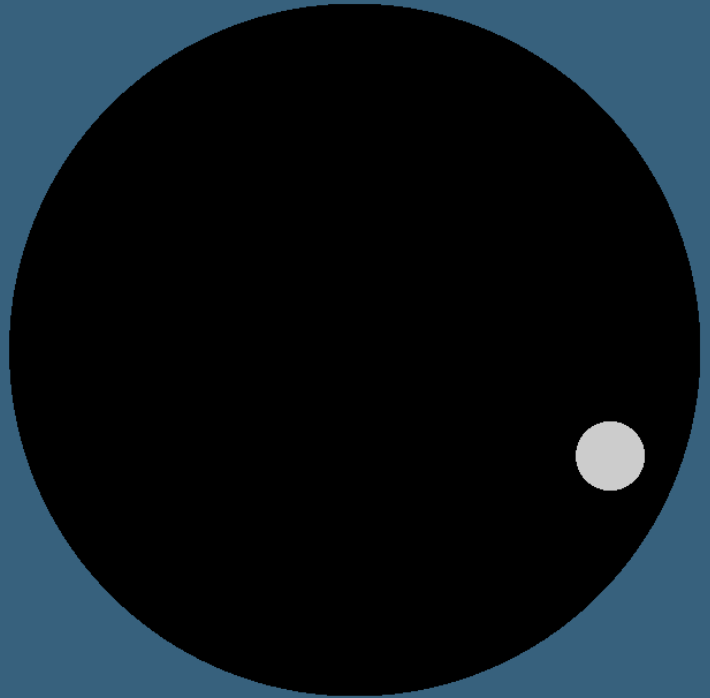


0.33 4xNA pupil

Pupil-fill affects imaging

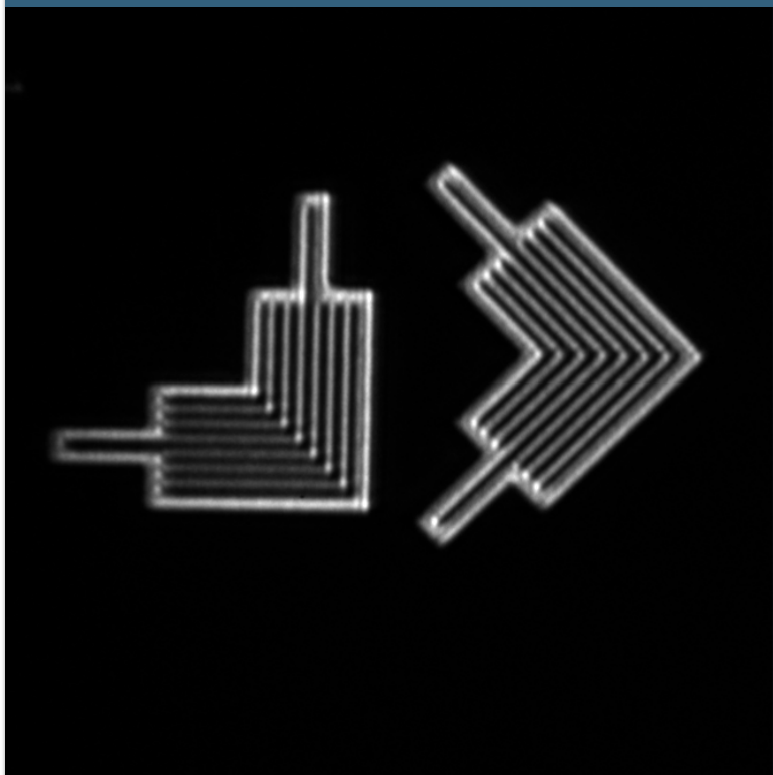


Elbows, 100-nm CD

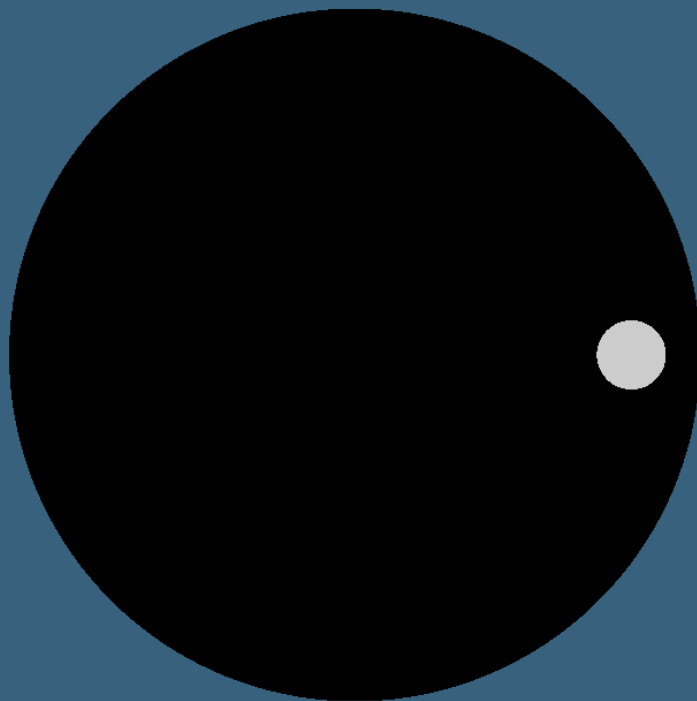


0.33 4xNA pupil

Pupil-fill affects imaging

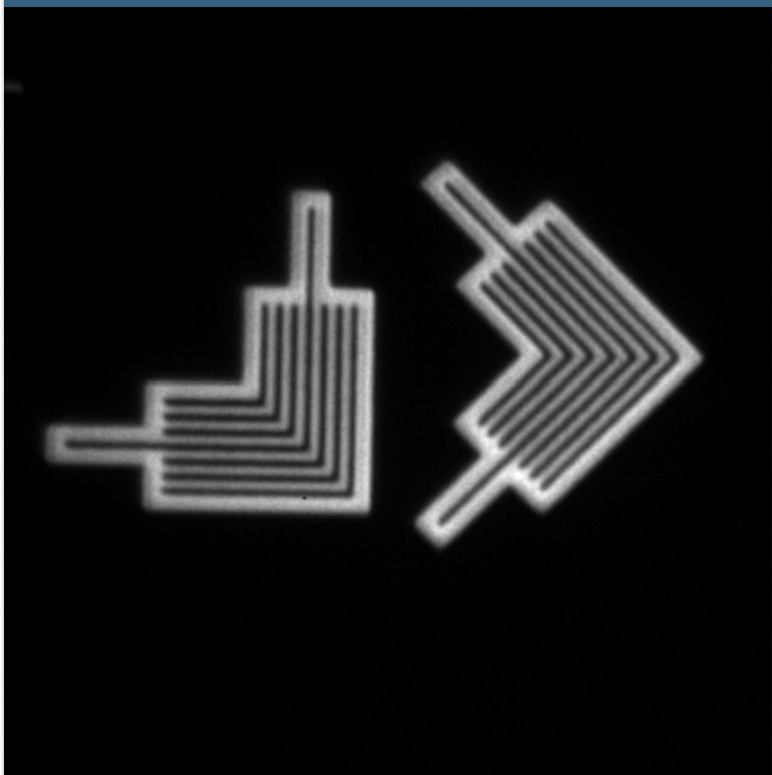


Elbows, 100-nm CD



0.33 4xNA pupil

Pupil-fill affects imaging

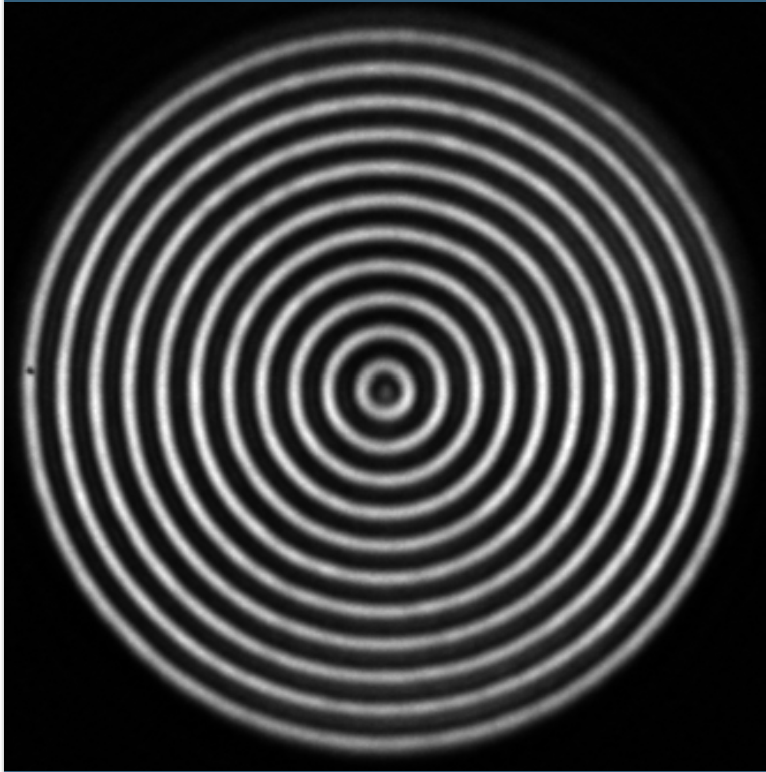


Elbows, 100-nm CD



0.33 4xNA pupil

Coherence affects imaging



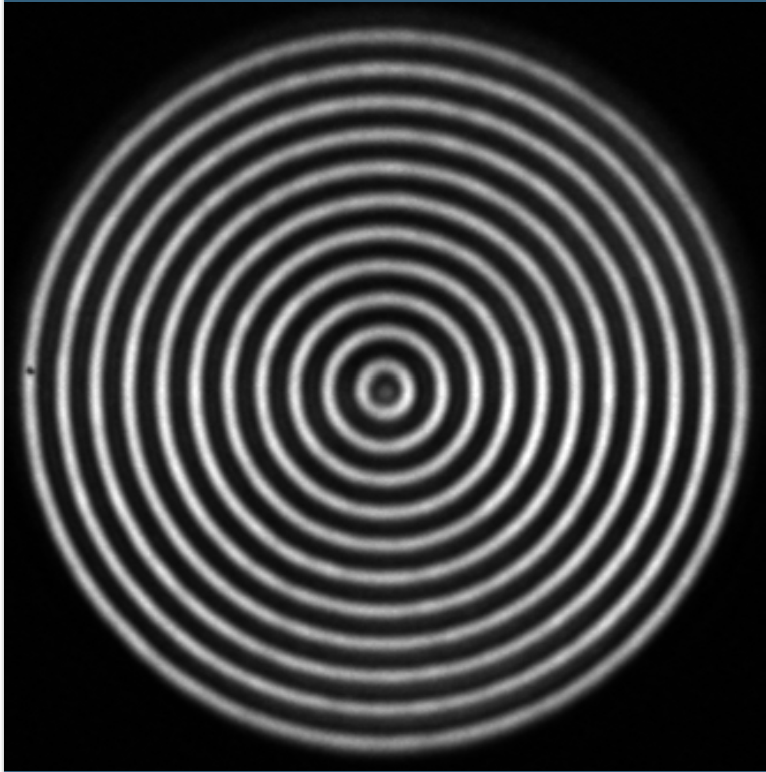
Circles, 110-nm CD



0.33 4xNA pupil

$$\sigma = 0.1$$

Coherence affects imaging



Circles, 110-nm CD

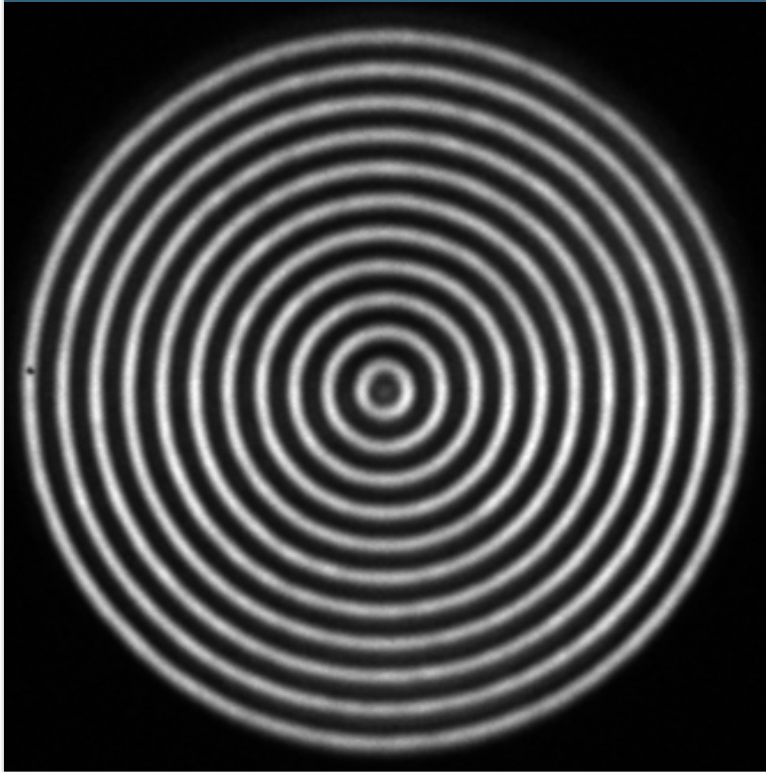
SHARP



0.33 4xNA pupil

$$\sigma = 0.2$$

Coherence affects imaging



Circles, 110-nm CD

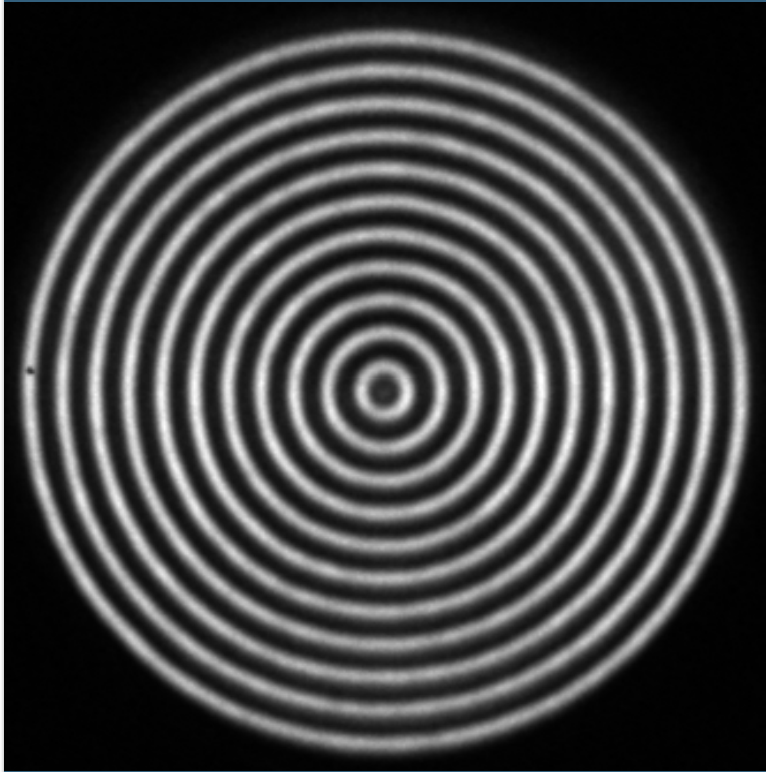
SHARP



0.33 NA pupil

$$\sigma = 0.3$$

Coherence affects imaging



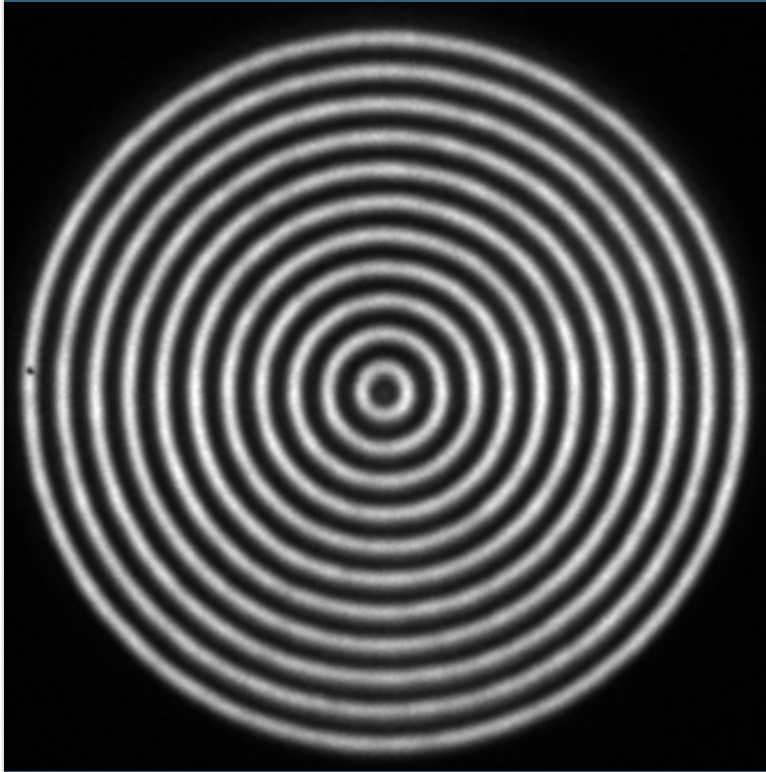
Circles, 110-nm CD



0.33 4xNA pupil

$$\sigma = 0.4$$

Coherence affects imaging



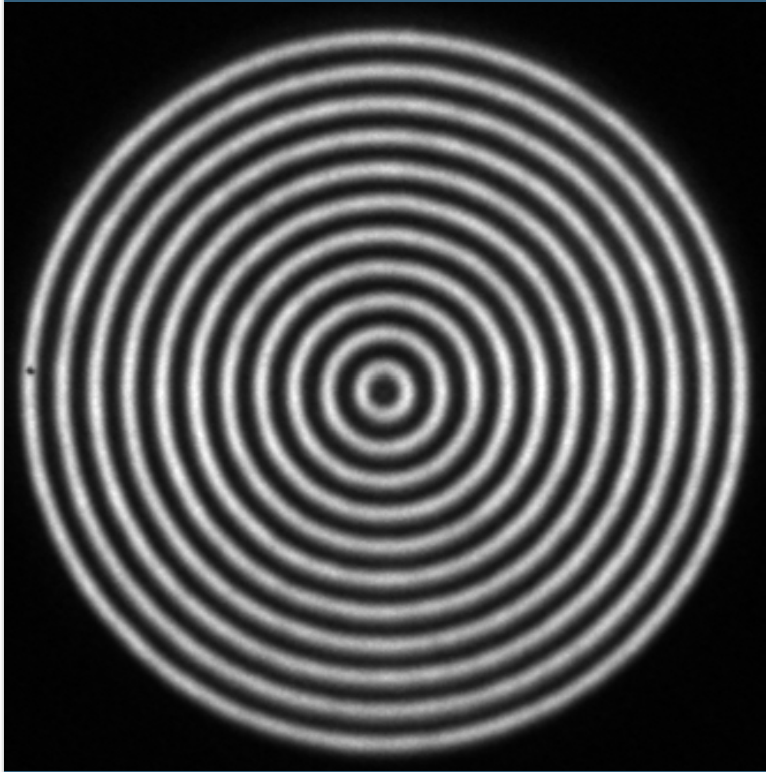
Circles, 110-nm CD



0.33 4xNA pupil

$$\sigma = 0.5$$

Coherence affects imaging



Circles, 110-nm CD

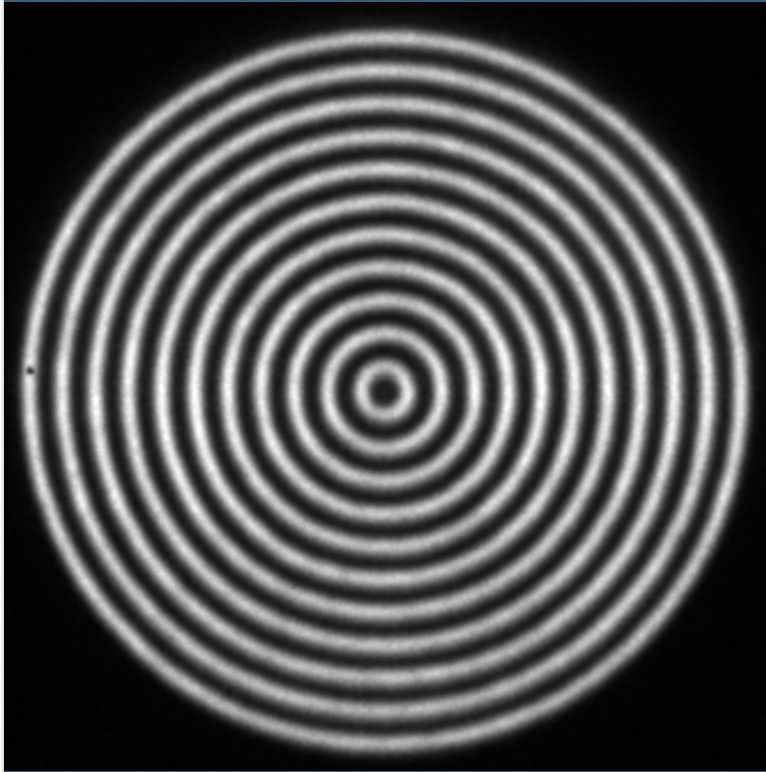
SHARP



0.33 NA pupil

$$\sigma = 0.6$$

Coherence affects imaging



Circles, 110-nm CD

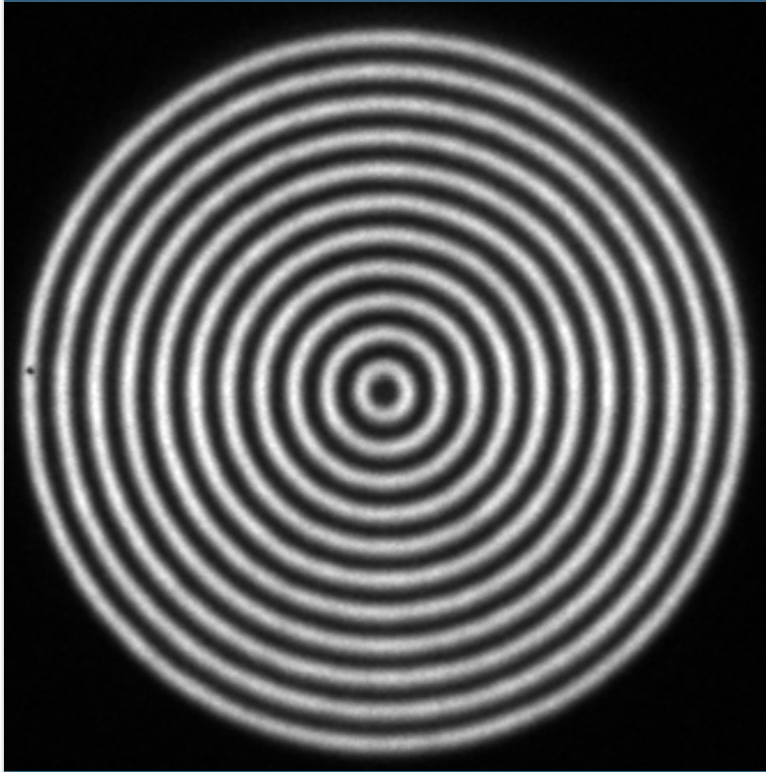
SHARP



0.33 NA pupil

$\sigma = 0.7$

Coherence affects imaging



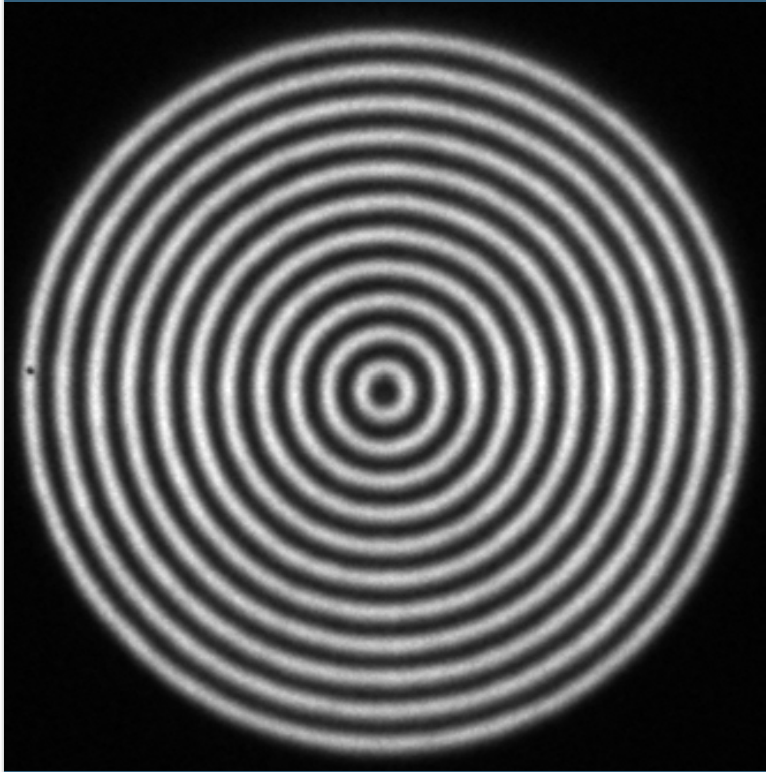
Circles, 110-nm CD



0.33 4xNA pupil

$$\sigma = 0.8$$

Coherence affects imaging



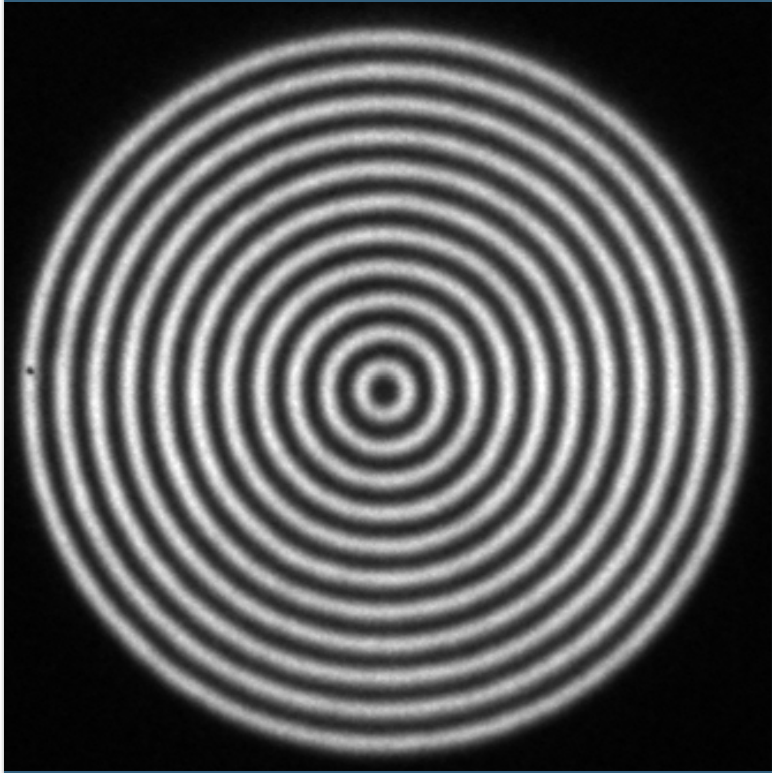
Circles, 110-nm CD



0.33 4xNA pupil

$$\sigma = 0.9$$

Coherence affects imaging



Circles, 110-nm CD

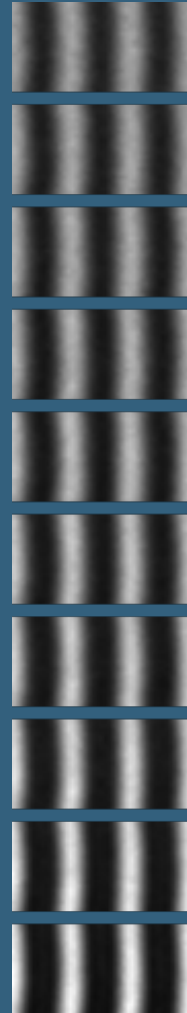
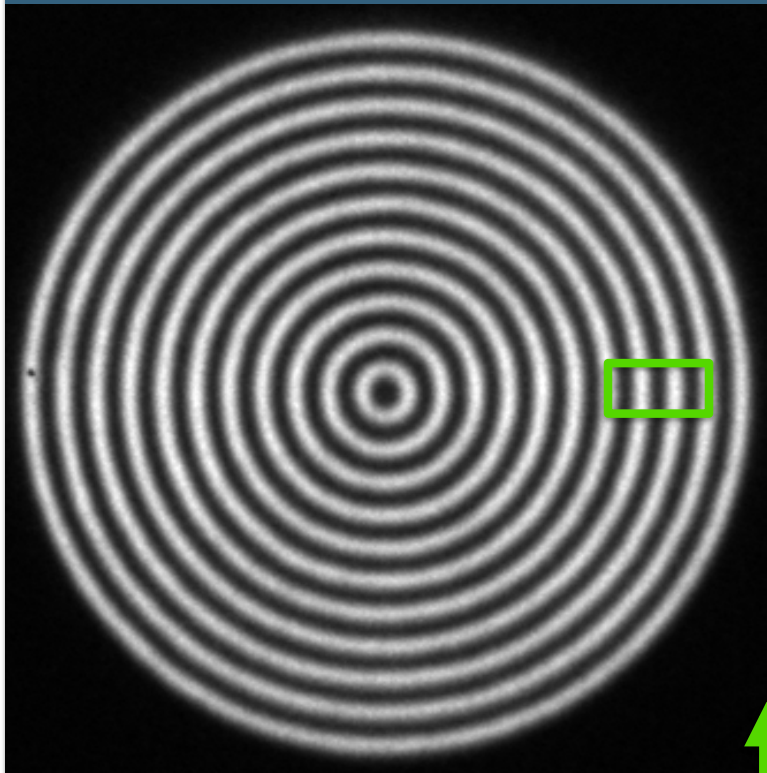
SHARP



0.33 4xNA pupil

$\sigma = 1.0$

Coherence affects imaging

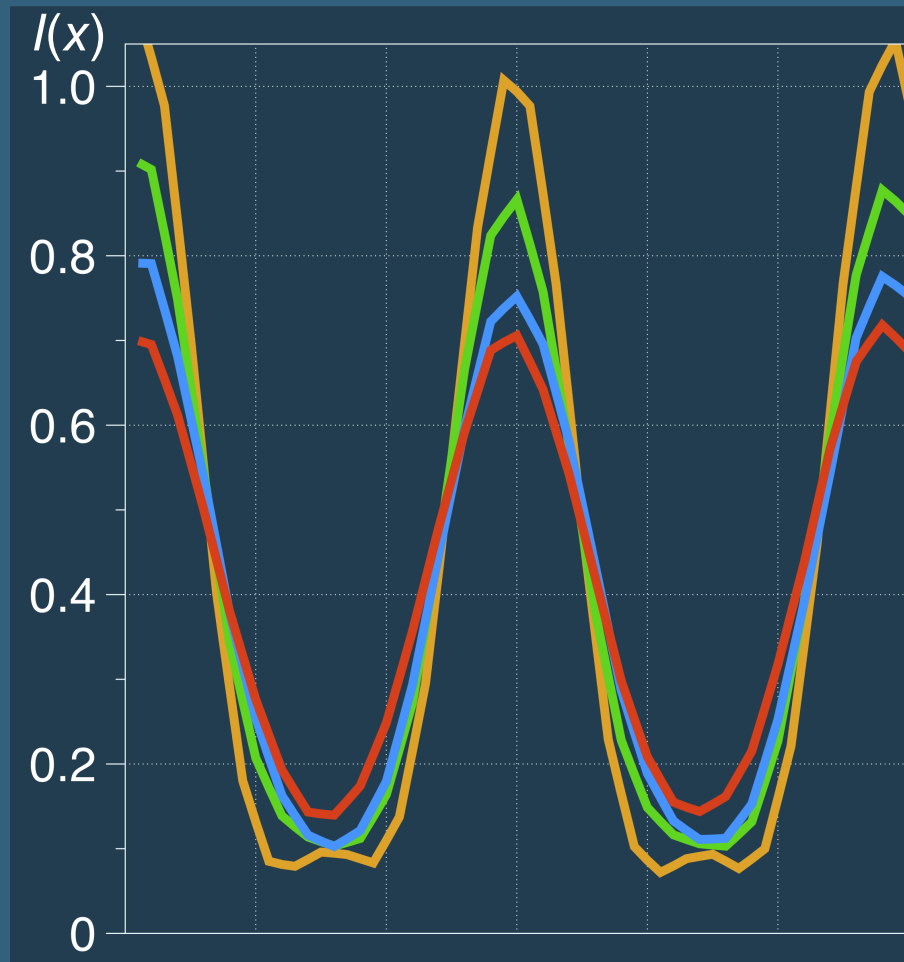
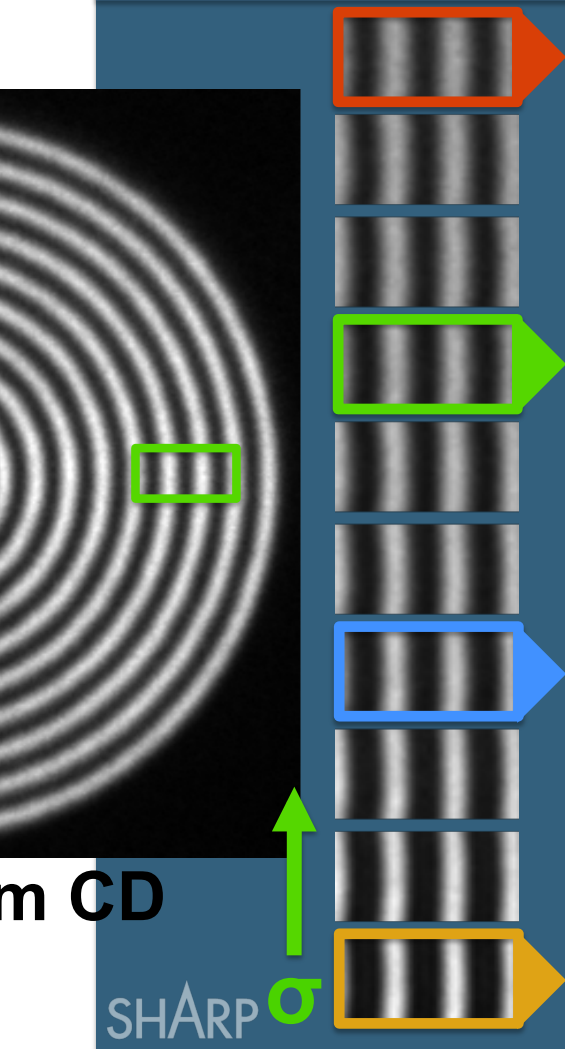


Circles, 110-nm CD

SHARP

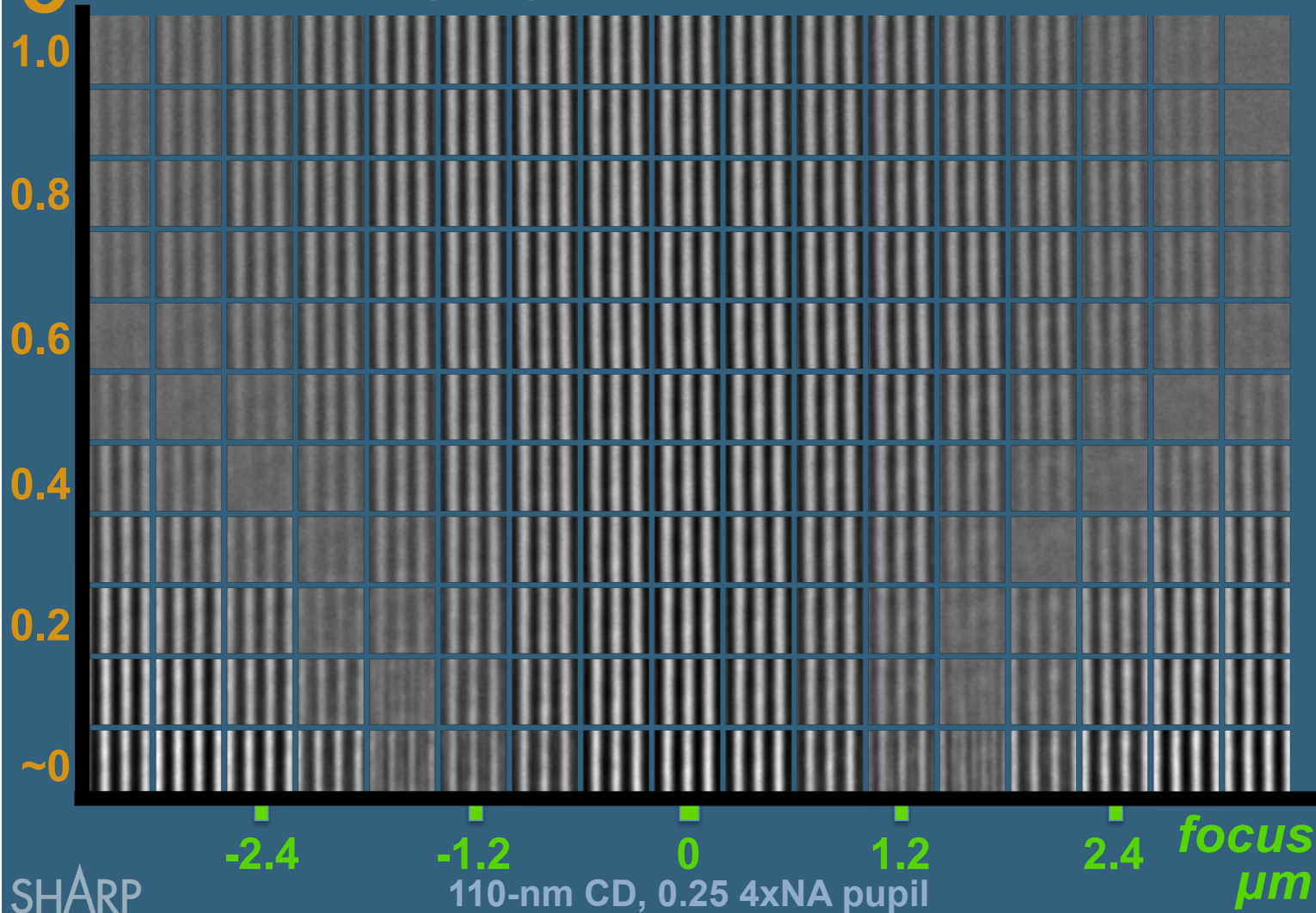
σ

Coherence affects imaging



σ Contrast vs. (z , σ)

**See Mochi, et al.*



**See Mochi, et al.*

Contrast vs. (z , σ)

σ

1.0

0.8

0.6

0.4

0.2

~0

DOF

-2.4

-1.2

0

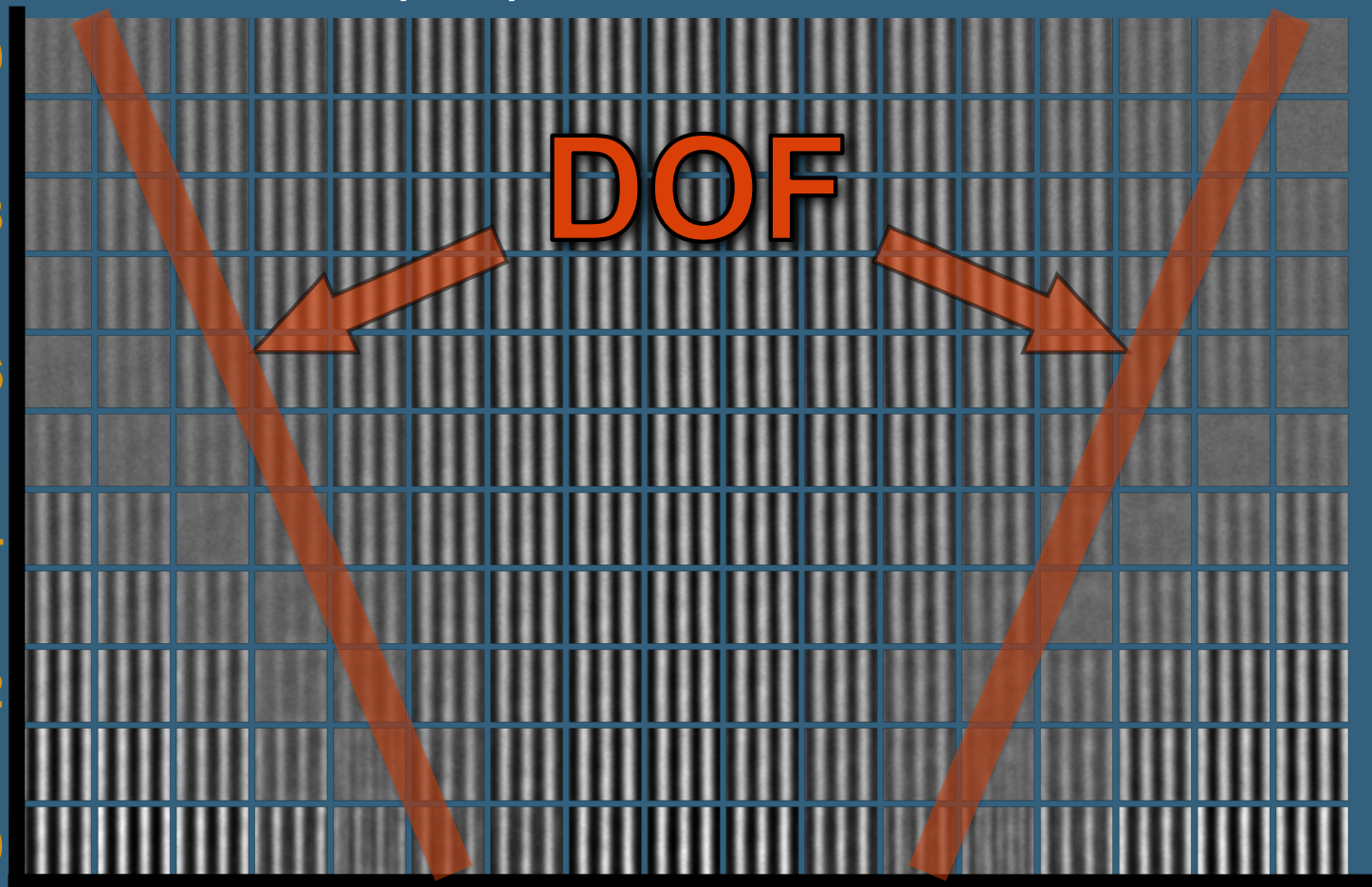
1.2

2.4

*focus
 μm*

SHARP

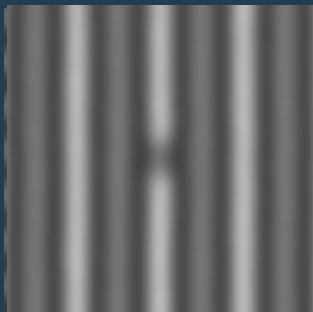
110-nm CD, 0.25 4xNA pupil



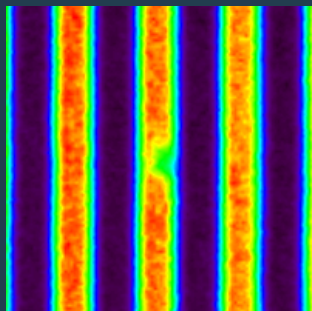
Native defect, illumination studies

Gremlin3, Defect 1439, 200 nm hp

Mask/KLA617
Teron

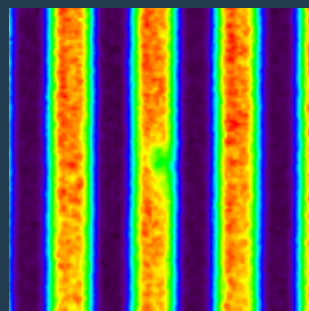


Quasar 45°
illumination



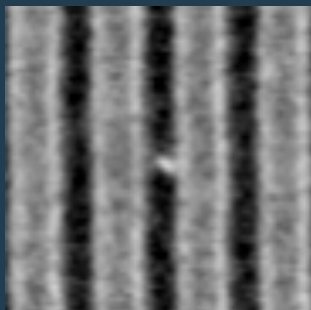
GREMLIN3-T30709-0031

Annular
illumination

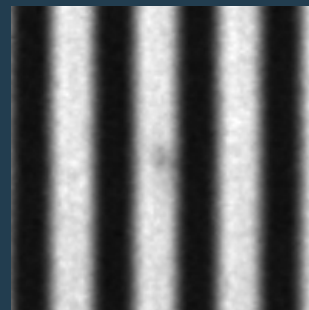


GREMLIN3-T30709-0032

Mask/SEM



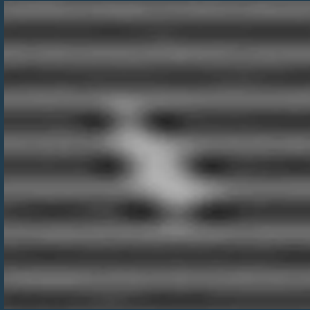
1.5 μm



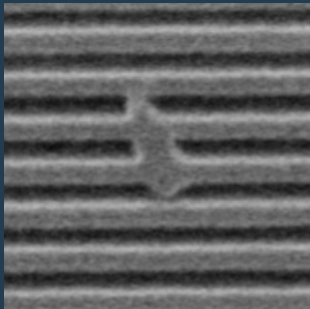
Native defect, illumination studies

Gremlin3, Defect 3200, 110 nm hp

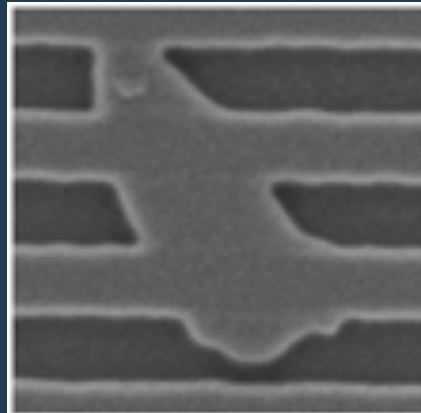
Mask/KLA617
Teron



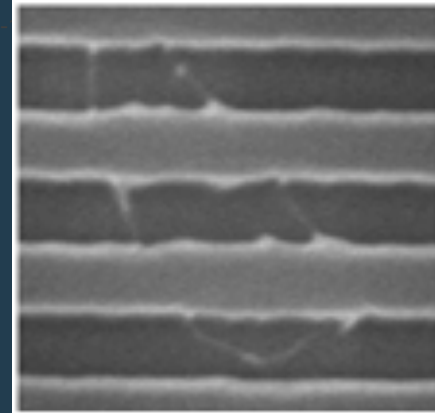
Mask/SEM



Pre-Repair



Post-Repair



Native defect, illumination studies

Gremlin3, Defect 3200, 110 nm hp

**Mask/KLA617
Teron**

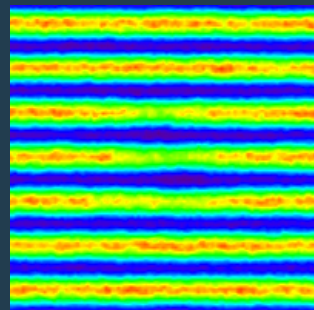


**Disk 0.9 σ
illumination**



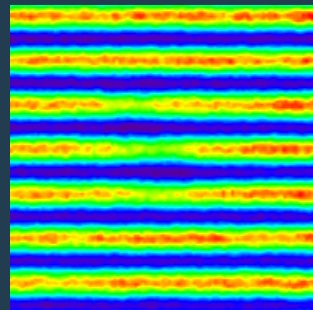
GREMLIN3-130709-0012

**Annular
illumination**



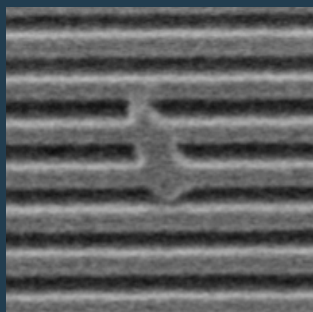
GREMLIN3-130709-0029

**Quasar 45°
illumination**

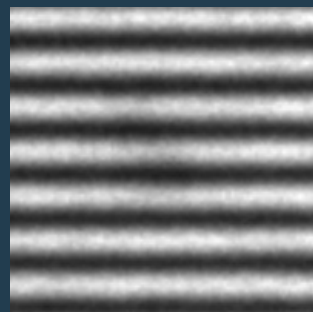
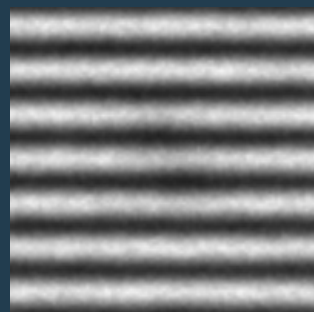


GREMLIN3-130709-0030

Mask/SEM



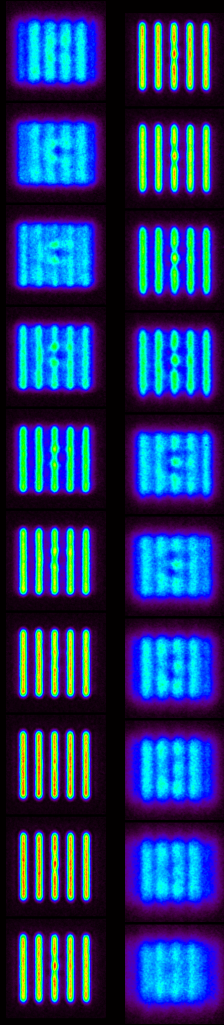
1.5 μm



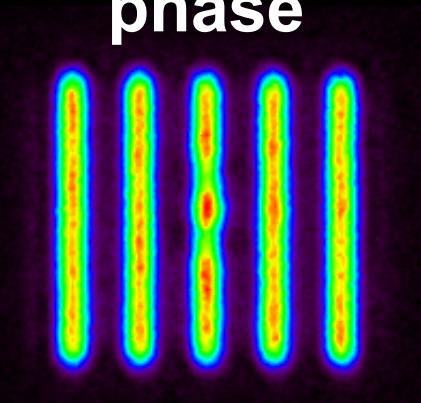
Native phase and amplitude defects



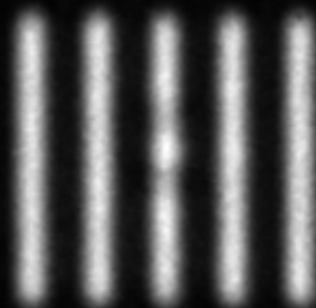
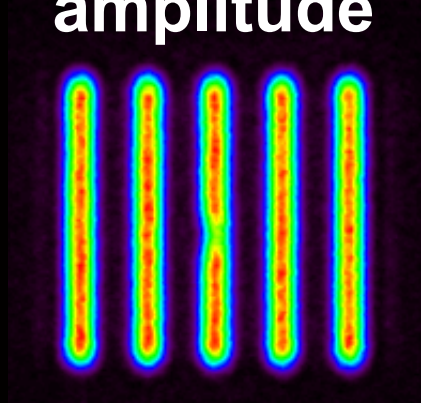
through focus
↓



phase



amplitude



← 2.0 μm →

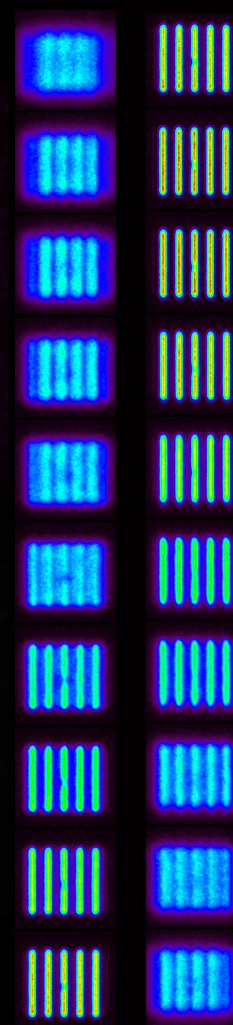
Patriot2, Defect 37

Patriot2-130612-0012-0009



Patriot2, Defect 42

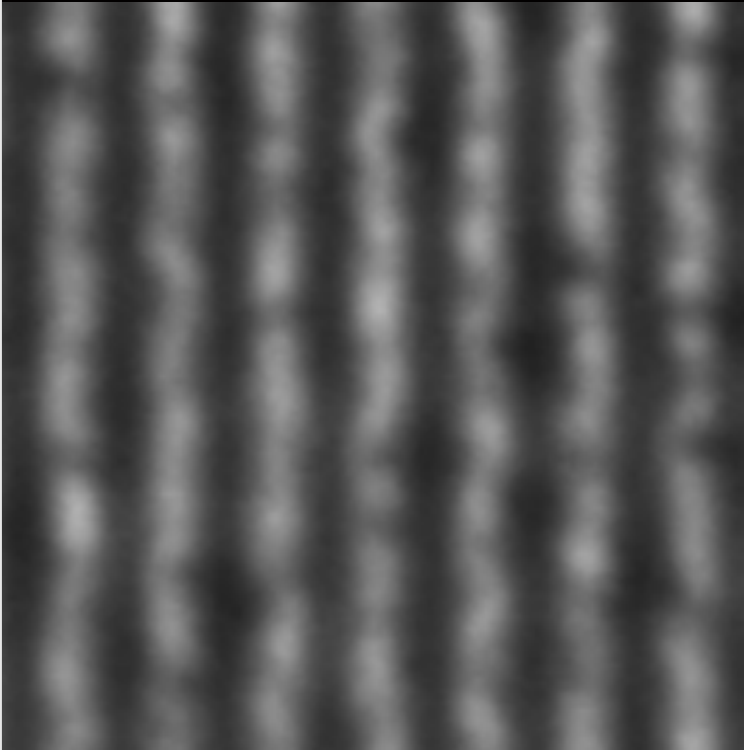
Patriot2-130612-0017-0009



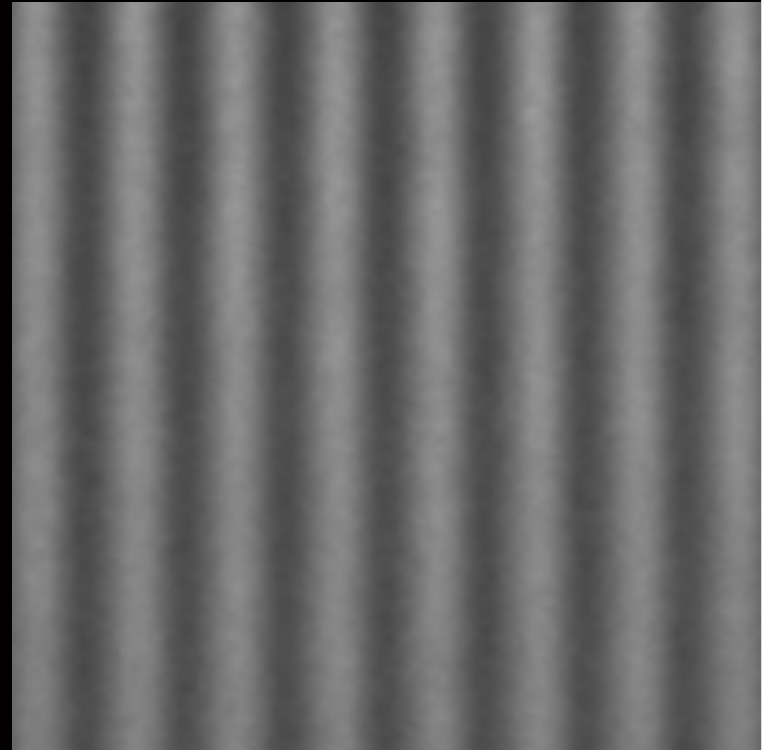
Substrate roughness experiments

2- μm

132-nm hp



IMO239379-130724-0003



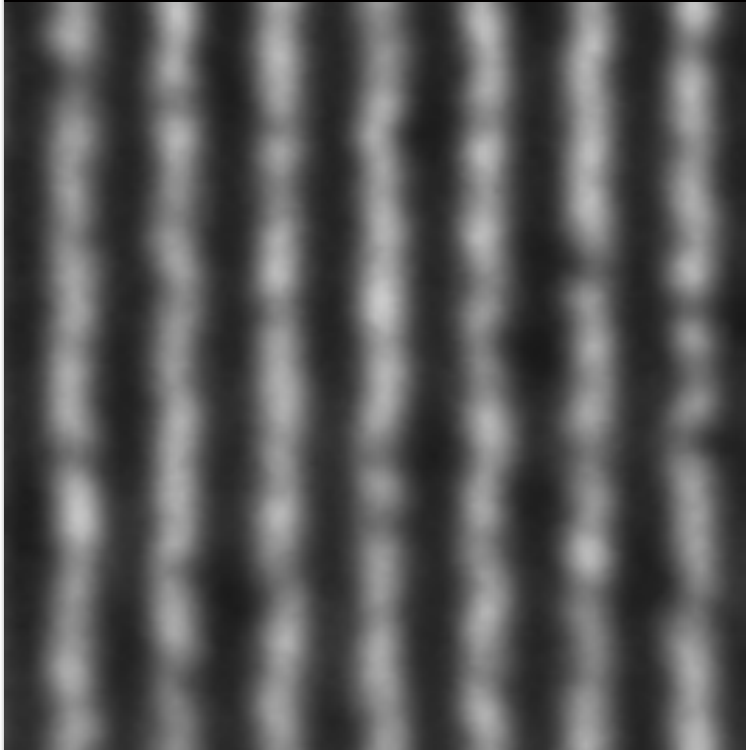
IMO239379-130724-0024



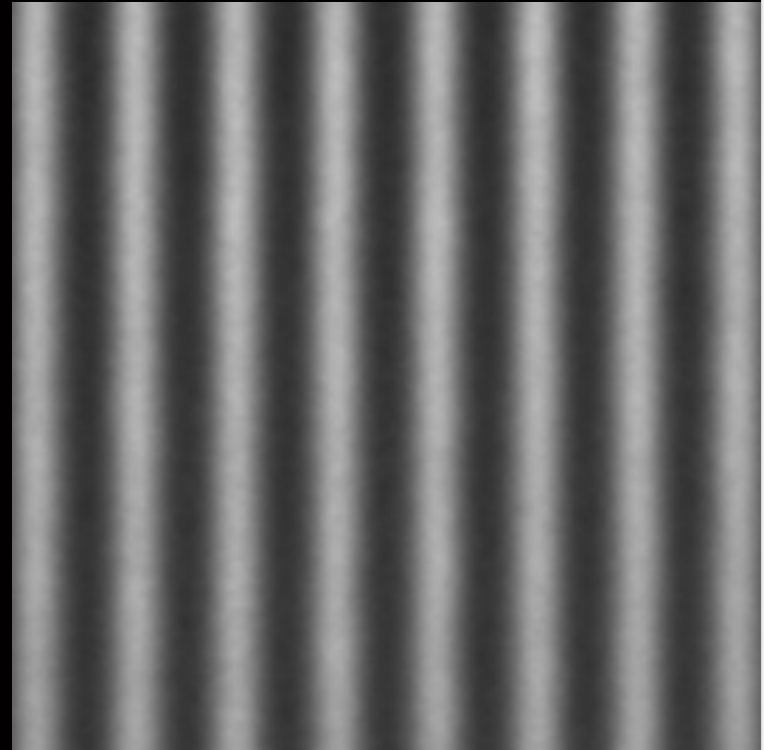
Substrate roughness experiments

2- μm

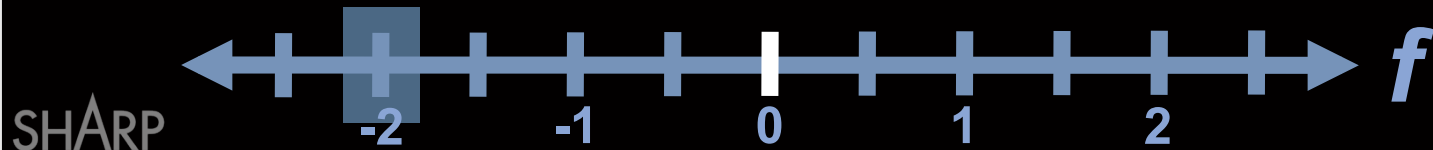
132-nm hp



IMO239379-130724-0003



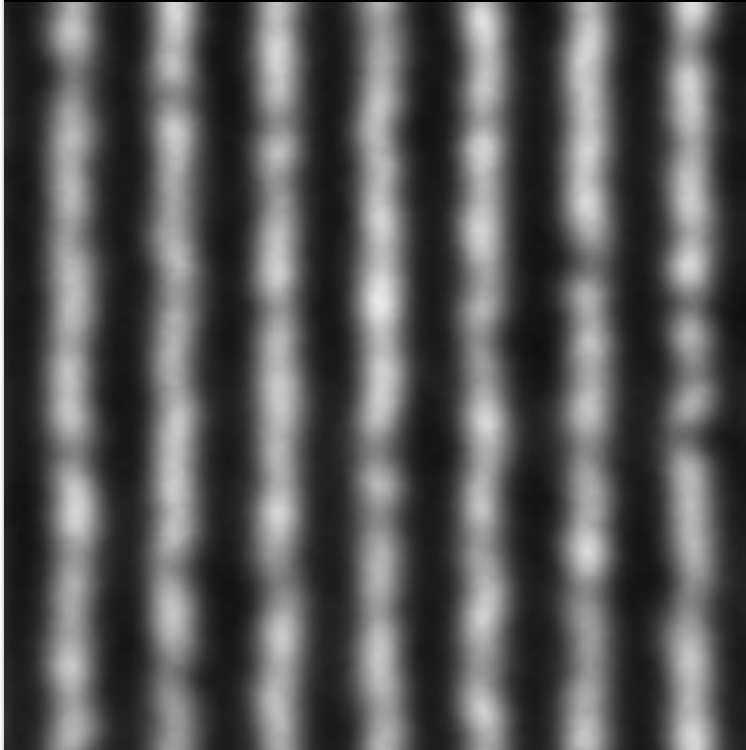
IMO239379-130724-0024



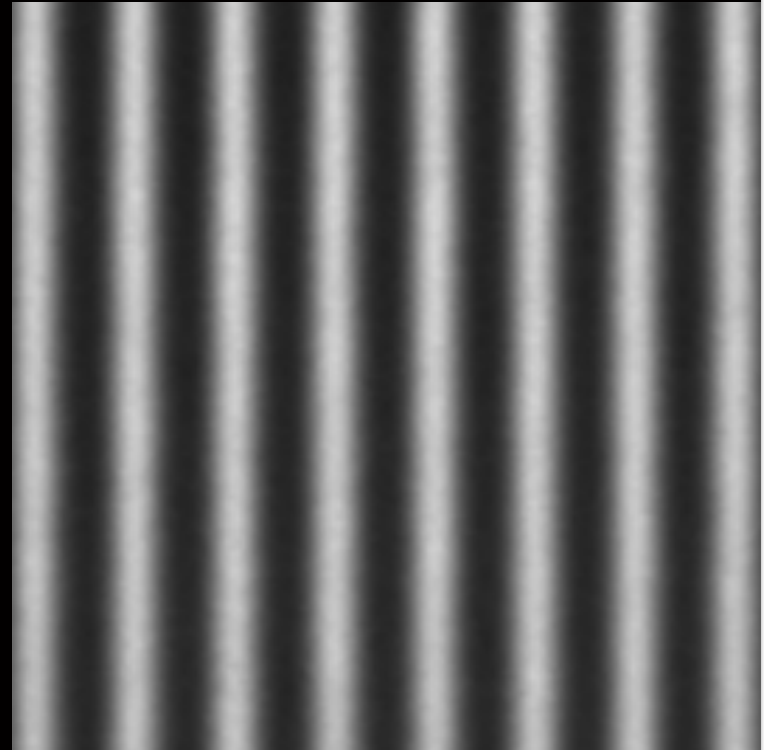
Substrate roughness experiments

2- μm

132-nm hp



IMO239379-130724-0003



IMO239379-130724-0024



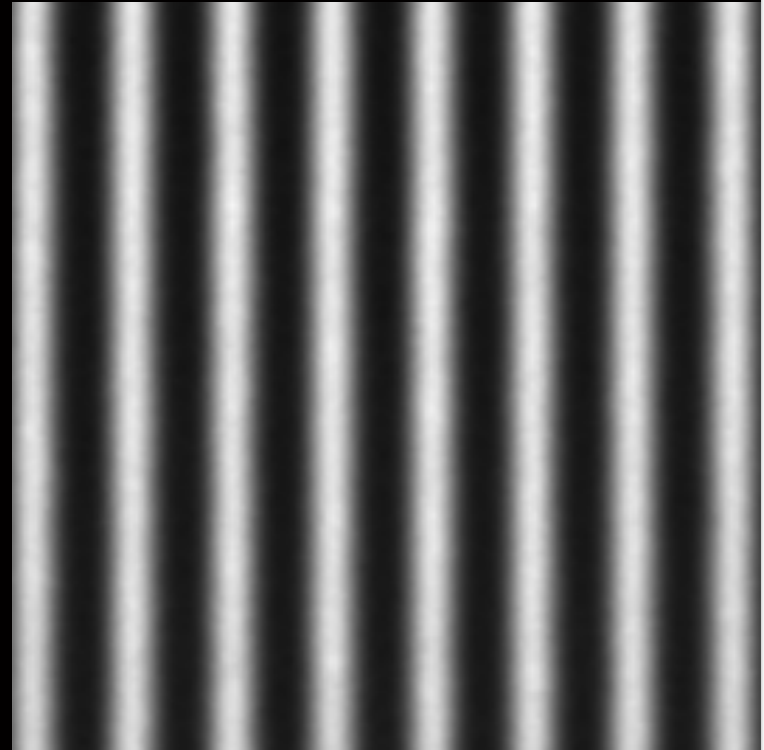
Substrate roughness experiments

2- μm

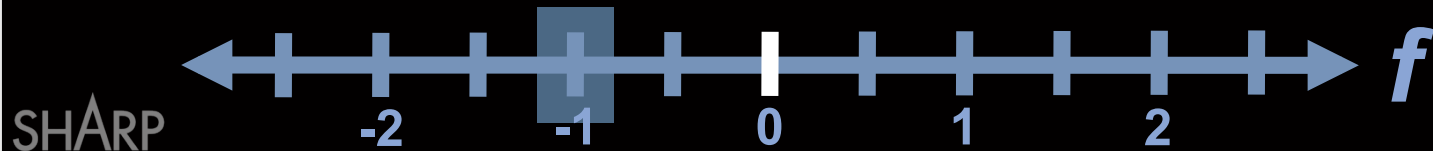
132-nm hp



IMO239379-130724-0003



IMO239379-130724-0024



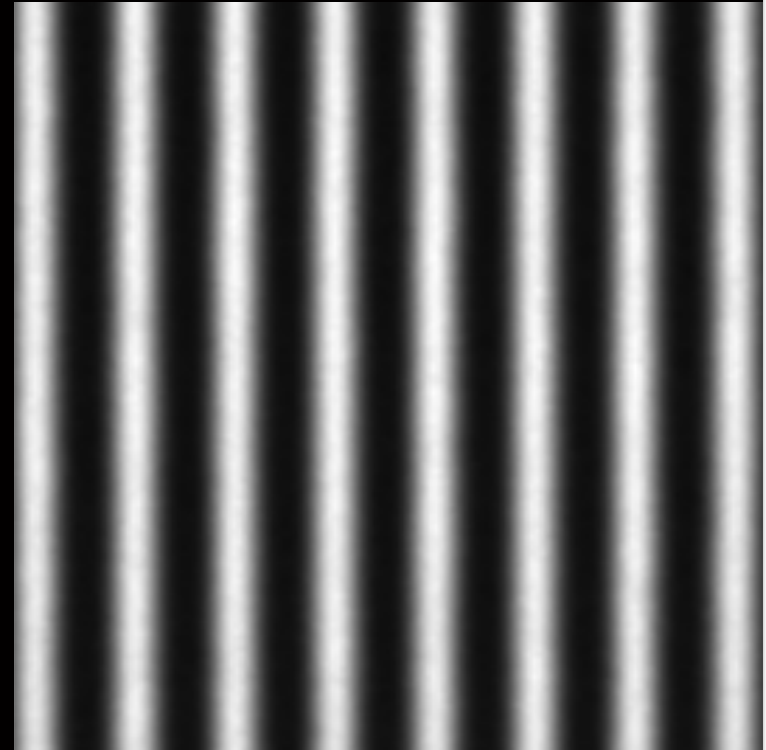
Substrate roughness experiments

2- μm

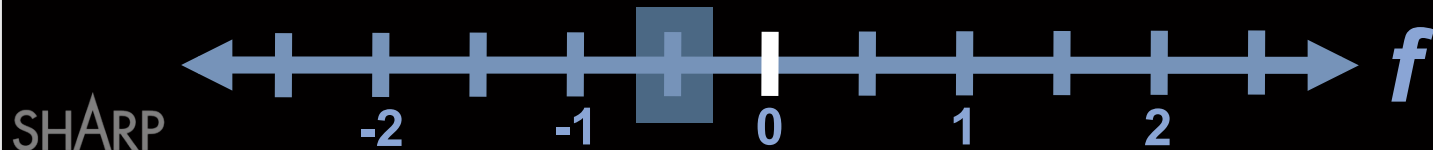
132-nm hp



IMO239379-130724-0003



IMO239379-130724-0024



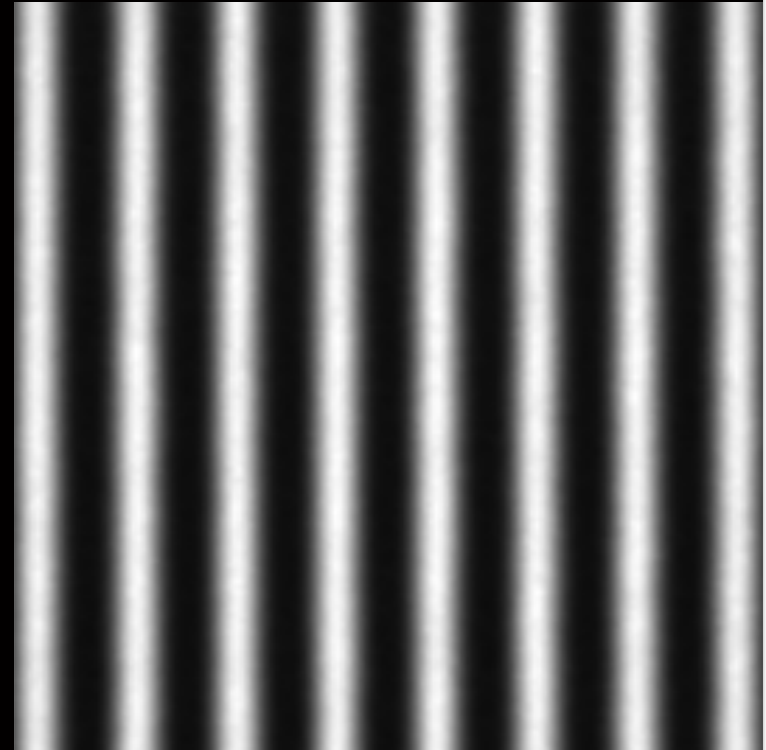
Substrate roughness experiments

2- μm

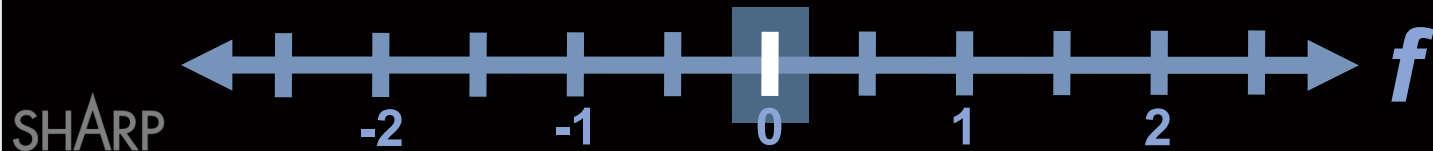
132-nm hp



IMO239379-130724-0003



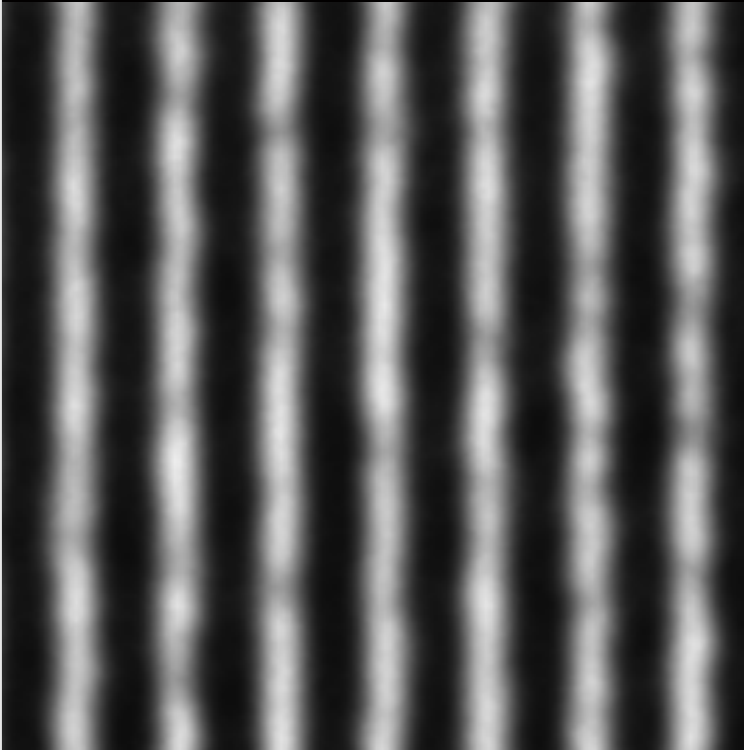
IMO239379-130724-0024



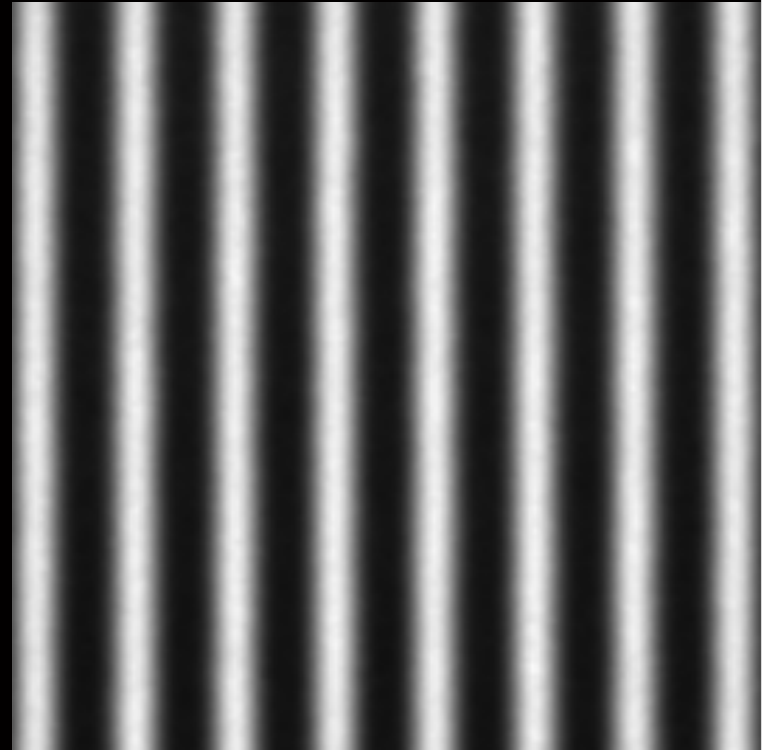
Substrate roughness experiments

2- μm

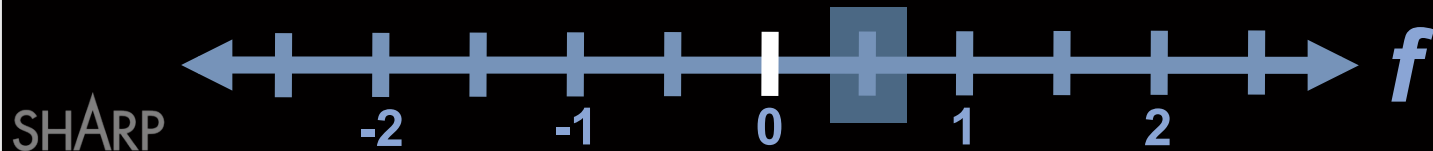
132-nm hp



IMO239379-130724-0003



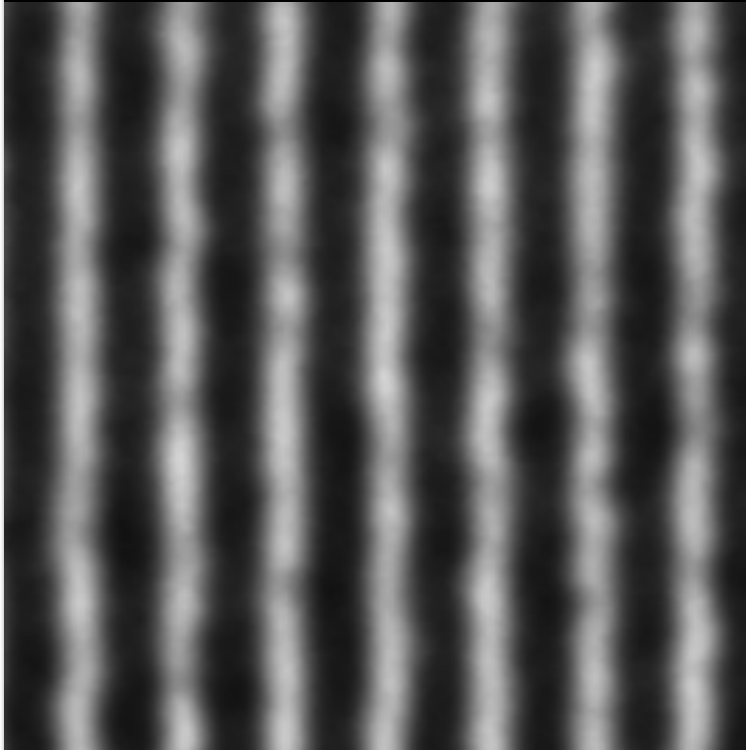
IMO239379-130724-0024



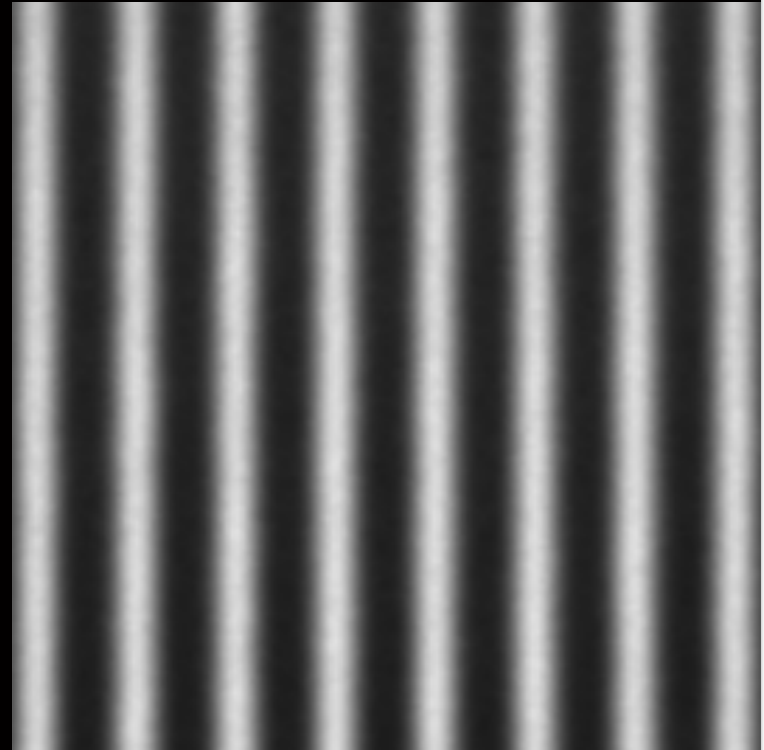
Substrate roughness experiments

2- μm

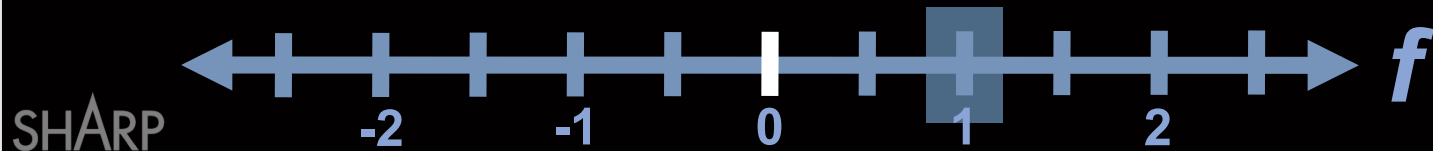
132-nm hp



IMO239379-130724-0003



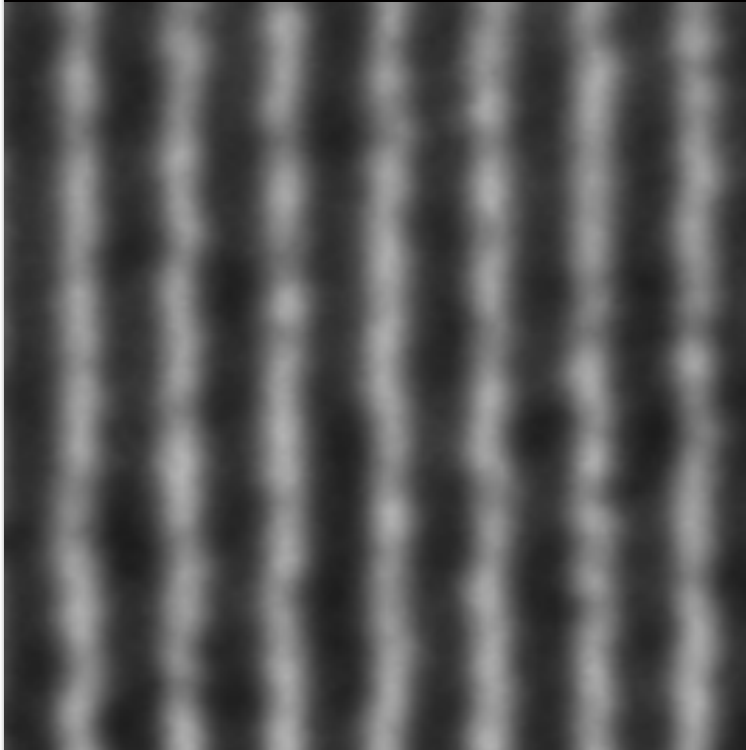
IMO239379-130724-0024



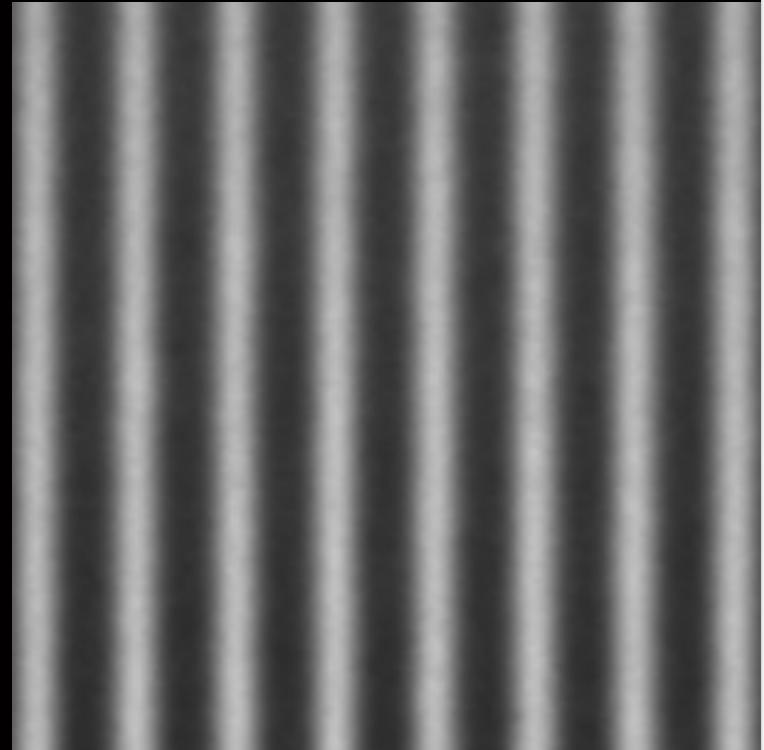
Substrate roughness experiments

2- μm

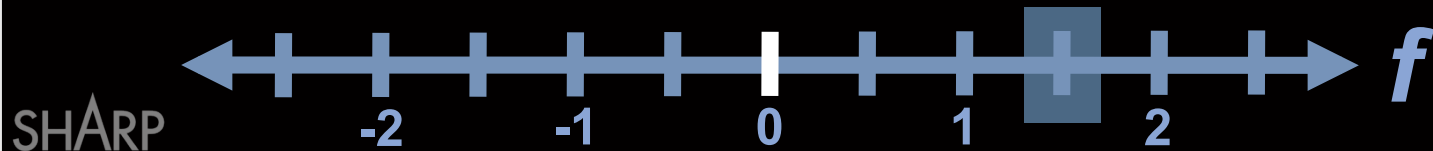
132-nm hp



IMO239379-130724-0003



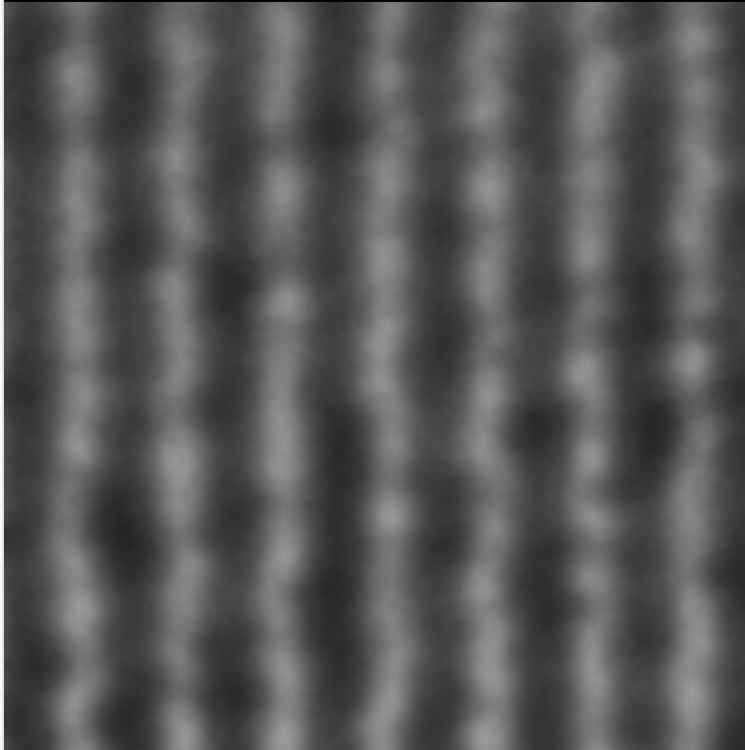
IMO239379-130724-0024



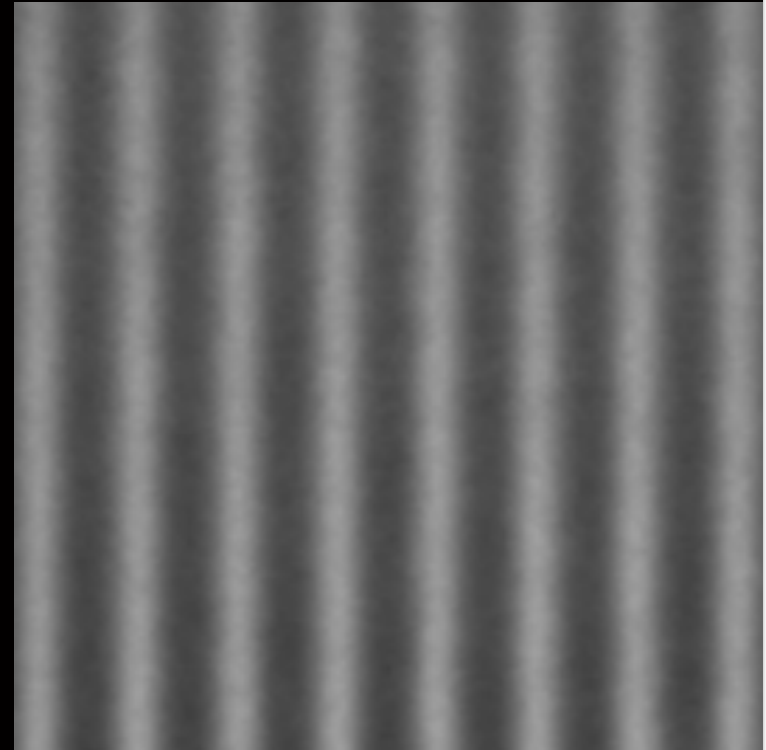
Substrate roughness experiments

2- μm

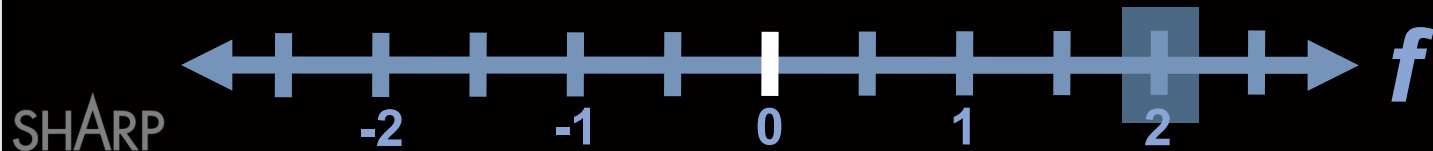
132-nm hp



IMO239379-130724-0003



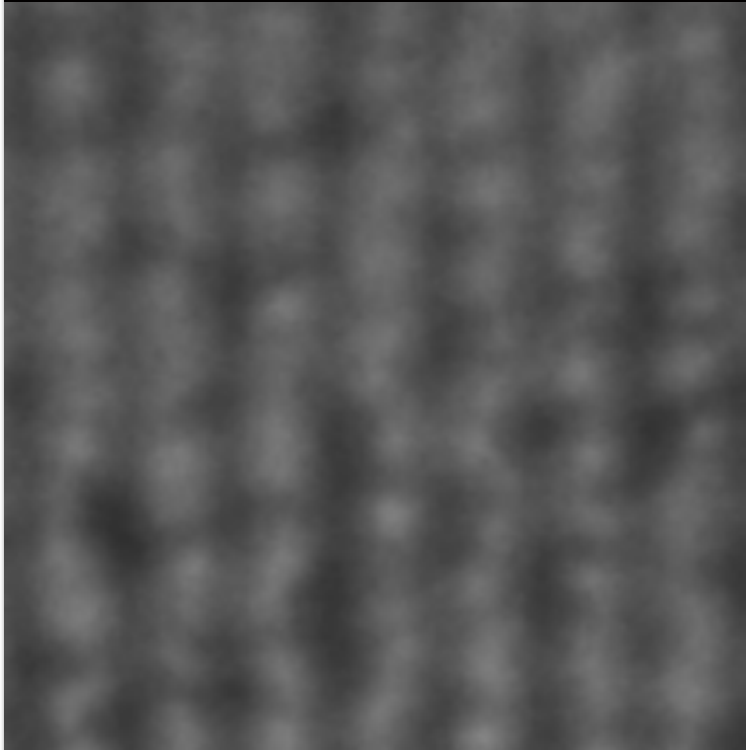
IMO239379-130724-0024



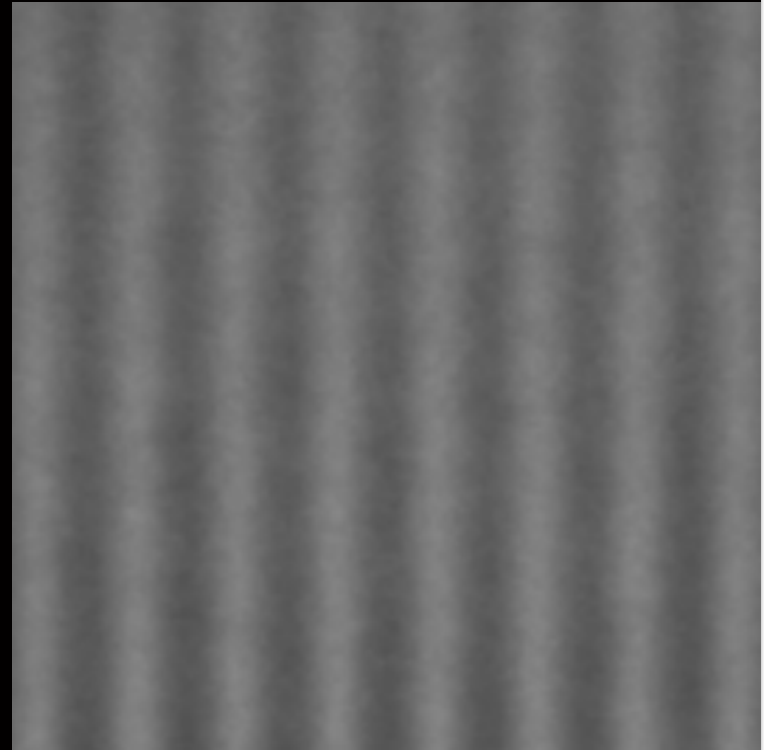
Substrate roughness experiments

2- μm

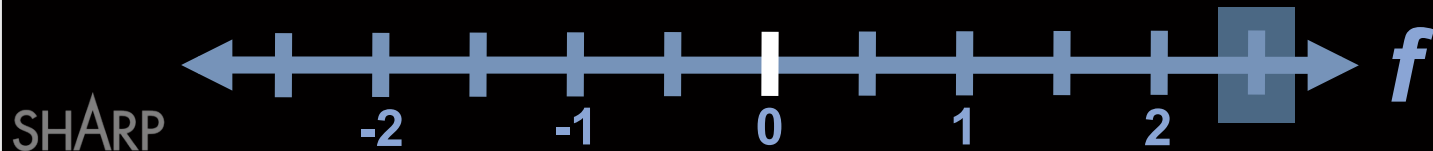
132-nm hp



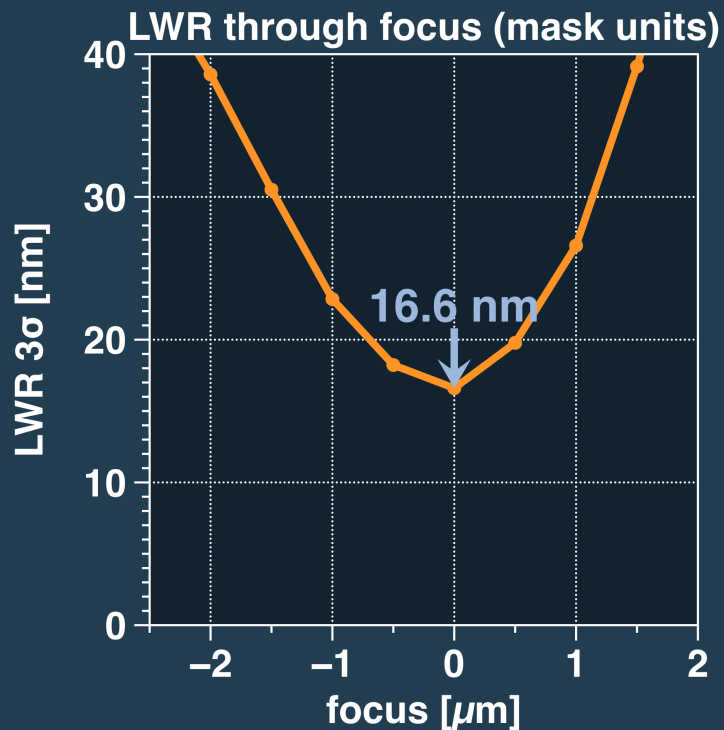
IMO239379-130724-0003



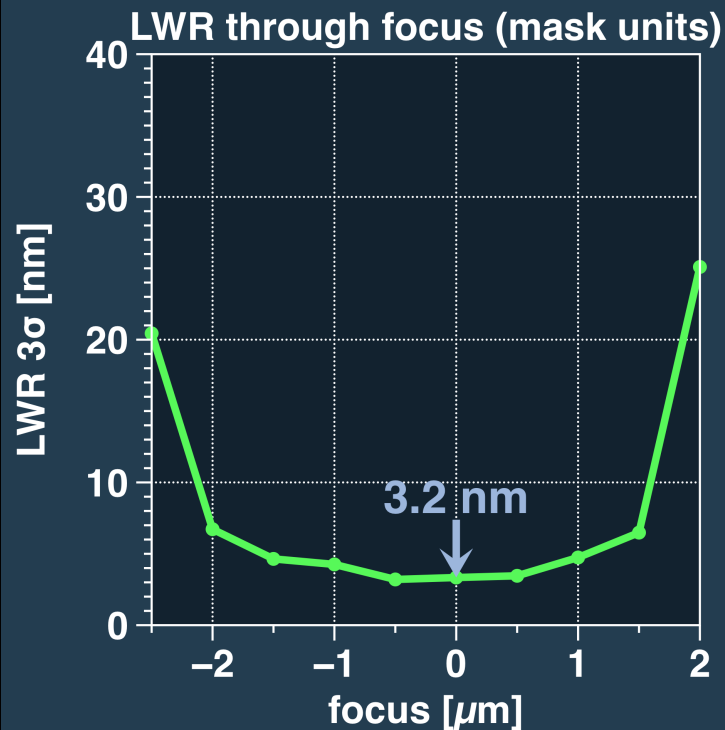
IMO239379-130724-0024



Substrate roughness experiments



IMO239379-130724-0003



IMO239379-130724-0024

SHARP:



NA:

(4x) 0.25

0.33

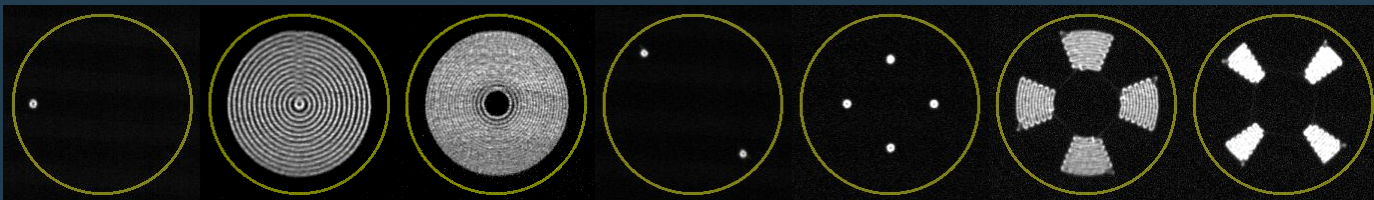
0.35

0.42

0.50

0.625

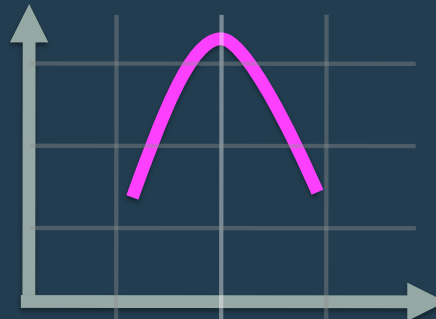
σ :



z:



λ :



13.5 nm

T:



~8 pts / h

SHARP was created by LBNL's Center for X-Ray Optics



ACKNOWLEDGMENTS

SEMATECH **Stefan Wurm, C.C. Lin, Andy Ma,
Frank Goodwin, Harry Kwon,
David Chan*, Bryan Rice**

ADC Inc. **Eric Van Every, Eric Acome**

Mirrorcle
Technologies **Vejlko Milanovic, Roger Hu**

L-3 Tinsley **Adam Magruder**

PI / MICOS /
MICRONIX **Nate Evans, Manfred Schneider**

info: sharp.lbl.gov

This work was funded by SEMATECH under Agreement No. LB08005006, and is performed under the auspices of the U.S. Department of Energy by the University of California Lawrence Berkeley National Laboratory under management and operating contract DE-AC02- 05CH11231.